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LOGINID:sssptau156cxh

PASSWORD:
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* * * * * * * * * * Welcome to STN International * * * * * * * * * *

NEWS 1		Web Page for STN Seminar Schedule - N. America
NEWS 2	APR 04	STN AnaVist, Version 1, to be discontinued
NEWS 3	APR 15	WPIDS, WPINDEX, and WPIX enhanced with new predefined hit display formats
NEWS 4	APR 28	EMBASE Controlled Term thesaurus enhanced
NEWS 5	APR 28	IMSRESEARCH reloaded with enhancements
NEWS 6	MAY 30	INPAFAMDB now available on STN for patent family searching
NEWS 7	MAY 30	DGENE, PCTGEN, and USGENE enhanced with new homology sequence search option
NEWS 8	JUN 06	EPFULL enhanced with 260,000 English abstracts
NEWS 9	JUN 06	KOREAPAT updated with 41,000 documents
NEWS 10	JUN 13	USPATFULL and USPAT2 updated with 11-character patent numbers for U.S. applications
NEWS 11	JUN 19	CAS REGISTRY includes selected substances from web-based collections
NEWS 12	JUN 25	CA/CAplus and USPAT databases updated with IPC reclassification data
NEWS 13	JUN 30	AEROSPACE enhanced with more than 1 million U.S. patent records
NEWS 14	JUN 30	EMBASE, EMBAL, and LEMBASE updated with additional options to display authors and affiliated organizations
NEWS 15	JUN 30	STN on the Web enhanced with new STN AnaVist Assistant and BLAST plug-in
NEWS 16	JUN 30	STN AnaVist enhanced with database content from EPFULL
NEWS 17	JUL 28	CA/CAplus patent coverage enhanced
NEWS 18	JUL 28	EPFULL enhanced with additional legal status information from the epoline Register
NEWS 19	JUL 28	IFICDB, IFIPAT, and IFIUDB reloaded with enhancements
NEWS 20	JUL 28	STN Viewer performance improved
NEWS 21	AUG 01	INPADOCDB and INPAFAMDB coverage enhanced
NEWS 22	AUG 13	CA/CAplus enhanced with printed Chemical Abstracts page images from 1967-1998
NEWS 23	AUG 15	CAOLD to be discontinued on December 31, 2008
NEWS 24	AUG 15	CAplus currency for Korean patents enhanced
NEWS 25	AUG 25	CA/CAplus, CASREACT, and IFI and USPAT databases enhanced for more flexible patent number searching
NEWS 26	AUG 27	CAS definition of basic patents expanded to ensure

comprehensive access to substance and sequence information

NEWS EXPRESS JUNE 27 08 CURRENT WINDOWS VERSION IS V8.3,
AND CURRENT DISCOVER FILE IS DATED 23 JUNE 2008.

NEWS HOURS STN Operating Hours Plus Help Desk Availability
NEWS LOGIN Welcome Banner and News Items
NEWS IPC8 For general information regarding STN implementation of IPC 8

Enter NEWS followed by the item number or name to see news on that specific topic.

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* * * * * * * * * * * * * * * * STN Columbus * * * * * * * * * * * * * * * * *

FILE 'HOME' ENTERED AT 15:27:54 ON 09 SEP 2008

=> file reg
COST IN U.S. DOLLARS SINCE FILE ENTRY TOTAL SESSION
FULL ESTIMATED COST 0.21 0.21

FILE 'REGISTRY' ENTERED AT 15:28:04 ON 09 SEP 2008
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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 8 SEP 2008 HIGHEST RN 1047724-15-1
DICTIONARY FILE UPDATES: 8 SEP 2008 HIGHEST RN 1047724-15-1

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.

Please note that search-term pricing does apply when conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

http://www.cas.org/support/stngen/stndoc/properties.html

=> s c9h9no2
L1 1742 C9H9NO2

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=> s c9h9no2/mf
L2          1271 C9H9NO2/MF

=> s l2 and acrylamide
         18439 ACRYLAMIDE
L3           4 L2 AND ACRYLAMIDE

=> d l-4

L3   ANSWER 1 OF 4  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   53854-70-9  REGISTRY
ED   Entered STN:  16 Nov 1984
CN   2-Propenamide, N-(2-hydroxyphenyl)-  (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN   Acrylanilide, 2'-hydroxy- (7CI)
OTHER NAMES:
CN   N-(2-Hydroxyphenyl)acrylamide
CN   N-Acryloyl-o-aminophenol
MF   C9 H9 N O2
CI   COM
LC   STN Files:   BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, USPATFULL
         (*File contains numerically searchable property data)
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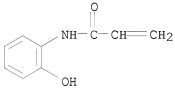


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**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**

              11 REFERENCES IN FILE CA (1907 TO DATE)
              11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
               1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L3   ANSWER 2 OF 4  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   34443-04-4  REGISTRY
ED   Entered STN:  16 Nov 1984
CN   2-Propenamide, N-(4-hydroxyphenyl)-  (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN   Acrylanilide, 4'-hydroxy- (6CI, 8CI)
OTHER NAMES:
CN   N-(4-Hydroxyphenyl)-2-propenamide
CN   N-(p-Hydroxyphenyl) acrylamide
CN   p-Acrylamidophenol
CN   p-Acryloylaminophenol
MF   C9 H9 N O2
CI   COM
LC   STN Files:   BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CHEMLIST,
       RTECS*, USPAT2, USPATFULL
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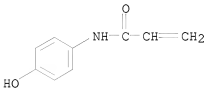
(*File contains numerically searchable property data)
Other Sources: EINECS**
(**Enter CHEMLIST File for up-to-date regulatory information)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

26 REFERENCES IN FILE CA (1907 TO DATE)
26 REFERENCES IN FILE CAPLUS (1907 TO DATE)
2 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L3 ANSWER 3 OF 4 REGISTRY COPYRIGHT 2008 ACS on STN
RN 33870-37-0 REGISTRY
ED Entered STN: 16 Nov 1984
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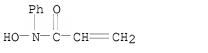
OTHER CA INDEX NAMES:
CN Acrylohydroxamic acid, N-phenyl- (8CI)
OTHER NAMES:
CN N-Hydroxy-N-phenylacrylamide
CN N-Hydroxyacrylanilide
MF C9 H9 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAPLUS, CASREACT, GMELIN*, TOXCENTER, USPATFULL
(*File contains numerically searchable property data)

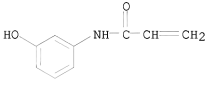


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

13 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
13 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L3 ANSWER 4 OF 4 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13040-21-6 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(3-hydroxyphenyl)- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylanilide, 3'-hydroxy- (7CI, 8CI)
OTHER NAMES:

CN N-(3-Hydroxyphenyl)acrylamide
CN NSC 122233
DR 194091-51-5
MF C9 H9 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, IFICDB, IFIPAT, IFIUDB, TOXCENTER, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

11 REFERENCES IN FILE CA (1907 TO DATE)
11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> FIL REGISTRY

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	28.05	28.26

FILE 'REGISTRY' ENTERED AT 15:34:11 ON 09 SEP 2008
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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 8 SEP 2008 HIGHEST RN 1047724-15-1
DICTIONARY FILE UPDATES: 8 SEP 2008 HIGHEST RN 1047724-15-1

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.

Please note that search-term pricing does apply when conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

http://www.cas.org/support/stngen/stndoc/properties.html

```
=> S 53854-70-9/RN

L4            1 53854-70-9/RN

=> SET NOTICE 1 DISPLAY

NOTICE SET TO 1 U.S. DOLLAR FOR DISPLAY COMMAND
SET COMMAND COMPLETED

=> D L4 SQIDE 1-

YOU HAVE REQUESTED DATA FROM 1 ANSWERS - CONTINUE? Y/(N):n

=> SET NOTICE LOGIN DISPLAY

NOTICE SET TO OFF  FOR DISPLAY COMMAND
SET COMMAND COMPLETED

=>

=> s  194091-51-5
L5            1 194091-51-5
                (194091-51-5/RN)

=> s  194091-51-5/crn
L6            0 194091-51-5/CRN

=> s  34443-04-4
L7            1 34443-04-4
                (34443-04-4/RN)

=> s  34443-04-4/crn
L8           53 34443-04-4/CRN

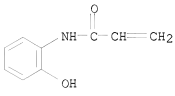
=> s  53854-70-9
L9            1 53854-70-9
                (53854-70-9/RN)

=> s  53854-70-9/crn
L10          15 53854-70-9/CRN

=> d l9; d 17;d 15

L9   ANSWER 1 OF 1  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   53854-70-9  REGISTRY
ED   Entered STN:  16 Nov 1984
CN   2-Propenamide, N-(2-hydroxyphenyl)-  (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN   Acrylanilide, 2'-hydroxy- (7CI)
OTHER NAMES:
CN   N-(2-Hydroxyphenyl)acrylamide
CN   N-Acryloyl-o-aminophenol
MF   C9 H9 N O2
```

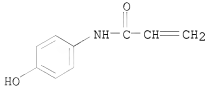
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

11 REFERENCES IN FILE CA (1907 TO DATE)
11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L7 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 34443-04-4 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(4-hydroxyphenyl)- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylanilide, 4'-hydroxy- (6CI, 8CI)
OTHER NAMES:
CN N-(4-Hydroxyphenyl)-2-propenamide
CN N-(p-Hydroxyphenyl) acrylamide
CN p-Acrylamidophenol
CN p-Acryloylaminophenol
MF C9 H9 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, RTECS*, USPAT2, USPATFULL
(*File contains numerically searchable property data)
Other Sources: EINECS**
(**Enter CHEMLIST File for up-to-date regulatory information)

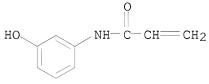


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

26 REFERENCES IN FILE CA (1907 TO DATE)

26 REFERENCES IN FILE CAPLUS (1907 TO DATE)
2 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L5 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13040-21-6 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(3-hydroxyphenyl)- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylanilide, 3'-hydroxy- (7CI, 8CI)
OTHER NAMES:
CN N-(3-Hydroxyphenyl)acrylamide
CN NSC 122233
DR 194091-51-5
MF C9 H9 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, IFICDB, IFIPAT, IFIUDB, TOXCENTER, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

11 REFERENCES IN FILE CA (1907 TO DATE)
11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> file caplus

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	8.30	36.56

FILE 'CAPLUS' ENTERED AT 15:37:04 ON 09 SEP 2008
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FILE COVERS 1907 - 9 Sep 2008 VOL 149 ISS 11
FILE LAST UPDATED: 8 Sep 2008 (20080908/ED)

Caplus now includes complete International Patent Classification (IPC) reclassification data for the second quarter of 2008.

Effective October 17, 2005, revised CAS Information Use Policies apply. They are available for your review at:

http://www.cas.org/legal/infopolicy.html

```
=> d his

     (FILE 'HOME' ENTERED AT 15:27:54 ON 09 SEP 2008)

     FILE 'REGISTRY' ENTERED AT 15:28:04 ON 09 SEP 2008
L1         1742 S C9H9NO2
L2         1271 S C9H9NO2/MF
L3            4 S L2 AND ACRYLAMIDE

     FILE 'REGISTRY' ENTERED AT 15:34:11 ON 09 SEP 2008
L4            1 S 53854-70-9/RN
                SET NOTICE 1 DISPLAY
                SET NOTICE LOGIN DISPLAY
L5            1 S  194091-51-5
L6            0 S  194091-51-5/CRN
L7            1 S  34443-04-4
L8           53 S  34443-04-4/CRN
L9            1 S  53854-70-9
L10          15 S  53854-70-9/CRN

     FILE 'CAPLUS' ENTERED AT 15:37:04 ON 09 SEP 2008

=> s l8 or l10
            63 L8
             6 L10
L11         67 L8 OR L10

=> s l11 and photo?
       1604210 PHOTO?
L12         46 L11 AND PHOTO?

=> d all 1-46

L12  ANSWER 1 OF 46  CAPLUS  COPYRIGHT 2008 ACS on STN
AN   2007:192679  CAPLUS
DN   146:283590
ED   Entered STN:  22 Feb 2007
TI   Photosensitive resin composition for forming optical waveguide,
     optical waveguide, and method for forming optical waveguide pattern
```

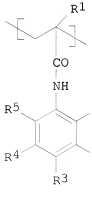
IN Maeda, Katsumi; Nakano, Kaichiro; Kubo, Masahiro
PA NEC Corporation, Japan
SO U.S. Pat. Appl. Publ., 15pp.
CODEN: USXXCO
DT Patent
LA English
INCL 385141000; 385129000
CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
Section cross-reference(s): 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 20070041698	A1	20070222	US 2006-488864	20060719
	JP 2007052120	A	20070301	JP 2005-235944	20050816
PRAI	JP 2005-235944	A	20050816		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 20070041698	INCL	385141000; 385129000
	IPCI	G02B0006-00 [I,A]
	IPCR	G02B0006-00 [I,C]; G02B0006-00 [I,A]
	NCL	385/141.000; 385/129.000
JP 2007052120	IPCI	G03F0007-038 [I,A]; G02B0006-12 [I,A]; G02B0006-13 [I,A]; G03F0007-004 [I,A]; C08F0020-58 [I,A]; C08F0020-00 [I,C*]
	IPCR	G03F0007-038 [I,C]; G03F0007-038 [I,A]; C08F0020-00 [I,C]; C08F0020-58 [I,A]; G02B0006-12 [I,C]; G02B0006-12 [I,A]; G02B0006-13 [I,C]; G02B0006-13 [I,A]; G03F0007-004 [I,C]; G03F0007-004 [I,A]
	FTERM	2H025/AA03; 2H025/AA09; 2H025/AA10; 2H025/AB14; 2H025/AC01; 2H025/AD01; 2H025/BD23; 2H025/BE00; 2H025/CB30; 2H025/CB45; 2H025/CC08; 2H025/CC17; 2H147/EA13C; 2H147/EA16A; 2H147/EA16B; 2H147/FA17; 2H147/FB04; 2H147/FE02; 2H147/FF06; 2H147/FF09; 4J100/AL08Q; 4J100/AM21P; 4J100/BA03P; 4J100/BC43P; 4J100/BC54Q; 4J100/CA04; 4J100/DA01; 4J100/DA04; 4J100/JA37

GI



I

AB A photosensitive resin composition for forming an optical waveguide comprises, at least, a polymer comprising at least one repeating structural unit represented by I [R1= H or Me group; R2-5 = H, halo or C1-4 alkyl], and a photoacid generator. This composition can form an optical waveguide pattern with excellent shape precision and at a low cost, and an optical waveguide of a low propagation loss.
ST photosensitive resin optical waveguide
IT Optical waveguides
(photosensitive resin composition for forming optical waveguide, optical waveguide, and method for forming optical waveguide pattern)
IT 95-55-6, o-Aminophenol 814-68-6, Acryloyl chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(photosensitive resin composition for forming optical waveguide, optical waveguide, and method for forming optical waveguide pattern)
IT 155599-69-2P 925909-92-8P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photosensitive resin composition for forming optical waveguide, optical waveguide, and method for forming optical waveguide pattern)
IT 2386-87-0, 3,4-Epoxycyclohexylmethyl 3,4-epoxycyclohexanecarboxylate 193756-79-5
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin composition for forming optical waveguide, optical waveguide, and method for forming optical waveguide pattern)

L12 ANSWER 2 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2006:1206271 CAPLUS
DN 145:489681
ED Entered STN: 17 Nov 2006
TI (Meth)acrylamide derivatives for chemically amplified photosensitive resin polymers and compositions with good crack resistance and adhesion
IN Maeda, Katsumi; Nakano, Kaichirou
PA NEC Corporation, Japan
SO PCT Int. Appl., 48pp.
CODEN: PIXXD2
DT Patent
LA Japanese
CC 35-2 (Chemistry of Synthetic High Polymers)
Section cross-reference(s): 38, 74
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 2006121150	A1	20061116	WO 2006-JP309540	20060512

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ,

CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

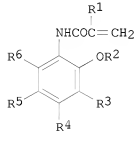
	CN 101175777	A	20080507	CN 2006-80016467	20071113
PRAI	JP 2005-141070	A	20050513		
	WO 2006-JP309540	W	20060512		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 2006121150	IPCI	C08F0020-58 [I,A]; C08F0020-00 [I,C*]; C07C0233-27 [I,A]; C07C0233-75 [I,A]; C07C0233-00 [I,C*]; C07D0309-10 [I,A]; C07D0309-00 [I,C*]; C07F0007-18 [I,A]; C07F0007-00 [I,C*]; G03F0007-004 [I,A]; G03F0007-039 [I,A]; G03F0007-075 [I,A]; G03F0007-40 [I,A]
	IPCR	C08F0020-00 [I,C]; C08F0020-58 [I,A]; C07C0233-00 [I,C]; C07C0233-27 [I,A]; C07C0233-75 [I,A]; C07D0309-00 [I,C]; C07D0309-10 [I,A]; C07F0007-00 [I,C]; C07F0007-18 [I,A]; G03F0007-004 [I,C]; G03F0007-004 [I,A]; G03F0007-039 [I,C]; G03F0007-039 [I,A]; G03F0007-075 [I,C]; G03F0007-075 [I,A]; G03F0007-40 [I,C]; G03F0007-40 [I,A]
	ECLA	G03F007/039C; C07C233/27; C07D309/10; C07F007/08D4H4H
CN 101175777	IPCI	C08F0020-58 [I,A]; C08F0020-00 [I,C*]; C07C0233-27 [I,A]; C07C0233-75 [I,A]; C07C0233-00 [I,C*]; C07D0309-10 [I,A]; C07D0309-00 [I,C*]; C07F0007-18 [I,A]; C07F0007-00 [I,C*]; G03F0007-004 [I,A]; G03F0007-039 [I,A]; G03F0007-075 [I,A]; G03F0007-40 [I,A]

OS MARPAT 145:489681

GI



I

AB Title (meth)acrylamide compds. are represented by I, wherein R1 = H or Me group; R2 = acid-decomposable group; and R3, R4, R5, R6 = independently H, halogene, or C1-4 alkyl group. Thus, 20 g o-aminophenol and 17.42 g acryloyl chloride were reacted to give N-(2-hydroxyphenyl)acrylamide, 20 g of which was reacted with 12.75 g chloromethyl Et ether to give N-(2-ethoxymethoxyphenyl)acrylamide, 9 g of which was polymerized with 12.2 g

N-(2-hydroxyphenyl)acrylamide in the presence of AIBN for 6 h undere a reflux condition to give a copolymer with Mw 35,800 and polydispersity 3.72, 6 g of the resulting copolymer was mixed with NAI 101 (photo acid generator) 0.144, a dissoln. inhibitor 1.2, and γ-butyrolactone 11.75 g, applied on a silicon wafer, dried at 100° for 20 min, irradiated through a photomask, baked at 90° for 10 min, developed, washed, irradiated , baked at 110° for 30 min and 220° for 1 h to form a benzoxazole ring to give a heat-resistant pattern, showing good crack resistance and adhesion.

ST methacrylamide deriv chem amplified photosensitive resin polymer compn; crack resistance adhesion; aminophenol acryloyl chloride chloromethyl ethyl ether reactant; ethoxymethoxyphenylacrylamide monomer prepn; hydroxyphenylacrylamide ethoxymethoxyphenylacrylamide copolymer prepn

IT Positive photoresists
((meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT Monomers
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
(Reactant or reagent)
((meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT Acrylic polymers, uses
RL: TEM (Technical or engineered material use); USES (Uses)
((meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT Siloxanes (nonpolymeric)
RL: MOA (Modifier or additive use); USES (Uses)
(adhesion improver; (meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT 155599-69-2P 914774-58-6P 914774-59-7P
914774-60-0P 914774-61-1P 914774-62-2P
914774-63-3P 914774-66-6P
RL: CPS (Chemical process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
((meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT 91859-19-7P 349607-63-2P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(adhesion improver; (meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT 914774-64-4P 914774-65-5P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(dissoln. inhibitor; (meth)acrylamide derivs. for chemical amplified photosensitive resin polymers and compns. with good crack resistance and adhesion)

IT 15457-49-5P 144080-77-3P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT

(Reactant or reagent)
(intermediate in dissoln. inhibitor preparation; (meth)acrylamide derivs.
for chemical amplified photosensitive resin polymers and compns.
with good crack resistance and adhesion)
IT 53854-70-9P, N-(2-Hydroxyphenyl)acrylamide
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
(Reactant or reagent)
(intermediate or monomer; preparation of (meth)acrylamide derivs. for chemical
amplified photosensitive resin polymers and compns. with good
crack resistance and adhesion)
IT 914774-57-5P
RL: CPS (Chemical process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
(intermediate; (meth)acrylamide derivs. for chemical amplified
photosensitive resin polymers and compns. with good crack
resistance and adhesion)
IT 914774-54-2P 914774-55-3P 914774-56-4P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
(Reactant or reagent)
(monomer; preparation of (meth)acrylamide derivs. for chemical amplified
photosensitive resin polymers and compns. with good crack
resistance and adhesion)
IT 85-44-9, Phthalic anhydride 2469-55-8, 1,3-Bis(3-aminopropyl)tetramethyldisiloxane
RL: RCT (Reactant); RACT (Reactant or reagent)
(reactant in adhesion improve preparation; (meth)acrylamide derivs. for
chemical amplified photosensitive resin polymers and compns.
with good crack resistance and adhesion)
IT 98-88-4, Benzoyl chloride 99-63-8, Isophthaloyl chloride 83558-87-6, 2,2-Bis(3-amino-4-hydroxyphenyl)hexafluoropropane
RL: RCT (Reactant); RACT (Reactant or reagent)
(reactant in dissoln. inhibitor preparation; (meth)acrylamide derivs. for
chemical amplified photosensitive resin polymers and compns.
with good crack resistance and adhesion)
IT 95-55-6, o-Aminophenol 109-92-2, Ethylvinyl ether 814-68-6, 2-Propenoyl chloride 3188-13-4, Chloromethyl ethyl ether 3331-55-3, N-(2-Hydroxyphenyl)methacrylamide
RL: RCT (Reactant); RACT (Reactant or reagent)
(reactant; preparation of (meth)acrylamide derivs. for chemical amplified
photosensitive resin polymers and compns. with good crack
resistance and adhesion)
RE.CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Fuji Photo Film Co Ltd; JP 2004219667 A 2004 CAPLUS
(2) Fuji Photo Film Co Ltd; JP 2004279662 A 2004 CAPLUS
(3) Konica Corp; JP 06-250448 A 1994 CAPLUS

L12 ANSWER 3 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2004:330792 CAPLUS
DN 140:347591
ED Entered STN: 23 Apr 2004
TI Photosensitive resin composition and presensitized lithographic plate
IN Sorori, Tadahiro; Iwato, Kaoru; Endo, Akihiro; Oshima, Yasuhito
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 52 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2004125985	A	20040422	JP 2002-287144	20020930
PRAI JP 2002-287144		20020930		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2004125985	ICM	G03F007-004
	ICS	G03F007-00
	IPCI	G03F0007-004 [ICM,7]; G03F0007-00 [ICS,7]
	IPCR	G03F0007-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-004 [I,A]; G03F0007-004 [I,C*]
	FTERM	2H025/AA04; 2H025/AC08; 2H025/AD01; 2H025/AD03; 2H025/CB14; 2H025/CB29; 2H025/CC11; 2H025/CC20; 2H025/FA10; 2H025/FA17; 2H096/AA06; 2H096/BA01; 2H096/BA09; 2H096/EA04; 2H096/EA23; 2H096/GA08

AB The composition contains (A) an alkali-soluble resin, (B) a light-to-heat converting agent, and (C) R3YCOCR1HCOR2 (R1-2 = H, monovalent substituent;
R3 = polymer residue; Y = linkage). The material is suited for direct platemaking using high power laser beam, and gives images with high contrast and development latitude.
ST photosensitive resin compn presensitized lithog plate; acrylic polymer ketone group photosensitive resin compn
IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak; photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT Photoimaging materials
(photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT Lithographic plates
(presensitized; photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT 27029-76-1, PR 54046
RL: TEM (Technical or engineered material use); USES (Uses)

(PR 54046; photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT 69415-30-1 134127-48-3 205744-92-9
RL: TEM (Technical or engineered material use); USES (Uses)
(light-to-heat converting agent; photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT 27901-88-8 65188-70-7 146245-53-6 681007-75-0 681007-76-1 681007-77-2 681007-79-4 681007-81-8 681007-83-0
RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)
IT 26284-14-0, Butyl methacrylate-methacrylic acid copolymer 37916-03-3, Isobutyl methacrylate-methacrylic acid copolymer 141634-00-6, Acrylonitrile-N-(p-aminosulfonylphenyl)methacrylamide-methyl methacrylate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin composition containing polymer with ketone groups for presensitized lithog. plate)

L12 ANSWER 4 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2002:538184 CAPLUS
DN 137:116969
ED Entered STN: 19 Jul 2002
TI Positive image-forming material
IN Kunita, Kazuto; Sato, Kenichiro
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 115 pp.
CODEN: EPXXDW
DT Patent
LA English
IC ICM G03F007-039
ICS G03F007-023; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1223467	A2	20020717	EP 2002-237	20020114
	EP 1223467	A3	20030205		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
	JP 2002214785	A	20020731	JP 2001-5178	20010112
	JP 2002309057	A	20021023	JP 2001-115595	20010413
	CN 1365025	A	20020821	CN 2002-103198	20020112
	US 20030057610	A1	20030327	US 2002-43135	20020114
	US 6716565	B2	20040406		
PRAI	JP 2001-5178	A	20010112		
	JP 2001-115595	A	20010413		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 1223467	ICM	G03F007-039
	ICS	G03F007-023; G03F007-004

	IPCI	G03F0007-039 [ICM,6]; G03F0007-023 [ICS,6]; G03F0007-004 [ICS,6]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-36 [I,C*]; B41M0005-36 [I,A]; G03F0007-00 [N,C*]; G03F0007-00 [N,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-038 [N,C*]; G03F0007-038 [N,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	ECLA	B41C001/10A; B41M005/36S; G03F007/021P; G03F007/023P; G03F007/039
JP 2002214785	IPCI	G03F0007-033 [ICM,7]; C08F0020-00 [ICS,7]; G03F0007-00 [ICS,7]; G03F0007-039 [ICS,7]
	IPCR	G03F0007-033 [I,C*]; G03F0007-033 [I,A]; C08F0020-00 [I,C*]; C08F0020-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
JP 2002309057	IPCI	C08L0033-04 [ICM,7]; C08L0033-00 [ICM,7,C*]; C08K0005-00 [ICS,7]; G03F0007-00 [ICS,7]; G03F0007-039 [ICS,7]; H01L0021-027 [ICS,7]; H01L0021-02 [ICS,7,C*]
	IPCR	G03F0007-039 [I,C*]; G03F0007-039 [I,A]; C08K0005-00 [I,C*]; C08K0005-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-04 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]
CN 1365025	IPCI	G03F0007-004 [ICM,7]; G03F0070-39 [ICS,7]; G03F0070-38 [ICS,7]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-36 [I,C*]; B41M0005-36 [I,A]; G03F0007-00 [N,C*]; G03F0007-00 [N,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-038 [N,C*]; G03F0007-038 [N,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
US 20030057610	IPCI	G03F0007-039 [ICM,7]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-36 [I,C*]; B41M0005-36 [I,A]; G03F0007-00 [N,C*]; G03F0007-00 [N,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-038 [N,C*]; G03F0007-038 [N,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	NCL	264/401.000; 430/001.000; 430/270.100; 430/285.100; 430/287.100; 430/302.000; 430/326.000; 430/944.000; 430/945.000; 526/245.000; 526/257.000; 526/258.000; 526/266.000; 526/274.000; 526/280.000; 526/285.000; 526/286.000; 526/292.100; 526/296.000; 526/297.000; 430/905.000
	ECLA	B41C001/10A; B41M005/36S; G03F007/021P; G03F007/023P; G03F007/039; S03F; S03F; S03F; S03F; S03F; S03F

AB The present invention relates to a pos. image-forming material favorably usable as the so-called direct lithog. printing plate material capable of plate-making directly form digital signals in a computer with various kinds of lasers, or suitably usable as photoresist materials. The pos. image-forming material comprises a resin including a repeating unit corresponding to a specific monomer having an α-heteromethyl structure: RaRbX1C-C(=C)Q1 (Q1 = cyano (CN), COX2; X1,2 = hetero atom, halogen atom; Ra,b = H, halogen atom, cyano group, organic residual group).

ST lithog printing plate photoresist resin acid generator
IT Holography
Lithographic plates
Photoresists
(pos. image-forming material for)
IT 201024-57-9 384850-16-2
RL: TEM (Technical or engineered material use); USES (Uses)
(IR absorbing dye; pos. image-forming material for lithog printing plate containing)
IT 79723-43-6 125604-88-8 304882-18-6
RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator; pos. image-forming material for lithog printing plate containing)
IT 52411-04-8 68900-98-1 84563-49-5 101491-20-7 120504-13-4
127326-57-2 134127-48-3 442900-31-4 442900-32-5
RL: TEM (Technical or engineered material use); USES (Uses)
(dissoln. inhibitor; pos. image-forming material for lithog printing plate containing)
IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 409332-98-5
409332-99-6 409333-02-4 442899-98-1 442899-99-2 442900-01-8
442900-02-9 442900-04-1 442900-05-2 442900-06-3
442900-07-4 442900-09-6 442900-11-0 442900-12-1 442900-13-2
442900-15-4 442900-17-6 442900-18-7 442900-19-8 442900-20-1
442900-22-3 442900-24-5 442900-26-7 442900-28-9 442900-30-3
RL: TEM (Technical or engineered material use); USES (Uses)
(resin; pos. image-forming material for lithog printing plate containing)

L12 ANSWER 5 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2002:532390 CAPLUS
DN 137:325939
ED Entered STN: 17 Jul 2002
TI Self-assembly of homopolymer and copolymers of N-4-hydroxyphenyl-acrylamide with diazoresin via H-bonding attraction
AU Yang, Zhaohui; Cao, Tingbing; Chen, Jinyu; Cao, Weixiao
CS Peking University, College of Chemistry and Molecular Engineering, Beijing, 100871, Peop. Rep. China
SO European Polymer Journal (2002), 38(10), 2077-2082
CODEN: EUPJAG; ISSN: 0014-3057
PB Elsevier Science Ltd.
DT Journal
LA English
CC 37-3 (Plastics Manufacture and Processing)
AB A kind of photoactive multilayer ultrathin films was fabricated via H-bonding attraction from hydroxyphenyl containing polymers as H-donor and diazoresin (DR) as H-acceptor by means of a self-assembly technique. The layer-by-layer deposition of two components is monitored spectrometrically and shows that the UV-VIS absorbance of the film increases linearly both at 250 nm (absorption of benzene nucleus) and at 383 nm (absorption of diazonium group), which indicates that the fabrication proceeds regularly.
The nature of H-bonding between layers was verified by the determination of IR

spectra of the film fabricated directly on a CaF2 wafer. The stability of the films toward polar solvents increases dramatically after UV irradiation of the films. It was confirmed provisionally that the bond nature between the layers of the film changes from H-bonding to covalent bonding under UV irradiation The photodecompn. of the -N2+ groups of the film under UV light follows first order reaction kinetics and a mechanism of the photoreaction has been tentatively proposed.
ST hydroxyphenylacrylamide polymer diazoresin self assembly hydrogen bonding
IT Multilayers
(photoactive; self-assembly of homopolymer and copolymers of hydroxyphenyl-acrylamide with diazoresin via H-bonding attraction)
IT Hydrogen bond
Light-sensitive materials
Self-assembly
(self-assembly of homopolymer and copolymers of hydroxyphenyl-acrylamide with diazoresin via H-bonding attraction)
IT 75-77-4, Trimethylsilyl chloride, reactions 123-30-8, 4-Aminophenol 814-68-6, Acryloyl chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(in preparation of hydroxyphenylacrylamide)
IT 34443-04-4P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation and polymerization of)
IT 29989-17-1P 155599-65-8P 428868-49-9P
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); SPN (Synthetic preparation); PREP (Preparation); PROC (Process)
(self-assembly of homopolymer and copolymers of hydroxyphenyl-acrylamide with diazoresin via H-bonding attraction)
RE.CNT 15 THERE ARE 15 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Ariga, K; J Am Chem Soc 1997, V119, P2224 CAPLUS
(2) Bertrand, P; Macromol Rapid Commun 2000, V21, P319 CAPLUS
(3) Cao, S; Polym Int 1998, V45, P142 CAPLUS
(4) Chen, J; Chem Commun 1999, P1711 CAPLUS
(5) Decher, G; Ber Busenges Phys Chem 1991, V95, P1430 CAPLUS
(6) Decher, G; Biosensor Bioelectron 1994, V9, P677 CAPLUS
(7) Decher, G; Science 1997, V277, P1232 CAPLUS
(8) Gallardo, A; Polymer 1993, V34, P395
(9) Kleiufeld, E; Science 1994, V265, P370
(10) Laschewsky, A; Ber Bunsen-Ges, Phys Chem 1996, V100, P1033 CAPLUS
(11) Lvov, Y; J Am Chem Soc 1995, V117, P6117 CAPLUS
(12) Ritter, H; Markromol Chem 1986, V187, P901
(13) Shimazaki, Y; Langmuir 1997, V13, P1385 CAPLUS
(14) Stockton, W; Macromolecules 1997, V30, P2117
(15) Wang, J; Macromol Rapid Commun 1997, V18, P509

L12 ANSWER 6 OF 46 CAPLUS
AN 2002:216335 CAPLUS
DN 136:270603

ED Entered STN: 22 Mar 2002
TI Presensitized lithographic plates containing acrylic binder polymers with small residual monomers
IN Tan, Shiro; Fujita, Kazuo
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-033
ICS C08F220-44; C08F220-48; G03F007-00; G03F007-022; C08F220-12; C08F220-56
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2002082435	A	20020322	JP 2000-272571	20000908
PRAI JP 2000-272571		20000908		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2002082435	ICM	G03F007-033
	ICS	C08F220-44; C08F220-48; G03F007-00; G03F007-022; C08F220-12; C08F220-56
	IPCI	G03F0007-033 [ICM,7]; C08F0220-44 [ICS,7]; C08F0220-48 [ICS,7]; G03F0007-00 [ICS,7]; G03F0007-022 [ICS,7]; C08F0220-12 [ICS,7]; C08F0220-56 [ICS,7]; C08F0220-00 [ICS,7,C*]
	IPCR	G03F0007-033 [I,C*]; G03F0007-033 [I,A]; C08F0220-00 [I,C*]; C08F0220-44 [I,A]; C08F0220-48 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]

AB The plates possess photosensitive layers containing (A) alkali-developable vinylic polymers and (B) o-naphthoquinonediazide, where A contain acrylonitrile (I) and H2C:CR1COX1R2Y1nZ1m [X1 = O, NR3 [R3 = H, C1-12 (cyclo)alkyl, aryl(alkyl)]; R1 = H, Me; R2 = single bond, bivalent organic group; Y1 = arylene; Z1 = acidic-H-bearing group; n = 0, 1; m ≥ 1 integer] and satisfying free I content ≤1% (based on the polymer solids). The plates show excellent wear and chemical resistance and printing durability.
ST presensitized lithog plate durability acrylic binder; acrylonitrile copolymd acrylic binder PS plate; wear resistance stability presensitized lithog plate
IT Lithographic plates
(presensitized; presensitized lithog. plates containing sp. acrylic binders and showing good wear and chemical resistance)
IT 169202-35-1P 263716-62-7P, Acrylonitrile-2-[N'-(4-hydroxyphenyl)ureido]ethyl methacrylate-methyl methacrylate copolymer 326820-82-0P 326820-92-2P 334978-35-7P, Acrylonitrile-N-(p-aminosulfonylphenyl)methacrylamide-N-isopropylacrylamide-methyl

methacrylate copolymer
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)
(binders; presensitized lithog. plates containing sp. acrylic binders and
showing good wear and chemical resistance)
IT 53208-22-3, o-Naphthoquinonediazide
RL: CAT (Catalyst use); USES (Uses)
(presensitized lithog. plates containing sp. acrylic binders and showing
good wear and chemical resistance)

L12 ANSWER 7 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2000:863745 CAPLUS
DN 134:35033
ED Entered STN: 11 Dec 2000
TI Photoresist composition suitable for lithographic printing plate
IN Furukawa, Akira; Doi, Kunihiro
PA Mitsubishi Paper Mills, Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F007-00; G03F007-032
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2000338657	A	20001208	JP 1999-152510	19990531
PRAI JP 1999-152510		19990531		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000338657	ICM	G03F007-004
	ICS	G03F007-00; G03F007-032
	IPCI	G03F0007-004 [ICM,7]; G03F0007-00 [ICS,7]; G03F0007-032 [ICS,7]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]

AB The photoresist composition comprises a sulfonylazido compound, a dye having absorption from visible to near IR, and a binder containing phenolic OH group. The composition shows excellent sensitivity and storage stability.
ST photoresist compn lithog printing plate
IT Polyvinyl acetals
RL: TEM (Technical or engineered material use); USES (Uses)
(hydroxybenzals; in photoresist composition suitable for lithog. printing plate)
IT Photoresists

(photoresist composition suitable for lithog. printing plate)
IT Lithographic plates
(presensitized; photoresist composition suitable for lithog. printing plate)
IT 7456-69-1, 1,5-Naphthalenedisulfonyl diazide 9003-39-8, Poly(vinyl pyrrolidone) 24979-70-2, Poly(4-vinylphenol) 25053-88-7, Formaldehyde-4-methylphenol copolymer 28777-87-9D, Hydroxybenzaldehyde, polyvinyl acetal derivs. 55281-19-1 134127-48-3 311817-52-4, 2,6-Naphthalenedisulfonyl diazide 311817-53-5 311817-54-6 311817-55-7 311817-56-8 311817-58-0 311817-59-1
RL: TEM (Technical or engineered material use); USES (Uses)
(in photoresist composition suitable for lithog. printing plate)

L12 ANSWER 8 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2000:420877 CAPLUS
DN 133:51217
ED Entered STN: 23 Jun 2000
TI Photosensitive element for lithographic plate preparation
IN Fujita, Kazuo; Kawamura, Koichi; Watanabe, Noriaki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 31 pp.
CODEN: EPXXDW
DT Patent
LA English
IC ICM G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 1011030	A1	20000621	EP 1999-124870	19991216
EP 1011030	B1	20020417		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2000181053	A	20000630	JP 1998-357362	19981216
PRAI JP 1998-357362	A	19981216		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 1011030	ICM	G03F007-004
	IPCI	G03F0007-004 [ICM,6]
	IPCR	B41N0001-12 [I,C*]; B41N0001-14 [I,A]; C09D0133-14 [I,C*]; C09D0133-14 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]
	ECLA	G03F007/004S
JP 2000181053	IPCI	G03F0007-00 [ICM,7]; B41N0001-14 [ICS,7]; B41N0001-12 [ICS,7,C*]; C09D0133-14 [ICS,7]; G03F0007-004 [ICS,7]; G03F0007-032 [ICS,7]
	IPCR	B41N0001-12 [I,C*]; B41N0001-14 [I,A]; C09D0133-14 [I,C*]; C09D0133-14 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]

AB A photosensitive element for lithog. plate preparation is obtained by coating a support with a solution containing a fluorine-containing copolymer, a

photosensitive compound, a binder, and an organic solvent and drying, wherein the fluorine-containing copolymer is obtained by dissolving a copolymer having 1-80% by weight of a fluorinated (meth)acrylate as a constituent unit in a solvent, purifying the fluorinated (meth)acrylate-containing copolymer by bringing the resulting solution into contact with an inorg. adsorbent containing 80% by weight or more of an oxide of silicon, an oxide of aluminum, or a mixture thereof, bringing the resulting solution into contact with a synthetic adsorbent comprising a (modified) styrene-divinylbenzene copolymer or a (meth)acrylate copolymer, and filtering the resulting solution through a filter having a pore size of 1 μm or less.

ST photosensitive element fluorinated methacrylate copolymer lithog plate; purifn fluorinated methacrylate copolymer presensitized lithog plate

IT Diatomite
RL: NUU (Other use, unclassified); USES (Uses)
(Radiolite 100; purification of fluorinated (meth)acrylate-containing copolymers for presensitized lithog. plate preparation using adsorbents containing diatomite and)

IT Photoimaging materials
(containing purified fluorinated (meth)acrylate copolymers for lithog. plate preparation)

IT Lithographic plates
(photosensitive compns. containing purified fluorinated (meth)acrylate copolymers for preparation of)

IT 1344-28-1, Alumina, uses
RL: NUU (Other use, unclassified); USES (Uses)
(active; adsorbent in purification of fluorinated (meth)acrylate-containing copolymers for use in photosensitive elements for lithog. plate preparation)

IT 109617-10-9, SP 207
RL: NUU (Other use, unclassified); USES (Uses)
(adsorbent in purification of fluorinated (meth)acrylate-containing copolymers for use in photosensitive elements for lithog. plate preparation)

IT 135758-92-8P 251098-96-1P 251113-55-0P 275818-99-0P 275819-00-6P
RL: PUR (Purification or recovery); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(purification and use in photosensitive elements for lithog. plate preparation)

IT 12197-54-5, Cerite
RL: NUU (Other use, unclassified); USES (Uses)
(purification of fluorinated (meth)acrylate-containing copolymers for presensitized lithog. plate preparation using adsorbents containing diatomite and)

IT 78-93-3, Methyl ethyl ketone, uses 107-98-2, 1-Methoxy-2-propanol
RL: NUU (Other use, unclassified); USES (Uses)

(solvent in purification of fluorinated (meth)acrylate-containing copolymers for
use in photosensitive elements for lithog. plate preparation)
RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Fuji Photo Film Co Ltd; EP 0843218 A 1998 CAPLUS
(2) Honda Kenji; US 5300628 A 1994 CAPLUS
(3) Okazaki, S; US 5422221 A 1995 CAPLUS
(4) Shinozaki, F; US 4803145 A 1989 CAPLUS

L12 ANSWER 9 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2000:254691 CAPLUS
DN 132:286357
ED Entered STN: 21 Apr 2000
TI Positive-working presensitized lithographic plates
IN Uno, Seiji; Tan, Shiro; Imaizumi, Atsuhiro; Akiyama, Keiji
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 29 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-039
ICS B41N001-14; G03F007-00; G03F007-004; G03F007-11
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2000112128	A	20000421	JP 1998-284507	19981006
PRAI JP 1998-284507		19981006		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000112128	ICM	G03F007-039
	ICS	B41N001-14; G03F007-00; G03F007-004; G03F007-11
	IPCI	G03F0007-039 [ICM,7]; B41N0001-14 [ICS,7]; G03F0007-00 [ICS,7]; G03F0007-004 [ICS,7]; G03F0007-11 [ICS,7]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41N0001-12 [I,C*]; B41N0001-14 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; G03F0007-11 [I,C*]; G03F0007-11 [I,A]

AB The lithog. plates have hydrophilic Al supports having thereon (a) internal layers containing polymers with acid group-containing components and
onium group-containing components, and (c) photosensitive layers containing polymers containing CH2:CR8PpQqRrZz(OH)n (P, R = divalent org group; Q,
Z = aromatic which may be substituted; R8 = H, alkyl, halo; p, q, r, z = 0,
1; n = 1-3 integer), (meth)acrylonitrile, (meth)acrylic acid esters, and other monomers. The lithog. plates have good adhesion to matt layers and exhibit good developability when developed with silicate salt-free developers.
ST pos working presensitized lithog plate; onium salt acid group polymer

lithog; acrylic polymer photosensitive layer lithog plate
IT Lithographic plates
(presensitized, pos.-working; pos.-working presensitized lithog. plates
having good adhesion to matt layers)
IT 220227-02-1 252721-97-4
RL: TEM (Technical or engineered material use); USES (Uses)
(internal layer containing; pos.-working presensitized lithog. plates having good adhesion to matt layers)
IT 263757-99-9P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photosensitive layer containing; pos.-working presensitized lithog. plates having good adhesion to matt layers)
IT 263758-00-5 263758-01-6
RL: TEM (Technical or engineered material use); USES (Uses)
(pos.-working presensitized lithog. plates having good adhesion to matt layers)

L12 ANSWER 10 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1998:653687 CAPLUS
DN 129:283448
OREF 129:57657a,57660a
ED Entered STN: 15 Oct 1998
TI Radiation sensitive composition and registration materials for lithographic printing plates prepared therewith
IN Elsasser, Andreas; Gaschler, Otfried; Haberhauer, Helmut; Eichhorn, Mathias; Grabley, Fritz-Feo; Leichsenring, Thomas; Koletar, Gabor I.; Seeley, Douglas A.
PA AGFA-GEVAERT A.-G., Germany
SO Eur. Pat. Appl., 8 pp.
CODEN: EPXXDW
DT Patent
LA German
IC ICM B41C001-10
ICS B41M005-40
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 867278	A1	19980930	EP 1998-105080	19980320
EP 867278	B1	20011121		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, MC, PT, IE, SI, LT, LV, FI, RO				
DE 19712323	A1	19981001	DE 1997-19712323	19970324
US 6100004	A	20000808	US 1998-38162	19980311
JP 10293398	A	19981104	JP 1998-66828	19980317
PRAI DE 1997-19712323	A	19970324		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 867278	ICM	B41C001-10

	ICS	B41M005-40
	IPCI	B41C0001-10 [ICM,6]; B41M0005-40 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	ECLA	B41C001/10A; B41M005/40F2; B41M005/46B
DE 19712323	IPCI	G03F0007-004 [ICM,6]; G03F0007-021 [ICS,6]; G03F0007-016 [ICS,6,C*]; G03F0007-14 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	ECLA	B41M005/46B; B41C001/10A
US 6100004	IPCI	G03F0007-021 [ICM,7]; G03F0007-016 [ICM,7,C*]; G03F0007-30 [ICS,7]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	NCL	430/176.000; 430/191.000; 430/192.000; 430/193.000; 430/270.100; 430/281.100; 430/302.000
	ECLA	B41C001/10A; B41M005/40F2
JP 10293398	IPCI	G03F0007-004 [ICM,6]; C09D0011-00 [ICS,6]; G03F0007-00 [ICS,6]; G03F0007-021 [ICS,6]; G03F0007-016 [ICS,6,C*]; G03F0007-022 [ICS,6]; G03F0007-32 [ICS,6]
	IPCR	B41C0001-10 [I,A]; B41C0001-10 [I,C*]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]
	ECLA	B41M005/46B; B41C001/10A

AB A pos.- or neg.-working radiation-sensitive resist mixture contains a soot pigment with a primary particle size of at least 80 nm as an IR-absorbing component, wherein the soot pigment is dispersed in a polymer containing an acid unit having pKs value of smaller than 13.

ST radiation sensitive resist compn printing plate; offset lithog plate soot pigment

IT Lithographic plates
(offset; radiation sensitive composition and registration materials for lithog. printing plates prepared therewith)

IT Photoresists
Soot
(radiation sensitive composition and registration materials for lithog.

printing plates prepared therewith)
IT Carbon black, uses
Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(radiation sensitive composition and registration materials for lithog.
printing plates prepared therewith)
IT 23121-00-8 24979-70-2, Poly(4-hydroxy styrene) 27029-76-1
31693-08-0, 2-Hydroxyethyl methacrylate-methacrylic acid copolymer
38333-84-5, Acetone-pyrogallol copolymer 68510-93-0 110254-07-4
128067-80-1, (4-Hydroxy-3,5-dimethylbenzyl)methacrylamide homopolymer
155599-65-8 213902-63-7
RL: TEM (Technical or engineered material use); USES (Uses)
(radiation sensitive composition and registration materials for lithog.
printing plates prepared therewith)
RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Clark, F; WO 9401280 A 1994
(2) Davi, H; WO 9620429 A 1996 CAPLUS
(3) Minnesota Mining & Mfg; EP 0562952 A 1993 CAPLUS
(4) Scitex Corp Ltd; WO 9700175 A 1997 CAPLUS

L12 ANSWER 11 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1998:160674 CAPLUS
DN 128:277125
OREF 128:54731a,54734a
ED Entered STN: 18 Mar 1998
TI Method of forming electrophotographic lithographic printing plate
IN Kato, Eiichi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 41 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03G013-28
ICS G03G015-16
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 10063042	A	19980306	JP 1996-221536	19960822
PRAI JP 1996-221536		19960822		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 10063042	ICM	G03G013-28
	ICS	G03G015-16
	IPCI	G03G0013-28 [ICM,6]; G03G0015-16 [ICS,6]
	IPCR	G03G0015-16 [I,C*]; G03G0015-16 [I,A]; G03G0013-28 [I,C*]; G03G0013-28 [I,A]

AB The process comprises the steps of (1) forming a peelable transfer layer made from a chemical removable resin (A) on the surface of electrophotog.

photoreceptor, (2) forming an electrophotog. toner image using a liquid developer, (3) transferring the toner image and the transfer layer onto a intermediate transfer material having sticky surface at a temperature (T1), (4) transferring the toner image and the transfer layer onto a final receptor which will turn to a lithog. printable hydrophilic surface at a temperature (T2; T2>T1), and (5) chemical removing the transfer layer, wherein a sticking force of the intermediate transfer material is set at ≥3 g·force at T1 and ≤40 g·force at T2 based on JIS Z 0237-1980. The process transferred the toner image well, and.

ST electrophotog lithog printing plate; intermediate transfer material lithog printing plate

IT Lithographic plates
(method of forming electrophotog. lithog. printing plate)

IT 205175-60-6P 205175-63-9P 205175-64-0P 205175-65-1P 205175-66-2P 205175-67-3P 205175-68-4P 205175-70-8P 205175-71-9P 205175-72-0P 205175-73-1P 205175-74-2P 205175-75-3P 205175-76-4P 205175-77-5P 205175-78-6P
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(method of forming electrophotog. lithog. printing plate)

L12 ANSWER 12 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1998:1273 CAPLUS
DN 128:95387
OREF 128:18533a,18536a
ED Entered STN: 02 Jan 1998
TI Negative-working photosensitive composition for lithographic printing plate
IN Aoshima, Keitaro
PA Fuji Photo Film Co., Ltd., Japan
SO U.S., 23 pp., Cont.-in-part of U.S. Ser. No. 953,259, abandoned.
CODEN: USXXAM
DT Patent
LA English
IC ICM G03F007-021
INCL 430176000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5698361	A	19971216	US 1993-142044	19931028
	JP 05100419	A	19930423	JP 1991-259432	19911007
	JP 05142765	A	19930611	JP 1991-303229	19911119
PRAI	JP 1991-259432	A	19911007		
	JP 1991-303229	A	19911119		
	US 1992-953259	B2	19920930		

CLASS
PATENT NO. CLASS PATENT FAMILY CLASSIFICATION CODES

US 5698361	ICM	G03F007-021
	INCL	430176000
	IPCI	G03F0007-021 [ICM,6]; G03F0007-016 [ICM,6,C*]
	IPCR	C08G0018-00 [I,C*]; C08G0018-38 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]
	NCL	430/176.000; 430/157.000; 430/175.000; 430/906.000; 522/032.000
	ECLA	C08G018/38F9; G03F007/021P
JP 05100419	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]; H01L0021-027 [ICS,5]; H01L0021-02 [ICS,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]
JP 05142765	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]; G03F0007-00 [ICS,5]; G03F0007-035 [ICS,5]; G03F0007-032 [ICS,5,C*]; H01L0021-027 [ICS,5]; H01L0021-02 [ICS,5,C*]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-032 [I,C*]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-035 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]

AB The present invention relates to a neg.-working photosensitive composition comprising a diazonium compound and a polymer binder. The polymer binder is (1) or (2) decribed below. (1) Is an AB type, ABA type or BAB type block copolymer of: (i) a block (A) represented by [H2CCR1(X1Z)] and (ii) a block (B) represented by [H2CCR5(X2R6)] being free from I. (2) Is a block copolymer obtained by subjecting to radical polymerization (i) an azo group-containing polyurethane (C) which contains a unit having R7NHCOOR6N=NR6OCONH and a unit having R9NHCOOR10OCONH in the mol. and which has a weight-average mol. weight of 2,000-200,000; and (ii) a polymerizable monomer having H2C=R1(X1Z).

ST neg photosensitive compn polymer binder; lithog printing plate photosensitive compn

IT Lithographic plates
(neg.-working photosensitive composition for lithog. printing plate)

IT Polyurethanes, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(neg.-working photosensitive composition for lithog. printing plate)

IT 149787-91-7P, Acrylic acid-ethyl methacrylate-2-hydroxyethyl methacrylate block copolymer 149826-04-0P 149826-05-1P 149826-06-2P 201054-29-7DP, Ethyl methacrylate-triphenylmethyl methacrylate copolymer, hydrolyzed, reaction product with 2-bromoethanol 201054-31-1P 201054-32-2P 201054-33-3P 201054-35-5P 201054-37-7P 201054-39-9P 201054-41-3P 201054-42-4P 201054-43-5P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(neg.-working photosensitive composition for lithog. printing plate)

L12 ANSWER 13 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1996:566824 CAPLUS
DN 125:208497
OREF 125:38761a,38764a
ED Entered STN: 21 Sep 1996
TI Photosensitive compositions useful for preparing presensitized lithographic plates
IN Tsuji, Shigeo; Matsuo, Fumyuki; Matsumura, Tomoyuki; Ishii, Nobuyuki; Kizu, Noryuki
PA Mitsubishi Chemical Corp., Japan; Konishiroku Photo Ind
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-021
ICS G03F007-00; G03F007-027; G03F007-032; G03F007-033
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 37
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 08171206	A	19960702	JP 1994-316650	19941220
PRAI JP 1994-316650		19941220		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 08171206	ICM	G03F007-021
	ICS	G03F007-00; G03F007-027; G03F007-032; G03F007-033
	IPCI	G03F0007-021 [ICM,6]; G03F0007-00 [ICS,6]; G03F0007-027 [ICS,6]; G03F0007-032 [ICS,6]; G03F0007-033 [ICS,6]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-027 [I,C*]; G03F0007-027 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]

AB The title compns., comprising a compound having ≥1 ethylenic unsatd. double bond, an acidic vinyl copolymer soluble or swellable in aqueous alkali, a photopolymn. initiator, and a diazo resin, employ, as the vinyl copolymer, a copolymer containing (a) a structural unit having an aromatic compound possessing ≥1 group comprising aromatic OH and sulfonamide groups in its side chain, (b) an unit having cyano group in its chain, (c) a unit based on Et methacrylate and/or Me methacrylate, and (d) an unit based on ≥1 monomer which is copolymerizable with the monomers (a), (b), and (c) and of which the glass transition of the homopolymer is ≤50°. The presensitized lithog. plates using the compns. show good alkali-developability and printing durability. Thus, a photosensitive composition comprised trimethylolpropane triacrylate, N-(4-hydroxyphenyl)methacrylamide-acrylonitrile-Me methacrylate-Et acrylate-methacrylic acid copolymer, a photopolymn. initiator,

and a diazo resin.
ST photosensitive compn vinyl copolymer; presensitized lithog plate photosensitive compn
IT Lithographic plates
(photosensitive composition containing acidic vinyl copolymer for presensitized lithog. plate)
IT 15625-89-5, Trimethylolpropane triacrylate 16941-11-0D, Ammonium hexafluorophosphate, reaction products with diazo resin 132459-36-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 181044-84-8
RL: DEV (Device component use); USES (Uses)
(photosensitive composition containing acidic vinyl copolymer for presensitized lithog. plate)
IT 125785-09-3DP, reaction products with ammonium hexafluorophosphate 126034-88-6DP, reaction products with ammonium hexafluorophosphate
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(photosensitive composition containing acidic vinyl copolymer for presensitized lithog. plate)

L12 ANSWER 14 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1996:469866 CAPLUS
DN 125:127831
OREF 125:23697a,23700a
ED Entered STN: 09 Aug 1996
TI Presensitized lithographic printing plate with improved printability
IN Tomyasu, Hiroshi; Kajiwara, Shigeru; Masai, Junji
PA Mitsubishi Chemical Corp., Japan; Konishiroku Photo Ind
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM B41N003-03
ICS C25D011-16; G03F007-00; G03F007-021
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 08132751	A	19960528	JP 1994-277840	19941111
PRAI JP 1994-277840		19941111		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 08132751	ICM	B41N003-03
	ICS	C25D011-16; G03F007-00; G03F007-021
	IPCI	B41N0003-03 [ICM,6]; C25D0011-16 [ICS,6]; G03F0007-00 [ICS,6]; G03F0007-021 [ICS,6]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; B41N0003-03 [I,C*]; B41N0003-03 [I,A]; C25D0011-04 [I,C*]; C25D0011-16 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]

AB The title printing plate comprises an anodized Al support with a sp. surface roughness measured by an AFM (Atomic force microscopy) and a

photosensitive layer containing a diazo resin or OH group-containing acrylic resin.
ST presensitized lithog plate aluminum support
IT Lithographic plates
(presensitized, presensitized lithog. printing plate with improved printability)
IT Lithographic plates
(supports, presensitized lithog. printing plate with improved printability)
IT 29763-27-7, Acrylonitrile-methacrylic acid-methyl methacrylate copolymer 125785-09-3, p-Diazodiphenylamine sulfate-formaldehyde-p-hydroxybenzoic acid copolymer 132459-36-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer
RL: DEV (Device component use); USES (Uses)
(photosensitive layer of presensitized lithog. printing plate comprising)

L12 ANSWER 15 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1996:191653 CAPLUS
DN 124:302567
OREF 124:55831a,55834a
ED Entered STN: 04 Apr 1996
TI Photosensitive transfer sheet useful for preparing color proofs
IN Wakata, Juichi; Araki, Katsumi; Totsuka, Mikio
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10; G03F007-11
CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07333836	A	19951222	JP 1994-126519	19940608
PRAI JP 1994-126519		19940608		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07333836	ICM	G03F007-004
	ICS	G03F003-10; G03F007-11
	IPCI	G03F0007-004 [ICM,6]; G03F0003-10 [ICS,6]; G03F0007-11 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-11 [I,C*]; G03F0007-11 [I,A]

AB The title transfer sheet, comprising a support with coatings of an organic
polymer-containing releasing layer and a color material-containing photosensitive layer or a laminate of a color material layer and a photosensitive layer, contains, in the releasing layer, ≥1 polymer having a repeating unit CH2CR1[XA(OH)n] (R1 = H, Me; A = C6-10

aryl which may be substituted for ≥1 or a combination of ≥2 selected from C1-6 alkyl, C6-10 aryl, C1-6 alkoxy, halo, cyano, CO2H, CO2R2, COR3, CONR4R5, and nitro; X = CO2, CONR6, CO2R7, CONR2R7; R2-6 = H, C1-6 alkyl, C6-10 aryl, these groups may be substituted for ≥1 or a combination of ≥2 selected from OH, C1-6 alkoxy, halo, and CN: R7 = C1-10 alkylene, aralkylene, these groups may be branched and may contain 1 or a combination of ≥2 selected from ether bond, OCO, and CO2; n = 1-3). The sheet useful for preparing color proofs and displays shows good transferability and imaging properties under varied moisture conditions and antiflaking properties and provides high-quality images without color fog. Thus, a PET film was coated successively with a releasing layer containing CM-8000 (alc.-soluble polyamide) and poly[N-(p-hydroxyphenyl)acrylamide], a yellow photosensitive layer, and a protective layer to give a yellow photosensitive transfer sheet. Magenta, cyan, and black photosensitive transfer sheets were prepared similarly.

ST photosensitive transfer sheet releasing layer

IT Photoimaging compositions and processes
(photosensitive transfer sheet with releasing layer)

IT Polyamides, uses
RL: DEV (Device component use); USES (Uses)
(photosensitive transfer sheet with releasing layer)

IT 25191-90-6, CM 8000
RL: DEV (Device component use); USES (Uses)
(photosensitive transfer sheet with releasing layer)

IT 80633-45-0P 134257-23-1P 155599-65-8P 175784-16-4P 175784-17-5P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(photosensitive transfer sheet with releasing layer)

IT 13040-21-6P 34443-04-4P, N-(p-Hydroxyphenyl)acrylamide 80633-44-9P 87157-77-5P 175784-18-6P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(preparation and polymerization of)

IT 51-67-2, p-(2-Aminoethyl)phenol 123-30-8, p-Aminophenol 150-75-4, p-Methylaminophenol 591-27-5 814-68-6, Acrylic acid chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of hydroxyphenylacrylamide compound)

L12 ANSWER 16 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:943574 CAPLUS
DN 123:354705
OREF 123:63371a,63374a
ED Entered STN: 24 Nov 1995
TI Photosensitive planographic printing plate processing method without using hazardous developers
IN Suzuki, Toshitsugu; Matsumura, Tomoyuki; Murata, Masahisa; Toshimitsu, Eriko; Tsuji, Shigeo
PA Konishiroku Photo Ind, Japan; Mitsubishi Kagaku KK
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF

DT Patent
LA Japanese
IC ICM G03F007-32
ICS G03F007-00; G03F007-004; G03F007-021; G03F007-033; G03F007-038
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07230172	A	19950829	JP 1994-41959	19940216
PRAI JP 1994-41959		19940216		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07230172	ICM	G03F007-32
	ICS	G03F007-00; G03F007-004; G03F007-021; G03F007-033; G03F007-038
	IPCI	G03F0007-32 [ICM,6]; G03F0007-00 [ICS,6]; G03F0007-004 [ICS,6]; G03F0007-021 [ICS,6]; G03F0007-033 [ICS,6]; G03F0007-038 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB The title method includes developing a photosensitive printing plate with an alkaline developing solution (pH <12) containing no organic solvent.
ST photosensitive planog printing plate processing
IT Alcohols
RL: DEV (Device component use); USES (Uses)
(C12-16, Conol 20F, development accelerator; photosensitive planog. printing plate comprising)
IT Polyesters, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(phenolic, photosensitive planog. printing plate comprising)
IT Printing plates
(planog., presensitized, photosensitive planog. printing plate processing method without using hazardous developers)
IT Phenolic resins, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(polyester-, photosensitive planog. printing plate comprising)
IT 89-51-0, Homophthalic acid 108-55-4, Glutaric acid anhydride 4023-65-8, trans-Aconitic acid 9050-31-1, HP 55
RL: DEV (Device component use); USES (Uses)
(development accelerator; photosensitive planog. printing plate comprising)
IT 16941-11-0DP, Ammonium hexafluorophosphate, reaction products with Na dibutylnaphthalenesulfonate 25417-20-3DP, Sodium dibutylnaphthalenesulfonate, reaction products with 4-diazophenylamine sulfate-formaldehyde-p-hydroxybenzoic acid copolymer 125785-09-3DP, 4-Diazodiphenylamine sulfate-p-hydroxybenzoic acid-paraformaldehyde

copolymer, reaction products with Na dibutylnaphthalenesulfonate 126033-29-2DP, 4-Diazodiphenylamine sulfate-paraformaldehyde-sodium benzensulfonate copolymer*, reaction products with Na dibutylnaphthalenesulfonate
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(diazo resin; photosensitive planog. printing plate comprising)
IT 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 143932-43-8P
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(lipophilic polymer; photosensitive planog. printing plate comprising)

L12 ANSWER 17 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:849469 CAPLUS
DN 123:270843
OREF 123:48195a,48198a
ED Entered STN: 12 Oct 1995
TI Photosensitive compositions useful as negative-working lithographic plates
IN Toshimitsu, Eriko; Shimizu, Shigeki
PA Mitsubishi Kagaku KK, Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-021
ICS G03F007-00; G03F007-004; G03F007-033; G03F007-038
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07168353	A	19950704	JP 1993-316553	19931216
PRAI JP 1993-316553		19931216		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07168353	ICM	G03F007-021
	ICS	G03F007-00; G03F007-004; G03F007-033; G03F007-038
	IPCI	G03F0007-021 [ICM,6]; G03F0007-016 [ICM,6,C*]; G03F0007-00 [ICS,6]; G03F0007-004 [ICS,6]; G03F0007-033 [ICS,6]; G03F0007-038 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]

OS MARPAT 123:270843
AB The title compns. contain a diazonium compound, an oleophilic polymer, and a
compound (R1R2AR3R4)+.X- [I; R1-4 = H, (substituted) alkyl which may have

multiple bonds, (substituted) aryl, ≥2 of R1-4 may form a ring, but ≥1 of R1-4 is not H; A = N, P; X = halo anion, O-containing anion]. The compns. have good developing property and better resistance to wetting upon printing, and the image areas exhibit good alkali resistance even after storage at high temperature and humidity. Thus, a photosensitive composition comprised a diazonium compound prepared from p-hydroxybenzoic acid, p-diazodiphenylamonium sulfate, and paraformaldehyde, p-hydroxyphenylmethacrylamide-Et acrylate-acrylonitrile copolymer, I (R1-4 = Bu, A = N, X = Cl), and additives.
ST photosensitive compn diazonium compd; quaternary ammonium salt lithog plate; phosphonium salt lithog plate
IT Lithographic plates
(neg.-working lithog. plate containing diazonium compound and quaternary ammonium or phosphonium compound)
IT Quaternary ammonium compounds, uses
RL: MOA (Modifier or additive use); USES (Uses)
(benzyl-C12-14-alkyldimethyl chlorides, neg.-working lithog. plate containing diazonium compound and quaternary ammonium or phosphonium compound)
IT 7646-85-7DP, Zinc chloride, reaction products with diazo resin and hexafluorophosphate 16941-11-0DP, Ammonium hexafluorophosphate, reaction products with diazo resin and zinc chloride 125785-09-3DP, p-Diazodiphenylammonium sulfate-formaldehyde-p-hydroxybenzoic acid copolymer, reaction products with zinc chloride and hexafluorophosphate 169202-35-1P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(neg.-working lithog. plate containing diazonium compound and quaternary ammonium or phosphonium compound)
IT 56-37-1, Triethylbenzylammonium chloride 67-48-1, Choline chloride 75-57-0, Tetramethylammonium chloride 112-00-5, Quartamin 24P 593-81-7 1112-67-0, Tetrabutylammonium chloride 1643-19-2, Tetrabutylammonium bromide 1941-27-1, Tetrabutylammonium nitrate 3115-68-2, Tetrabutylphosphonium bromide 7182-86-7, Tetrabutylammonium p-toluenesulfonate 32503-27-8, Tetrabutylammonium hydrosulfate
RL: MOA (Modifier or additive use); USES (Uses)
(neg.-working lithog. plate containing diazonium compound and quaternary ammonium or phosphonium compound)

L12 ANSWER 18 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:499874 CAPLUS
DN 123:22208
OREF 123:3999a,4002a
ED Entered STN: 20 Apr 1995
TI Alkali-developable photosensitive composition and image formation using it
IN Kawamura, Koichi; Takita, Satoshi; Kawamura, Yoshitaka; Akyama, Keiji

PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 22 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-033
ICS G03F007-00; G03F007-039; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

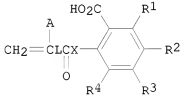
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 07036185	A	19950207	JP 1993-183023	19930723
	JP 3071611	B2	20000731		
PRAI	JP 1993-183023		19930723		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07036185	ICM	G03F007-033
	ICS	G03F007-00; G03F007-039; H01L021-027
	IPCI	G03F0007-033 [ICM,6]; G03F0007-00 [ICS,6]; G03F0007-039 [ICS,6]; H01L0021-027 [ICS,6]; H01L0021-02 [ICS,6,C*]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; C08F0020-00 [I,C*]; C08F0020-20 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]

GI



I

AB The composition contains a polymer obtained by polymerization of ≥1 vinyl-containing benzoic acid derivative I [A = H, halo, alkyl; X = O, NH, NR5; R1-4 = H, halo, (substituted) alkyl, (substituted) aryl, OR6, OCOR7, NHCOR8, NHCONHR9, OCONHR10, CO2R11, CONHR12, COR13, CONR14R15, CN, CHO; 2 of R1-4 may be form ring; R5 = alkyl; R6-15 = (substituted) alkyl, (substituted) aryl; L = divalent organic group] and a pos. photosensitive substance. Images are obtained by exposing a material having a photosensitive layer obtained from the composition and developing with an alkali aqueous solution with pH ≤12.5. The composition is useful for manufacture of lithog. printing plates, integrated circuits, photomasks, etc. The composition gave lithog. printing plates with

good printability.
ST alkali developable photoresist benzoic acid polymer
IT Resists
(photo-, alkali-developable photoresist containing benzoic acid derivative polymer and image formation using it)
IT 163588-51-0P 163588-53-2P 163588-54-3P 163588-55-4P 163588-56-5P 163588-57-6P 163588-59-8P 163588-60-1P 163588-61-2P 163588-62-3P 163588-64-5P 163588-65-6P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(alkali-developable photoresist containing benzoic acid derivative polymer and image formation using it)
IT 163588-42-9P 163588-43-0P 163588-44-1P 163588-45-2P 163588-46-3P 163588-47-4P 163588-48-5P 163588-49-6P 163588-50-9P
RL: PNU (Preparation, unclassified); PREP (Preparation)
(alkali-developable photoresist containing benzoic acid derivative polymer and image formation using it)
IT 118-92-3, Anthranilic acid 320-72-9, 3,5-Dichloro-2-hydroxybenzoic acid 635-21-2, 2-Amino-5-chlorobenzoic acid 1075-49-6, 4-Vinylbenzoic acid 6245-04-1 30674-80-7, 2-Isocyanatoethyl methacrylate 68701-14-4 69260-38-4 69260-39-5 86017-34-7 91652-00-5, 4-(6-Methacryloyloxyhexyloxy)benzoic acid 159086-65-4 163588-41-8
RL: RCT (Reactant); RACT (Reactant or reagent)
(alkali-developable photoresist containing benzoic acid derivative polymer and image formation using it)
IT 5610-94-6 68584-99-6
RL: TEM (Technical or engineered material use); USES (Uses)
(alkali-developable photoresist containing benzoic acid derivative polymer and image formation using it)

L12 ANSWER 19 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1994:334822 CAPLUS
DN 120:334822
OREF 120:58665a,58668a
ED Entered STN: 25 Jun 1994
TI Silver halide photographic materials with good drying properties
IN Yamanochi, Junichi; Takagi, Yasuyuki; Tamura, Yutaka
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 28 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03C001-053
ICS G03C005-26
CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05323488	A	19931207	JP 1992-133922	19920526
	JP 2794513	B2	19980910		
	US 5445931	A	19950829	US 1994-283763	19940803
PRAI	JP 1992-133922	A	19920526		
	US 1993-66199	B1	19930525		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 05323488	ICM	G03C001-053
	ICS	G03C005-26
	IPCI	G03C0001-053 [ICM,5]; G03C0005-26 [ICS,5]
	IPCR	G03C0001-053 [I,C*]; G03C0001-053 [I,A]; G03C0005-26 [I,C*]; G03C0005-26 [I,A]
US 5445931	IPCI	G03C0001-047 [ICM,6]
	IPCR	G03C0001-053 [I,C*]; G03C0001-053 [I,A]
	NCL	430/627.000; 430/516.000; 430/529.000; 430/537.000; 430/539.000; 430/635.000; 430/640.000; 430/963.000
	ECLA	G03C001/053

AB The title materials, prepared by forming ≥1 Ag halide emulsion layer on a support, contain a water-soluble polymer, which is insol. and soluble in water at pH ≤6 and ≥10, resp., derived from CO2H-containing monomers or their salts in ≥1 of the hydrophilic colloid layers. The materials show good drying properties in super-high speed process. Thus, a PET film coated with an undercoat layer was coated with a Ag(Br, I) emulsion layer and a gelatin-based protective layer containing a NaOH-neutralized homopolymer of CH2:CHCONH(CH2)10CO2H to give a photog. film.

ST carboxyl group polymer photog material

IT Photographic films
(with good drying properties, containing polymer with carboxyl group)

IT 155599-61-4 155599-62-5 155599-64-7 155599-66-9 155599-68-1 155599-70-5 155599-72-7
RL: USES (Uses)
(photog. film containing, for good drying properties)

L12 ANSWER 20 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1994:311539 CAPLUS
DN 120:311539
OREF 120:54557a,54560a
ED Entered STN: 11 Jun 1994
TI Photoimaging material and image formation using some
IN Wakata, Juichi; Iwasaki, Masayuki; Fujikura, Sadao; Ito, Hideaki
PA Fuji Photo Film Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-027
ICS G02B005-20; G03F007-038; G03F007-30
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05080510	A	19930402	JP 1991-239484	19910919
PRAI	JP 1991-239484		19910919		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 05080510	ICM	G03F007-027

ICS G02B005-20; G03F007-038; G03F007-30
IPCI G03F0007-027 [ICM,5]; G02B0005-20 [ICS,5]; G03F0007-038
[ICS,5]; G03F0007-30 [ICS,5]
IPCR G02B0005-20 [I,C*]; G02B0005-20 [I,A]; G03F0007-027 [I,C*]; G03F0007-027 [I,A]; G03F0007-038 [I,C*]; G03F0007-038 [I,A]; G03F0007-095 [I,C*]; G03F0007-095 [I,A]; G03F0007-26 [I,C*]; G03F0007-26 [I,A]; G03F0007-30 [I,C*]; G03F0007-30 [I,A]

AB In the title material comprising a 1st photosensitive-resin layer developable by an aqueous alkali solution and a 2nd photosensitive -resin layer developable by a weaker aqueous alkali solution than the above, the
1st layer contains a polymer of acid value 70-150 with acid groups of pKa 9-13, and the 2nd layer contains a polymer of acid value 50-250 with acid groups of pKa 3-8. The 1st layer may contain a polymer with SO2NH, CONHCO, or hydroxyphenyl and the 2nd layer CO2H. The image is produced on
the above layers by patternwise exposing the 2nd layer, developing the exposed 2nd layer using a weaker alkali developer which will not develop the 1st layer, patternwise exposing the exposed 1st layer, and developing the 1st layer using an alkali developer having a smaller H+ concentration than
the above weaker developer.

ST photosensitive layer dual alkali development; photoresist double layer patterning

IT Optical imaging devices
(color filters for, photoresist patterning for)

IT Photoimaging compositions and processes
(dual photoresist layer using)

IT Resists
(photo-, patterning of, dual layer)

IT Electric circuits
(printed, photoresist for manufacturing)

IT 29061-97-0 65697-21-4 147026-46-8 147161-03-3 155079-18-8 155079-19-9 155079-20-2
RL: USES (Uses)
(photoresist composition from)

IT 34443-04-4, N-(p-Hydroxy phenyl)acrylamide 56992-87-1, N-(p-Amino sulfonyl phenyl)methacrylamide 123426-65-3 146883-73-0
RL: USES (Uses)
(preparation polymerization of, photoresist composition from)

L12 ANSWER 21 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1994:284820 CAPLUS
DN 120:284820
OREF 120:50033a,50036a
ED Entered STN: 28 May 1994
TI Color photographic material containing polymeric coupler
IN CHen, Tien Teh; Cowan, Stanley Wray; Schofield, Edward; Tang, Ping Wah
PA Eastman Kodak Co., USA
SO Eur. Pat. Appl., 24 pp.
CODEN: EPXXDW
DT Patent
LA English

IC ICM G03C007-327
ICS C08F020-36
CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 569097	A2	19931110	EP 1993-201275	19930505
	EP 569097	A3	19950405		
	EP 569097	B1	19990818		
	R: BE, CH, DE, FR, GB, IT, LI, NL				
	US 5360710	A	19941101	US 1992-879044	19920506
	JP 06051468	A	19940225	JP 1993-104380	19930430
	US 5455147	A	19951003	US 1994-263231	19940621
PRAI	US 1992-879044	A	19920506		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 569097	ICM	G03C007-327
	ICS	C08F020-36
	IPCI	G03C0007-327 [ICM,5]; C08F0020-36 [ICS,5]; C08F0020-00 [ICS,5,C*]
	IPCR	C08F0020-00 [I,C*]; C08F0020-36 [I,A]; G03C0007-327 [I,C*]; G03C0007-327 [I,A]
	ECLA	C08F020/36; G03C007/327B
US 5360710	IPCI	G03C0007-327 [ICM,5]
	IPCR	C08F0020-00 [I,C*]; C08F0020-36 [I,A]; G03C0007-327 [I,C*]; G03C0007-327 [I,A]
	NCL	430/548.000; 430/546.000; 430/558.000
	ECLA	C08F020/36; G03C007/327B
JP 06051468	IPCI	G03C0007-327 [ICM,5]
	IPCR	C08F0020-00 [I,C*]; C08F0020-36 [I,A]; G03C0007-327 [I,C*]; G03C0007-327 [I,A]
US 5455147	IPCI	G03C0007-388 [ICM,6]
	IPCR	C08F0020-00 [I,C*]; C08F0020-36 [I,A]; G03C0007-327 [I,C*]; G03C0007-327 [I,A]
	NCL	430/449.000; 430/546.000; 430/548.000; 516/056.000; 516/060.000; 516/061.000
	ECLA	C08F020/36; G03C007/327B

AB A color photog. material comprises a support bearing a silver halide emulsion layer containing at least one water-dispersible polymeric coupler. The polymeric coupler is formed by polymerization of a mixture of at least one ethylenically unsatd. coupler monomer containing a dye-forming coupler moiety and at least one ionic monomer containing an ionizable functional group in a water-miscible organic solvent. The polymeric coupler contains less than 10 weight% of the ionic monomer.

ST color photog material polymeric coupler

IT Photographic couplers
(polymeric, water-dispersed, preparation and use of)

IT Photographic emulsions
(color, containing water-dispersed polymeric color formers)

IT 154868-41-4P 154868-42-5P 154868-44-7P 154868-45-8P
154868-46-9P 154868-48-1P 154868-50-5P 154868-51-6P 154868-52-7P

154868-53-8P 154868-54-9P 154868-55-0P 154868-56-1P 154868-57-2P
154868-59-4P 154868-61-8P 154868-62-9P 154868-63-0P 154868-65-2P
154868-66-3P 154868-67-4P 154868-69-6P 154868-71-0P 154868-73-2P
154868-74-3P 154868-75-4P
RL: TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photog. coupler, water-dispersed, preparation and use of)

L12 ANSWER 22 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:459759 CAPLUS
DN 119:59759
OREF 119:10579a,10582a
ED Entered STN: 07 Aug 1993
TI Manufacture of presensitized lithographic plate with quick inking property
IN Koike, Akinobu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-00
ICS G03F007-016; G03F007-027; G03F007-30
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04299345	A	19921022	JP 1991-64754	19910328
PRAI JP 1991-64754		19910328		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04299345	ICM	G03F007-00
	ICS	G03F007-016; G03F007-027; G03F007-30
	IPCI	G03F0007-00 [ICM,5]; G03F0007-016 [ICS,5]; G03F0007-027 [ICS,5]; G03F0007-30 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-016 [I,A]; G03F0007-027 [I,C*]; G03F0007-027 [I,A]; G03F0007-30 [I,C*]; G03F0007-30 [I,A]

AB The lithog. plate prepared by coating a substrate with a photosensitive layer containing (1) arom diazonium compound containing ≥1 group selected from CO2H, phenolic OH, SO3H, SO2H, and P oxygen acid, (2) oleophilic polymer, and (3) a polymer containing p-hydroxystyrene ester as a monomer unit and/or silicone-type surfactant, is imagewise exposed, and developed by an aqueous alkali developer with pH ≥12 (at 25°) and containing essentially number organic solvent. The lithog. plate can be developed by aqueous developer, and shows quick inking property, and gives clear images without stains.
ST presensitized lithog plate inking property

IT Siloxanes and Silicones, uses
RL: DEV (Device component use); USES (Uses)
(acrylic, presensitized lithog. plate containing, for quick inking property
, Aron GS 30)
IT Lithographic plates
(presensitized, developable with aqueous alkali solution, with good inking
property)
IT 7646-85-7D, Zinc chloride, reaction product with diazo resin and dibutylnaphthalenesulfonate 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction product with diazo resin and zinc chloride 125785-09-3D, reaction product with zinc chloride and dibutylnaphthalenesulfonate 126033-29-2D, reaction product with zinc chloride and dibutylnaphthalenesulfonate 132459-36-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 143932-42-7D, reaction product with zinc chloride and dibutylnaphthalenesulfonate 148798-87-2
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plate containing)
IT 147833-70-3 148798-89-4
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plate containing, for quick inking property)

L12 ANSWER 23 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:202124 CAPLUS
DN 118:202124
OREF 118:34537a,34540a
ED Entered STN: 14 May 1993
TI Manufacture of lithographic plate using diazo resin
IN Koike, Akinobu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-00
ICS G03F007-016; G03F007-30
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04299344	A	19921022	JP 1991-64753	19910328
PRAI JP 1991-64753		19910328		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04299344	ICM	G03F007-00
	ICS	G03F007-016; G03F007-30
	IPCI	G03F0007-00 [ICM,5]; G03F0007-016 [ICS,5]; G03F0007-30 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-004

[I,C*]; G03F0007-004 [I,A]; G03F0007-016 [I,C*]; G03F0007-016 [I,A]; G03F0007-30 [I,C*]; G03F0007-30 [I,A]

AB The title plate is manufactured by a process including following steps: (1) coating a solution of a photosensitive composition containing an arom diazonium compound substituted with carboxyl, sulfonic acid, sulfinic acid, and/or P oxyacid group in a mixture of ≥2 solvents containing a liquid of b.p. ≥115° and a solvent of b.p. ≤95°, (2) drying, (3) imagewise exposing the resulting photosensitive plate, and (4) developing by an organic solvent-free water-based alkaline liquid of pH ≥12 at 25°. The plate shows improved printing resistance.

ST lithog plate photosensitive azo resin; org solvent free development lithog; carboxy substituted azo resin lithog; sulfonic acid substituted azo resin; sulfinic acid substituted azo resin; phosphorus oxyacid substituted azo resin; alk water based development lithog

IT Lithographic plates
(manufacture of, development by organic solvent-free aqueous solns. of azo resin-containing photosensitive compns. in)

IT 1310-58-3, Potassium hydroxide, uses 1312-76-1, Potassium silicate
RL: USES (Uses)
(developing solns. containing, for manufacture of lithog. plates)

IT 67-56-1, Methanol, uses 78-93-3, Methyl ethyl ketone, uses 107-98-2, 1-Methoxy-2-propanol 109-86-4, Methyl cellosolve
RL: USES (Uses)
(photosensitive compns. containing, for manufacture of lithog. plates)

IT 125785-09-3DP, reaction products with dibutylnaphthalenesulfonic acid hexafluorophosphoric acid 126033-29-2DP, reaction products with dibutylnaphthalenesulfonic acid hexafluorophosphoric acid 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 147045-53-2P
RL: PREP (Preparation)
(preparation of, for manufacture of lithog. plates)

L12 ANSWER 24 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:202119 CAPLUS
DN 118:202119
OREF 118:34533a,34536a
ED Entered STN: 14 May 1993
TI Manufacture of lithographic printing plate using aqueous alkali solution
IN Koike, Akinobu; Sakaki, Hirokazu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-32
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other

Reprographic Processes)

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04284457	A	19921009	JP 1991-49837	19910314
PRAI JP 1991-49837		19910314		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04284457	ICM	G03F007-32
	ICS	G03F007-00
	IPCI	G03F0007-32 [ICM,5]; G03F0007-00 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-09 [I,C*]; G03F0007-09 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB A presensitized lithog. plate, prepared by forming a photosensitive layer containing a diazo resin and an oleophilic polymer on a support obtained by anodic oxidation of a HCl-electrolytically coarsened Al plate in a H2SO4 solution using d.c. of c.d. 8-25 A/dm2, is imagewise exposed and developed with an aqueous alkali solution of pH ≥12 containing no organic solvent to give a lithog. printing plate. The generation of scums in developing bath is prevented even when the plate is developed with an aqueous alkali solution

ST presensitized lithog plate prepn; alkali aq developer lithog plate; anodization aluminum substrate presensitized lithog plate

IT Anodization
(of aluminum plates for lithog. plate substrates)

IT Lithographic plates
(presensitized, anodization of substrates for, for alkali development)

IT 37321-70-3
RL: RCT (Reactant); RACT (Reactant or reagent)
(anodization of, for presensitized lithog. plate substrates)

IT 125785-09-3DP, reaction products with anions 147025-68-1DP, reaction products with anions
RL: PREP (Preparation)
(preparation of, for presensitized lithog. plates)

IT 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 143932-43-8P
RL: PREP (Preparation)
(preparation of, for presensitized lithog. plates containing diazo resins)

IT 7646-85-7D, Zinc chloride, reaction products with diazo resins 16941-11-0D, Ammonium hexafluorophosphate, reaction products with diazo resins 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction products with diazo resins
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plates containing)

L12 ANSWER 25 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN

AN 1993:202118 CAPLUS
DN 118:202118
OREF 118:34533a,34536a
ED Entered STN: 14 May 1993
TI Manufacture of lithographic printing plate using aqueous alkali developer
IN Koike, Akinobu; Sakaki, Hirokazu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-32
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04284456	A	19921009	JP 1991-49836	19910314
PRAI JP 1991-49836		19910314		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04284456	ICM	G03F007-32
	ICS	G03F007-00
	IPCI	G03F0007-32 [ICM,5]; G03F0007-00 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB A presensitized lithog. plate, prepared by forming a photosensitive layer containing a diazo resin and an oleophilic polymer on an alkali-etched, acid-neutralized, and HCl-electrolytically coarsened support, is imagewise exposed and developed with an aqueous alkali solution of pH ≥12 containing no organic solvent to give a lithog. printing plate. The printing plate developed with an aqueous alkali solution shows good printing durability.
ST presensitized lithog plate plate making; alkali aq developer lithog plate; aluminum substrate presensitized lithog plate
IT Lithographic plates
(presensitized, pretreatment of substrates for, for alkali development)
IT 1310-73-2, Sodium hydroxide, uses 6834-92-0, Sodium metasilicate
RL: USES (Uses)
(lithog. plate aluminum substrates pretreated with)
IT 125785-09-3DP, reaction products with anions 147025-68-1DP, reaction products with anions
RL: PREP (Preparation)
(preparation of, for presensitized lithog. plates)
IT 143932-43-8P
RL: PREP (Preparation)
(preparation of, for presensitized lithog. plates containing diazo resins)
IT 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-

hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer
RL: PREP (Preparation)
(preparation of, presensitized lithog. plates containing diazo resins and)
IT 7646-85-7D, Zinc chloride, reaction products with diazo resins 16941-11-0D, Ammonium hexafluorophosphate, reaction products with diazo resins 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction products with diazo resins
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plates containing)
IT 37321-70-3
RL: USES (Uses)
(pretreatment of, for presensitized lithog. plate substrates)

L12 ANSWER 26 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:157975 CAPLUS
DN 118:157975
OREF 118:26903a,26906a
ED Entered STN: 13 Apr 1993
TI Preparation of lithographic printing plate using aqueous alkali solutions
IN Koike, Akinobu; Sakaki, Hirokazu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-32
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04285966	A	19921012	JP 1991-49839	19910314
JP 2632090	B2	19970716		
PRAI JP 1991-49839		19910314		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04285966	ICM	G03F007-32
	ICS	G03F007-00
	IPCI	G03F0007-32 [ICM,5]; G03F0007-00 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-09 [I,C*]; G03F0007-09 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB A presensitized lithog. plate, prepared by forming a photosensitive layer containing a diazo resin and an oleophilic polymer on an Al support containing Cu 0.015-0.03 weight%, is imagewise exposed and developed with an aqueous alkali solution of pH ≥12 containing no organic solvent to give a lithog. printing plate. The printing plate shows good printing durability, and the method prevents generation of scums in developing bath during

development.
ST presensitized lithog plate plate making; alkali aq development lithog plate; aluminum support copper lithog plate
IT Lithographic plates
(presensitized, manufacture of, in alkali development, aluminum substrate for)
IT 125785-09-3DP, reaction products with zinc sulfate and anions 126033-29-2DP, reaction products with zinc sulfate and anions 143932-42-7DP, 4-Diazodiphenylammonium sulfate-formaldehyde-phenoxyacetic acid copolymer, reaction products with zinc sulfate and anions
RL: PREP (Preparation)
(preparation of, presensitized lithog. plate containing)
IT 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 143932-43-8P
RL: PREP (Preparation)
(preparation of, presensitized lithog. plate containing diazo resin and)
IT 7646-85-7D, Zinc chloride, reaction products with diazo resins 16941-11-0D, Ammonium hexafluorophosphate, reaction products with diazo resins 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction products with diazo resins
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plate containing)
IT 37321-70-3
RL: USES (Uses)
(presensitized lithog. plate substrate)

L12 ANSWER 27 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:157974 CAPLUS
DN 118:157974
OREF 118:26903a,26906a
ED Entered STN: 13 Apr 1993
TI Manufacture of lithographic printing plate using aqueous alkali solutions
IN Koike, Akinobu; Sakaki, Hirokazu
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-32
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04285965	A	19921012	JP 1991-49838	19910314
PRAI JP 1991-49838		19910314		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04285965	ICM	G03F007-32
	ICS	G03F007-00

IPCI G03F0007-32 [ICM,5]; G03F0007-00 [ICS,5]
IPCR G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB A presensitized lithog. plate, prepared by forming a photosensitive layer containing a diazo resin and an oleophilic polymer on an Al support the surface of which is electrolytically coarsened in a HCl solution using a.c. of c.d. 20-48 A/dm2, is imagewise exposed and developed with an aqueous alkali solution of pH ≥12 containing no organic solvent to give a lithog. printing plate. The printing plate shows good printing durability.

ST presensitized lithog plate plate making; alkali aq development lithog plate

IT Lithographic plates
(presensitized, electrochem. coarsening substrate of, for alkali development)

IT 37321-70-3
RL: USES (Uses)
(electrochem. coarsening of, presensitized lithog. plate substrate)

IT 125785-09-3DP, reaction products with zinc sulfate and anions 126033-29-2DP, reaction products with zinc sulfate and anions
RL: PREP (Preparation)
(preparation of, presensitized lithog. plate containing)

IT 132459-36-0P, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 143932-43-8P
RL: PREP (Preparation)
(preparation of, presensitized lithog. plate containing diazo resin and)

IT 7646-85-7D, Zinc chloride, reaction products with diazo resins 16941-11-0D, Ammonium hexafluorophosphate, reaction products with diazo resins 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction products with diazo resins
RL: DEV (Device component use); USES (Uses)
(presensitized lithog. plate containing)

L12 ANSWER 28 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:136271 CAPLUS
DN 118:136271
OREF 118:23313a,23316a
ED Entered STN: 30 Mar 1993
TI Photosensitive printing plate containing o-naphthoquinone diazide and acrylic copolymers
IN Tomita, Koji; Nakai, Hideyuki; Ishii, Nobuyuki; Sasaki, Mitsuru
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-023
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04155341	A	19920528	JP 1990-279997	19901018
PRAI	JP 1990-279997		19901018		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04155341	ICM	G03F007-023
	IPCI	G03F0007-023 [ICM,5]
	IPCR	G03F0007-023 [I,C*]; G03F0007-023 [I,A]

AB A photosensitive printing plate consists of a photosensitive composition containing (a) o-naphthoquinone diazide, (b) a copolymer having a structure-repeating unit [CH2CR1CO2(X)lZ] (R1 = H, Me; Z = alkyl (meth)acrylate-containing polymer component (number-average mol. weight≥100), where the alkyl group may have a C≥2 substituent; X = bivalent linkage group; l = 0,1], and (c)a copolymer having a structure-repeating unit [CR6R7CR8CONR9(X)nYOH (R6, R7 = H, halo, alkyl, aryl, CO2H or its salt; R8 = H, halo, alkyl, aryl; R9 = H, alkyl, aryl, aralkyl; Y = arom group; X = bivalent organic group; n = 0-5]. The photosensitive printing plate provides excellent resistance to processing chems. and lipophilicity towards fatty ink.

ST photosensitive printing plate; naphthoquinone diazide
photosensitive printing plate; acrylic copolymer
photosensitive printing plate

IT Printing plates
(photosensitive, containing naphthoquinone diazide and acrylic copolymers, for high chemical resistance and lipophilicity to ink)

IT 93641-24-8
RL: TEM (Technical or engineered material use); USES (Uses)
(acid-generating agent, photosensitive printing plate containing)

IT 146359-10-6
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitizer, photosensitive printing plate containing)

IT 34443-04-4P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation and copolymn. of, with Me methacrylate and vinylpyrrolidone)

IT 109921-98-4D, reaction products with glycidyl methacrylate
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of, as binder, photosensitive printing plate containing)

IT 29757-02-6P 146447-77-0P 146447-78-1P
146447-79-2P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(preparation of, as binder, photosensitive printing plate containing)

L12 ANSWER 29 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:113214 CAPLUS
DN 118:113214
OREF 118:19565a,19568a
ED Entered STN: 19 Mar 1993

TI Development of diazo resin-containing photosensitive material
IN Koike, Akinobu; Kita, Nobuyuki
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-30
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 04217255	A	19920807	JP 1990-403794	19901219
JP 2640573	B2	19970813		
PRAI JP 1990-403794		19901219		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 04217255	ICM	G03F007-30
	ICS	G03F007-00
	IPCI	G03F0007-30 [ICM,5]; G03F0007-00 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-30 [I,C*]; G03F0007-30 [I,A]

AB A presensitized lithog. plate, comprising a support with a coating of a photosensitive layer containing an aromatic diazonium compound having ≥1 group selected from CO2H, phenolic OH, sulfonic acid, sulfinic acid, and P oxygen acid groups, is imagewise exposed and developed with an aqueous alkali developing solution of pH 8-12 at 25° containing no organic solvent. The development can be carried out safely. Thus, an etched and anodized Al substrate was coated with a composition containing a diazo resin prepared from p-hydroxybenzoic acid, 4-diazodiphenylammonium sulfate, paraformaldehyde, and Na dibutylnaphthalenesulfonate, an oleophilic polymer, and additives, and the presensitized plate was imagewise exposed and developed with a Na silicate aqueous solution (pH 11.6) to give a printing plate producing high quality prints without greasing.
ST diazo resin photosensitive material development; lithog plate aq alkali development
IT Lithographic plates
(presensitized, diazo resin containing, developing method for, using no organic solvent)
IT 25155-30-0D, Sodium dodecylbenzenesulfonate, reaction products with diazo resin 25417-20-3D, Sodium dibutylnaphthalenesulfonate, reaction products with diazo resins 125785-09-3D, reaction products with sodium dibutylnaphthalenesulfonate 126033-29-2D, reaction products with sodium dibutylnaphthalenesulfonate 132459-36-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer 137843-04-0, 2-Hydroxyethyl

methacrylate-N-(4-hydroxyphenyl)acrylamide-methacrylic acid-methyl methacrylate copolymer 143932-42-7D, 4-Diazodiphenylammonium sulfate-formaldehyde-phenoxyacetic acid copolymer, reaction products with sodium dibutylnaphthalenesulfonate 143932-43-8 143963-00-2D, reaction products with sodium dibutylnaphthalene sulfonate 143963-01-3D, reaction products with sodium dodecylbenzenesulfonate 143963-04-6D, reaction products with sodium dibutylnaphthalene sulfonate 146248-74-0D, reaction products with dibutylnaphthalene sulfonate
RL: USES (Uses)
(aqueous alkali-developable photosensitive composition containing, for lithog. plate)

L12 ANSWER 30 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:581848 CAPLUS
DN 117:181848
OREF 117:31209a,31212a
ED Entered STN: 01 Nov 1992
TI Presensitized lithographic plate containing aromatic diazonium compound
IN Koike, Akinobu; Kita, Nobuyuki
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 42 pp.
CODEN: EPXXDW
DT Patent
LA English
IC ICM G03F007-021
ICS G03F007-115; G03F007-32
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 487343	A1	19920527	EP 1991-310746	19911121
	EP 487343	B1	19990428		
	R: DE, GB				
	JP 05005984	A	19930114	JP 1991-147327	19910619
PRAI	JP 1990-317510	A	19901121		
	JP 1991-147327	A	19910619		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 487343	ICM	G03F007-021
	ICS	G03F007-115; G03F007-32
	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]; G03F0007-115 [ICS,5]; G03F0007-09 [ICS,5,C*]; G03F0007-32 [ICS,5]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-09 [I,C*]; G03F0007-115 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	ECLA	G03F007/021; G03F007/115; G03F007/32A
JP 05005984	IPCI	G03F0007-00 [ICM,5]; G03F0007-021 [ICS,5]; G03F0007-016 [ICS,5,C*]; G03F0007-32 [ICS,5]

IPCR G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-09 [I,C*]; G03F0007-115 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]

AB A presensitized lithog. plate which can be developed with an aqueous alkaline solution substantially free from organic solvents comprises, on a substrate, a photosensitive layer comprising an aromatic diazonium compound having at least one group selected from the group consisting of carboxyl, phenolic hydroxyl, sulfonic, sulfinic, and phosphorus oxyacid groups and a mat layer having projections which are provided sep. from each other. The presensitized lithog. plate provides excellent vacuum contact with an original so that the time required for vacuum contact is shortened and fine halftone dots are faithfully reproduced.

ST presensitized lithog plate arom diazonium compd

IT Epoxy resins, uses
Phenolic resins, uses
Polyamides, uses
RL: USES (Uses)
(mat layers containing, for presensitized lithog. plates containing aromatic diazonium compds.)

IT Vinyl acetal polymers
RL: USES (Uses)
(butyrals, mat layers containing, for presensitized lithog. plates containing aromatic diazonium compds.)

IT Lithographic plates
(presensitized, containing photosensitive layers containing aromatic diazonium compds. and top mat layers for providing excellent vacuum contact with originals)

IT 9002-85-1, Poly(vinylidene chloride) 9003-01-4, Poly(acrylic acid) 9003-05-8, Polyacrylamide 9003-09-2, Poly(vinyl methyl ether) 9003-20-7, Poly(vinyl acetate) 9003-53-6 25322-68-3
RL: USES (Uses)
(mat layers containing, for presensitized lithog. plates containing aromatic diazonium compds.)

IT 116543-69-2 137843-04-0 143932-43-8
RL: USES (Uses)
(photosensitive compns. containing aromatic diazonium compds. and, for presensitized lithog. plates with top mat layers)

IT 89-25-8D, reaction products with diazomethoxydiphenylamine bisulfate-dihydroxyphosphinylpropanal-formaldehyde copolymer 9070-36-4D, reaction products with sodium dibutylnaphthalenesulfonate 16941-11-0D, reaction products with p-diazodiphenylamine sulfate-formaldehyde copolymer 25155-30-0D, reaction products with diazodiphenylamine sulfate-phenoxyacetic acid-formaldehyde copolymer 25417-20-3D, reaction products with p-diazodiphenylamine sulfate-aldehydic acids-formaldehyde copolymer 125785-09-3D, reaction products with sodium

dibutylnaphthalenesulfonate 126033-29-2D, reaction products with sodium dibutylnaphthalenesulfonate 136999-79-6D, reaction products with sodium dibutylnaphthalenesulfonate 143932-42-7D, reaction products with sodium dibutylnaphthalenesulfonate and sodium didecylbenzenesulfonate 143963-00-2D, reaction products with sodium dibutylnaphthalenesulfonate 143963-01-3D, reaction products with phenylmethylpyrazolone and sodium dodecylbenzenesulfonate 143963-04-6D, reaction products with sodium dibutylnaphthalenesulfonate
RL: USES (Uses)
(photosensitive compns. containing, for presensitized lithog. plates with top mat layers)

L12 ANSWER 31 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:417330 CAPLUS
DN 117:17330
OREF 117:3031a,3034a
ED Entered STN: 11 Jul 1992
TI Aromatic diazo compound condensed resin composition for photosensitive printing plate
IN Kamiya, Akihiko
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-021
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 03089250	A	19910415	JP 1989-225599	19890831
PRAI JP 1989-225599		19890831		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 03089250	ICM	G03F007-021
	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]

AB The title composition contains a condensed resin from an aromatic compound substituted with CO2H and/or OH and an aromatic diazo compound having a counter anion of a long chain alkyl-substituted aromatic sulfonic acid. Thus, p-hydroxybenzoic acid, 4-diazo-4'-methoxydiphenylamine sulfate, and paraformaldehyde were treated then mixed with Na dodecylbenzenesulfonate to give the title diazo resin. Then, a mixture of the resin, N-(4-hydroxyphenyl)acrylamide-acrylonitrile-Et acrylate-methacrylic acid copolymer, Victria Pure Blue BOH, Jurymer AC 10L, malic acid, and 2-methoxyethanol was coated on an Al plate, imagewise exposed, and developed to give a lithog. printing plate, which gave blue clear printed image without staining.
ST photosensitive lithog printing plate; azo formalin resin photosensitive printing; hydroxybenzoic acid azomethoxydiphenylamine formalin copolymer; alkylsulfonic acid counter

anion
IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(diazo-substituted, photosensitive resin containing, for printing plate, prevention of staining in)
IT Printing plates
(photosensitive resin for, condensed azo compound having alkylsulfonic acid anion as, prevention of staining in)
IT 137020-35-0
RL: TEM (Technical or engineered material use); USES (Uses)
(diazo condensed resin containing, for photosensitive printing plate, prevention of staining in)
IT 125766-04-3D, reaction products with dodecylbenzenesulfonic acid salt
140939-73-7D, reaction products with dioctylnaphthalenesulfonic acid salt
140939-74-8D, reaction products with dodecylbenzenesulfonic acid salt
140939-76-0D, reaction products with dodecylbenzenesulfonic acid salt
140939-77-1D, reaction products with dioctylnaphthalenesulfonic acid
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin containing, for printing plate, prevention of staining in)
IT 27176-87-0D, reaction products with copolymers 140946-22-1D, reaction products with copolymers
RL: TEM (Technical or engineered material use); USES (Uses)
(photosensitive resins containing, for printing plates, prevention of staining in)

L12 ANSWER 32 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:48955 CAPLUS
DN 116:48955
OREF 116:8307a,8310a
ED Entered STN: 08 Feb 1992
TI Light-sensitive composition and presensitized plate for use in making lithographic printing plates
IN Kamiya, Akihiko; Koike, Akinobu; Imai, Masanori
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 48 pp.
CODEN: EPXXDW
DT Patent
LA English
IC ICM G03F007-021
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

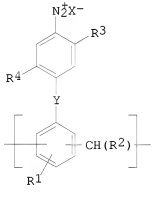
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 399755	A1	19901128	EP 1990-305481	19900521
	EP 399755	B1	19940330		
	R: DE, GB				
	JP 03002867	A	19910109	JP 1989-137890	19890531
	JP 03002868	A	19910109	JP 1989-137891	19890531
	US 5112743	A	19920512	US 1990-523997	19900516
	JP 04018559	A	19920122	JP 1990-128379	19900518
PRAI	JP 1989-130493	A	19890524		
	JP 1989-137890	A	19890531		
	JP 1989-137891	A	19890531		

JP 1990-100886 19900417

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 399755	ICM	G03F007-021
	ICMI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]
JP 03002867	IPCI	G03F0007-00 [ICM,5]; G03F0007-021 [ICS,5]; G03F0007-016 [ICS,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-11 [I,C*]; G03F0007-11 [I,A]
JP 03002868	IPCI	G03F0007-00 [ICM,5]; G03F0007-021 [ICS,5]; G03F0007-016 [ICS,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]
US 5112743	IPCI	G03C0001-60 [ICM,5]; G03C0001-52 [ICM,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]
	NCL	430/175.000; 430/176.000; 430/281.100; 430/287.100
	ECLA	G03F007/021
JP 04018559	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]

GI



I

AB A photosensitive composition for use in preparing a presensitized lithog. plate comprises a diazo resin which has ≥1 repeating unit represented by the formula I (R1 = H, OH, alkyl, alkoxy, carboxyl, or a carboxy ester group; R2 = carboxyl or a group having ≥1 carboxyl group; R3, R4 = H, alkyl, or alkoxy; X- = an anion; Y = NH, O, or S), a polymerizable compound having an ethylenically unsatd. bond, a photopolymerizable initiator, and an alkaline solution-soluble or -swellable polymer having film-forming ability. The diazo resin is readily prepared by

condensing a monomer with a 4-diazodiphenylamine, 4-diazodiphenyl ether, or 4-diazodiphenyl sulfide skeleton with an aldehyde having the formula HO2CY1CHO (Y1 = single bond, a divalent aliphatic or aromatic hydrocarbon group, or a divalent heterocyclic group). A presensitized lithog. plate using the photosensitive composition shows high sensitivity and good adhesion between the photosensitive composition and the substrate and provides a lithog. plate having high printing durability and free of background contamination.

ST diazo resin presensitized lithog plate

IT Lithographic plates
(presensitized, photosensitive compns. containing diazo resins for)

IT 90-94-8, Michler's ketone 811-32-5 4986-89-4, Pentaerythritol tetraacrylate 15625-89-5, Trimethylolpropane triacrylate 19878-93-4 63149-07-5 77084-52-7 77945-59-6 77945-61-0, Methyl methacrylate-N-(2-(methacryloyloxy)ethyl)-2,3-dimethylmaleimide-methacrylic acid copolymer 90216-38-9, Allyl methacrylate-methacrylic acid copolymer 109115-61-9 115168-59-7 127115-35-9 131663-16-6 131663-21-3 131690-07-8 131690-08-9 131690-09-0 131690-10-3 137020-32-7 137020-33-8 137020-34-9 137020-35-0
RL: USES (Uses)
(photosensitive compns. containing diazo resins and, for presensitized lithog. plates)

IT 6628-37-1D, reaction products with diazodiphenylamine hydrogen sulfate-acetaldehyde-glyoxylic acid copolymer 17084-13-8D, reaction products with formaldehyde-diazodiphenylamine-aldehydic acid copolymer 25155-30-0D, reaction products with diazodiphenylamine hydrogen sulfate-aldehyde-aldehydic acid copolymer 136999-79-6D, reaction products with sodium dodecylbenzenesulfonate 136999-80-9D, reaction products with sodium dodecylbenzenesulfonate 137020-27-0D, reaction products with sodium 2-methoxy-4-hydroxy-5-benzoylbenzenesulfonate 137020-28-1D, reaction products with potassium hexafluorophosphate 137020-31-6D, reaction products with potassium hexafluorophosphate
RL: USES (Uses)
(photosensitive compns. containing, for presensitized lithog. plates)

L12 ANSWER 33 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:31559 CAPLUS
DN 116:31559
OREF 116:5249a,5252a
ED Entered STN: 24 Jan 1992
TI Imaging method by transfer for color proof preparation
IN Shimizu, Kunio; Sasa, Nobumasa; Watabe, Manabu; Urano, Toshiyoshi; Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10; G03F007-004
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other

Reprographic Processes)
Section cross-reference(s): 37

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 03154057	A	19910702	JP 1989-294434	19891113
PRAI JP 1989-294434		19891113		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 03154057	ICM	G03F007-004
	ICS	G03F003-10; G03F007-004
	IPCI	G03F0007-004 [ICM,5]; G03F0003-10 [ICS,5]; G03F0007-004 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]

AB The title method involves imagewise exposure of materials having a substrate, a rubber layer, a parting layer, and a photosensitive transparent layer containing o-quinonediazide compound and polymers having aromatic OH group in side chains with softening point ≤70°, developing, appln. of toners on the material, and transfer of toner image to receptor sheet. These materials for fabrication of color proofs provide images closely alike printed materials, by transfer mainly by pressure. Thus, a PET film was coated with a 20-μm-thick isoprene-styrene rubber layer, and then with a silicone parting layer. A copolymer was obtained by reaction of N-(4-p-hydroxyphenyl)-acrylamide (prepared from p-hydroxyaniline and acrylic chloride) 26.58, Bu acrylate 44.86, and 2-ethylhexyl thioglycolate 3.57 g. A composition containing 1.15 g ester of 2,3,4-trihydroxybenzoquinone with 1,2-naphthoquinonediazide-5-sulfonic acid, and 3.85 g above copolymer, and Et cellosolve was applied on the rubber layer and dried to form a 1-μm-thick layer. These materials were sep. exposed to color-separated images, were rubbed with resp. toner consisting of 1:1 mixture of cellulose acetate particles and particles of cellulose acetate containing carbon black or coloring agents. Successive transfer of resp. images to an art paper sheet by pressurized roller gave fine color proof. Equally good result was obtained using less smooth paper sheet.

ST imaging material color pressure transfer

IT Photoimaging compositions and processes
(for color proofs, transfer of tonered color-separated images, similarity to printed products)

IT Rubber, synthetic
RL: PREP (Preparation)
(photoimaging materials having layer of, for imaging by transfer of toner images, for preparation of color proofs, Cariflex TR1107 as)

IT 128319-90-4 137885-69-9

RL: USES (Uses)
(photoimaging materials containing quinonediazide compds. and, for color proof preparation, transfer of toner image)
IT 5610-94-6
RL: USES (Uses)
(photoimaging materials containing, for color proof preparation, imaging by successive toner image transfer)

L12 ANSWER 34 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:31558 CAPLUS
DN 116:31558
OREF 116:5249a,5252a
ED Entered STN: 24 Jan 1992
TI Materials for imaging by pressure transfer
IN Shimizu, Kunio; Sasa, Nobumasa; Watabe, Manabu; Urano, Toshiyoshi; Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 37
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 03154056	A	19910702	JP 1989-294433	19891113
PRAI JP 1989-294433		19891113		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 03154056	ICM	G03F007-004
	ICS	G03F003-10
	IPCI	G03F0007-004 [ICM,5]; G03F0003-10 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]

AB The title materials have a substrate, a rubber layer, a parting layer, and a photosensitive colored layer containing o-quinonediazide compound and polymers having aromatic OH group in side chains with softening point ≤70°. These materials for fabrication of color proofs provide images closely alike printed materials, by transfer by pressure not using heat. Thus, a PET film was coated with a 20-μm-thick isoprene-styrene rubber layer, and then with a silicone parting layer. A copolymer was obtained by reaction of N-(4-p-hydroxyphenyl)-acrylamide (prepared from p-hydroxyaniline and acrylic chloride) 26.58, Bu acrylate 44.86, and 2-ethylhexyl thioglycolate 3.57 g. A composition containing ester of 2,3,4-trihydroxybenzoquinone with 1,2-naphthoquinonediazide-5-sulfonic acid 1.15, above copolymer 3.85, carbon black 0.99 g and Et cellosolve was

applied on the rubber layer and dried to form a 1-μm-thick layer. Three other materials were prepared using cyan, magenta or yellow dye instead of carbon black. Exposure of these materials through color-separated positives and developing gave 4 color-separated images. Transfer of the images to an art paper sheet by pressurized roller gave fine color proof. Equally good result was obtained using less smooth paper sheet.
ST imaging material color pressure transfer
IT Photoimaging compositions and processes
(for color proofs, transfer of color-separated images by pressure, similarity to printed products)
IT Rubber, synthetic
RL: PREP (Preparation)
(photoimaging materials having layer of, for image transfer by pressure, for preparation of color proofs, Cariflex TR1107 as)
IT 137885-69-9
RL: USES (Uses)
(photoimaging materials containing quinonediazide compds. and, for color proof preparation, image transfer by pressure)
IT 5610-94-6
RL: USES (Uses)
(photoimaging materials containing, for color proof preparation, image transfer by pressure)

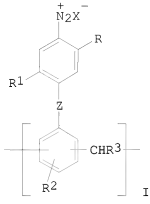
L12 ANSWER 35 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:13408 CAPLUS
DN 116:13408
OREF 116:2315a,2318a
ED Entered STN: 11 Jan 1992
TI Image-forming method using diazo resin photosensitive layer for organic-free solvent development
IN Kamiya, Akihiko
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-021
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 03163550	A	19910715	JP 1989-303704	19891122
PRAI JP 1989-303704		19891122		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 03163550	ICM	G03F007-021
	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]

GI



AB The title method comprises imagewise exposing the photosensitive layer containing copolycondensed diazo resin having I and Z1CHR4 (R, R1-2 = H, alkyl, alkoxy; R3-4 = H, alkyl, phenyl; X = PF6, BF4, Z = NH, S, O; Z1 = (substituted) phenylene or naphthylene with ≥1 substituent selected from sulfinic acid, sulfinate, sulfonic acid, sulfonate) as structural units, and developing with an aqueous alkali developer free of organic solvents.

The method gives clear images without stains. Thus, coarsened Al plate was coated with a photosensitive layer containing a reaction product of Na benzensulfonate-4-diazo-4'-methoxydiphenylammonium hexafluorophosphate-paraformaldehyde copolymer and zinc chloride, and acrylonitrile-Et acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid copolymer to give a presensitized lithog. plate, which was developed using an aqueous alkali developer containing Na silicate.

ST presensitized lithog plate diazo resin; alkali aq developer lithog plate

IT Lithographic plates
(presensitized, processing of, containing diazo resin, aqueous alkali developer for)

IT 77833-95-5, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid copolymer 136826-56-7D, reaction product with zinc chloride 137843-01-7D, reaction product with zinc chloride 137843-02-8D, reaction product with zinc chloride 137843-03-9D, reaction product with zinc chloride 137843-04-0 138007-88-2D, reaction product with zinc chloride
RL: USES (Uses)
(photosensitive layer containing, in presensitized lithog. plate)

L12 ANSWER 36 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1991:523882 CAPLUS
DN 115:123882
OREF 115:21043a,21046a
ED Entered STN: 23 Sep 1991
TI Preparation of transferred color images

IN Shimizu, Kunio; Sasa, Nobumasa; Watabe, Manabu; Urano, Toshoshi; Mayama, Shinya; Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02275454	A	19901109	JP 1989-97067	19890417
PRAI JP 1989-97067		19890417		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02275454	ICM	G03F007-004
	ICS	G03F003-10
	IPCI	G03F0007-004 [ICM,5]; G03F0003-10 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]

AB In the title preparation by an imagewise exposure of an image-forming material having on a support an image-forming layer containing a coloring agent and a photosensitive composition, developing the exposed material to form color images, and transferring the color images to a receptor to form transferred images, the photosensitive composition contains a graft copolymer having an acrylic acid polymer on its branched components.
ST color proof photoimaging compn polymer
IT Printing plates
(color proofs for, image-forming materials with photosensitive compns. containing graft polymer binders for producing)
IT 128417-61-8, Butyl acrylate polymer
RL: USES (Uses)
(image-forming materials containing, for forming color proofs)
IT 135732-41-1 135756-89-7 136005-34-0
RL: USES (Uses)
(image-forming materials with photosensitive compns. containing, for forming color proofs)

L12 ANSWER 37 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1991:111929 CAPLUS
DN 114:111929
OREF 114:18885a,18888a
ED Entered STN: 23 Mar 1991
TI Preparation of lithographic plates comprising development using aqueous alkali
IN Fumiya, Shinichi; Katahashi, Eriko; Uehara, Masabumi; Matsubara, Shinichi
PA Mitsubishi Kasei Corp., Japan; Konica Co.
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF

DT Patent
LA Japanese
IC ICM G03F007-00
ICS G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02189544	A	19900725	JP 1989-10738	19890119
PRAI JP 1989-10738		19890119		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02189544	ICM	G03F007-00
	ICS	G03F007-004
	IPCI	G03F0007-00 [ICM,5]; G03F0007-004 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]

AB A presensitized lithog. plate has a photosensitive layer containing a copolycondensation product comprising an aromatic compound having ≥1 group selected from carboxyl, OH, sulfonic acid, sulfonic acid base, sulfinic acid, and sulfinic acid base groups and an aromatic diazonium compound as structural units, and an oleophilic polymer on a support. The plate is imagewise exposed and then developed with an aqueous alkali of pH ≥12 containing no organic solvent to give a lithog. plate. The method provides high quality lithog. plates without using organic solvents. Thus, a pretreated Al plate was coated with a composition containing a diazo resin prepared from Na benzenesulfonate, 4-diazo-4'-methoxydiphenylamine.H2SO4, and paraformaldehyde and N-(4-hydroxyphenyl)methacrylamide-acrylonitrile-Me methacrylate-Et acrylate-methacrylic acid copolymer, and the obtained plate was imagewise exposed and developed with an aqueous solution containing Na silicate, NaOH, exposed and developed with an aqueous solution containing Na silicate, NaOH, and Na2SO3 to give a lithog. plate.

ST presensitized lithog plate diazo resin; oleophilic polymer presensitized lithog plate; alkali soln development lithog plate

IT Lithographic plates
(containing aromatic diazonium compds., developed with aqueous alkali)

IT 1310-73-2, Sodium hydroxide, uses and miscellaneous 6834-92-0 7757-83-7, Sodium sulfite
RL: USES (Uses)
(lithog. plate developing solution containing)

IT 77833-95-5, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid copolymer 125785-09-3, 4-Diazodiphenylamine sulfate-p-hydroxybenzoic acid-paraformaldehyde copolymer 126033-28-1 126033-29-2, 4-Diazodiphenylamine sulfate-paraformaldehyde-sodium benzensulfonate copolymer 126034-88-6, 4-Diazo-4'-methoxydiphenylamine

sulfate-paraformaldehyde-sodium benzenesulfonate copolymer 132459-36-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methacrylic acid-methyl methacrylate copolymer
RL: USES (Uses)
(lithog. plate photosensitive layer using)

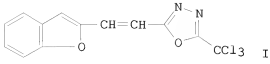
L12 ANSWER 38 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1990:621404 CAPLUS
DN 113:221404
OREF 113:37235a,37238a
ED Entered STN: 08 Dec 1990
TI Photosensitive compositions for lithographic plates
IN Uehara, Masabumi; Matsubara, Shinichi; Fumiya, Shinichi; Katahashi, Eriko
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-021
ICS C08F299-00; C08L101-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 02139558	A	19900529	JP 1988-265844	19881021
	EP 353873	B1	19931229	EP 1989-306904	19890706
	R: DE, FR, GB				
	US 5009981	A	19910423	US 1990-585048	19900920
PRAI	JP 1988-172241	A1	19880711		
	JP 1988-172242	A1	19880711		
	JP 1988-172240	A	19880711		
	US 1989-376517	B2	19890707		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02139558	ICM	G03F007-021
	ICS	C08F299-00; C08L101-00
	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]; C08F0299-00 [ICS,5]; C08L0101-00 [ICS,5]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]; C08F0290-00 [I,C*]; C08F0290-00 [I,A]; C08F0299-00 [I,C*]; C08F0299-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
EP 353873	IPCI	G03F0007-021 [ICM,5]; G03F0007-016 [ICM,5,C*]
US 5009981	IPCI	G03C0001-52 [ICM,5]
	IPCR	G03F0007-016 [I,C*]; G03F0007-021 [I,A]
	NCL	430/175.000; 430/176.000; 430/177.000
	ECLA	G03F007/021

GI



I

AB The title compns. contain aromatic compds. with polymerizable unsatd. bonds and a condensed diazo resin containing aromatic diazonium compds. These compns. may also contain photopolymn. initiators, photopolymerizable monomers, and/or polymer binders having ≥1 polymerizable unsatd. bond. Excellent performance, especially high resistance to chems. and stability of sensitivity toward oxygen, are obtained. Thus, a diazo resin was obtained from 4-hydroxyphenylmethacrylamide, 4-diazodiphenylamine sulfate, and HCHO, and was converted to a PF6 salt. A composition containing this resin, a 133.4:8.6 (weight) allyl methacrylate-methacrylic acid copolymer (unsatd. binder), the photopolymn. initiator I, trimethylolpropane triacrylate, and other agents, was applied onto an anodized and sealed Al plate, to obtain a lithog. plate. This plate showed a sensitivity unaffected by air pumping at the time of exposure, and the obtained printing plate was highly resistant to a plate cleaning mixture

ST lithog plate diazo oxygen effect; binder unsatd photosensitive lithog plate

IT Lithographic plates
(photosensitive, diazo compound-based, with resistance to oxygen)

IT 59592-92-6, Acrylonitrile-2-hydroxyethyl methacrylate-methyl methacrylate-methacrylic acid copolymer 77833-95-5, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide- methacrylic acid copolymer 90216-38-9, Allyl methacrylate-methacrylic acid copolymer 96536-79-7 122988-13-0, Acrylonitrile-ethyl acrylate-N-(4-hydroxyphenyl)methacrylamide-methyl acrylate-methacrylic acid copolymer 129542-22-9
RL: USES (Uses)
(binder, lithog. plates containing diazo compds. and, with resistance to oxygen)

IT 129343-24-4 130139-01-4 130139-02-5 130139-04-7 130139-05-8 130159-78-3
RL: USES (Uses)
(lithog. plates containing, with resistance to oxygen)

IT 93641-24-8 97802-84-1
RL: USES (Uses)
(photopolymn. initiator, lithog. plates containing)

L12 ANSWER 39 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1990:562576 CAPLUS
DN 113:162576

OREF 113:27451a,27454a
ED Entered STN: 27 Oct 1990
TI Preparation of color proofs using color image-forming material
IN Watabe, Manabu; Sasa, Nobumasa; Shimizu, Kunio; Urano, Toshoshi; Mayama, Shinya; Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10; G03F007-16
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02003045	A	19900108	JP 1988-151594	19880620
PRAI JP 1988-151594		19880620		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02003045	ICM	G03F007-004
	ICS	G03F003-10; G03F007-16
	IPCI	G03F0007-004 [ICM,5]; G03F0003-10 [ICS,5]; G03F0007-16 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-16 [I,C*]; G03F0007-16 [I,A]

AB The title preparation is effected by forming a colored photosensitive layer containing at least a photosensitive composition and a coloring agent using a coating liquid containing cyclohexanone.
ST color proof imaging material manuf; cyclohexanone imaging material color proof
IT Carbon black, uses and miscellaneous
RL: USES (Uses)
(color photoimaging compns. containing, for color proof preparation)
IT Photoimaging compositions and processes
(containing photosensitive materials and coloring agents for color proofing)
IT Printing plates
(production of, photoimaging compns. for color proofing in)
IT 108-94-1, Cyclohexanone, uses and miscellaneous
RL: USES (Uses)
(coating solns. containing, for color photoimaging layers for color proof preparation)
IT 523-42-2, Cyanine Blue 4920 4986-89-4, Pentaerythritol tetraacrylate 5281-04-9 6358-85-6, Seika Fast Yellow H 7055 35464-74-5 68510-93-0 122024-02-6
RL: USES (Uses)
(color photoimaging compns. containing, for color proof preparation)
IT 9003-35-4, Formaldehyde-phenol copolymer
RL: USES (Uses)
(novolak, color photoimaging compns. containing, for color proof preparation)

L12 ANSWER 40 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1990:506480 CAPLUS
DN 113:106480
OREF 113:17855a,17858a
ED Entered STN: 16 Sep 1990
TI Color image-forming material and color proofing method using the material
IN Watabe, Manabu; Sasa, Nobumasa; Shimizu, Kunio; Urano, Toshoshi; Mayama, Shinya; Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F003-10
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02018563	A	19900122	JP 1988-168324	19880706
PRAI JP 1988-168324		19880706		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02018563	ICM	G03F007-004
	ICS	G03F003-10
	IPCI	G03F0007-004 [ICM,5]; G03F0003-10 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]

AB In the title material having on a support a colored photosensitive layer containing at least a photosensitive composition, a binder, and a coloring agent, the photosensitive layer contains the coloring agent 10-30%. The title method is effected by at least an imagewise exposure and development of the color image-forming material to form color images and then transferring the color images to an image receptor.
ST photosensitive color proofing material; dye image transfer color proofing
IT Carbon black, uses and miscellaneous
RL: USES (Uses)
(color proofing materials having photosensitive layers containing)
IT Printing plates
(production of, color proofing in, photosensitive materials for)
IT 523-42-2, Cyanine Blue 4920 4986-89-4, Pentaerythritol tetraacrylate 5281-04-9 6358-85-6, Seikafast Yellow H 7055 9003-35-4, Formaldehyde-phenol copolymer 68510-93-0 128888-19-7
RL: USES (Uses)
(color proofing materials having photosensitive layers containing)
IT 9003-07-0, Polypropylene 25038-59-9, PET (polyester), uses and miscellaneous
RL: USES (Uses)

(supports, for photosensitive color proofing materials)

L12 ANSWER 41 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1990:468483 CAPLUS
DN 113:68483
OREF 113:11405a,11408a
ED Entered STN: 17 Aug 1990
TI Formation of transferred images
IN Shimizu, Kunio; Sasa, Nobumasa; Watabe, Manabu; Ide, Koji; Mayama, Shinya;
Masuda, Tetsuya
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-039
ICS G03F003-10; G03F007-004
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02069749	A	19900308	JP 1988-222973	19880906
JP 2707286	B2	19980128		
PRAI JP 1988-222973		19880906		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 02069749	ICM	G03F007-039
	ICS	G03F003-10; G03F007-004
	IPCI	G03F0007-039 [ICM,5]; G03F0003-10 [ICS,5]; G03F0007-004 [ICS,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]

AB The title method involves image transfer from materials with a support, and a photosensitive layer containing coloring agents, pos.-working photosensitive materials and binder polymers having phenolic group-containing side chains. This method provides color proofs closely simulating the printed images, by simple transfer process. Thus, PET films coated with polypropylene were sep. coated with 1 of 4 compns., resp. containing 2,3,4-trihydroxybenzophenone esterified with 1,2-naphthoquinone-(2)-diazide-5-sulfonic acid, 26.58:44.86:3.57 (weight) N-(4-hydroxyphenyl)acrylamide-Bu acrylate-2-ethylhexyl thioglycolate copolymer, and a pigment (black, cyan, magenta or yellow). Single-color images obtained by exposure of each films to color-separated image and development were transferred to an art paper sheet, to obtain a colorproof closely similar to printed images.
ST color transfer sheet polymer binder; printing color proof transfer material

IT Printing, nonimpact
(thermal-transfer, for colorproofs, phenol-containing polymer binders contained in, close similarity to printed image)
IT 7659-86-1D, ether with Bu acrylate-hydroxyphenyl acrylamide copolymer 128319-88-0D, ether with ethylhexyl mercaptoacetic acid 128319-89-1 128319-90-4
RL: USES (Uses)
(binder, colorproof sheet containing, for close similarity to printed image)
IT 68510-93-0
RL: USES (Uses)
(photosensitive colorproof transfer sheet containing polymer binders and)
IT 920-46-7
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with hydroxyaniline, binder polymer for colorproof transfer sheet from)
IT 123-30-8, p-Hydroxyaniline
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with methacryloyl chloride, binder polymer for colorproof
transfer sheet from)

L12 ANSWER 42 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1989:487493 CAPLUS
DN 111:87493
OREF 111:14563a,14566a
ED Entered STN: 03 Sep 1989
TI Colored image-forming material and process for forming colored images
IN Ide, Hiroshi; Mayama, Shinya; Masuda, Tetsuya; Sasa, Nobumasa; Watanabe, Manabu; Shimizu, Kunio
PA Mitsubishi Kasei Corp., Japan; Konica Co.
SO PCT Int. Appl., 43 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
IC ICM G03C001-00
ICS G03C001-72; G03C005-08; G03F003-10; B44C001-17
CC 74-7 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 8804068	A1	19880602	WO 1987-JP916	19871126
	W: US				
	RW: AT, BE, CH, DE, FR, GB, IT, LU, NL, SE				
	JP 63133143	A	19880604	JP 1986-281443	19861126
	JP 01090437	A	19890406	JP 1987-248564	19871001
	JP 01102546	A	19890420	JP 1987-261129	19871016
	EP 291537	A1	19881123	EP 1987-907818	19871126
	EP 291537	B1	19930908		
	R: DE, FR, GB, IT, NL				
PRAI	JP 1986-281443	A	19861126		
	JP 1987-248564	A	19871001		
	JP 1987-261129	A	19871016		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 8804068	ICM	G03C001-00
	ICS	G03C001-72; G03C005-08; G03F003-10; B44C001-17
	IPCI	G03C0001-00 [ICM,4]; G03C0001-72 [ICS,4]; G03C0005-08 [ICS,4]; G03F0003-10 [ICS,4]; B44C0001-17 [ICS,4]
	IPCR	G03F0003-10 [I,C*]; G03F0003-10 [I,A]
	ECLA	G03F003/10
JP 63133143	IPCI	G03C0001-00 [ICM,4]; G03C0001-72 [ICS,4]; G03C0005-08 [ICS,4]
	IPCR	G03F0007-20 [I,C*]; G03F0007-20 [I,A]; G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-09 [I,C*]; G03F0007-09 [I,A]
JP 01090437	IPCI	G03C0001-00 [ICM,4]; G03C0001-00 [ICS,4]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-09 [I,C*]; G03F0007-09 [I,A]
JP 01102546	IPCI	G03C0001-00 [ICM,4]; G03C0001-00 [ICS,4]; G03F0003-10 [ICS,4]
	IPCR	G03C0001-00 [I,C*]; G03C0001-00 [I,A]; G03F0003-10 [I,C*]; G03F0003-10 [I,A]; G03F0007-09 [I,C*]; G03F0007-09 [I,A]
EP 291537	IPCI	G03C0001-00 [ICM,4]; G03C0001-72 [ICS,4]; G03C0005-08 [ICS,4]; G03F0003-10 [ICS,4]; B44C0001-17 [ICS,4]
	IPCR	G03F0003-10 [I,C*]; G03F0003-10 [I,A]

AB The title materials providing high-quality transfer color images comprise a transparent support, a heat-fusible layer containing alicyclic saturated hydrocarbyl group-containing resin, and photosensitive composition-containing color recording layer in that order, wherein the recording layer contains polymers of repeating unit -C(R1)(R2)C(R3)[CON(R4)XnYOH]- [R1, R2 = H, alkyl, carboxy; R3 = H, halogen, alkyl; R4 = H, alkyl, Ph, aralkyl; X = divalent organic group linking N and a C atom in aromatic ring; n = 0.1; Y = (un)substituted phenylene, naphthylene]. A biaxially stretched PET film was coated 7 μm thick (dry) with a fusible layer comprising Arkon P-90 60, Arkon P-100 15, Tufprene A 25, and toluene 75 parts, dried at 60° for 5 min, coated 1.5 μm thick (dry) with a color recording layer from a 50%-solids 8.85:2.65:33.1 (monomer ratio in g) N-(4-hydroxyphenyl)methacrylamide-acrylonitrile-Me acrylate copolymer (I) solution 66.2, 2,3,4-tris(1-oxo-2-diazo-1,2-dihydro-4-naphthylsulfonyloxy)benzophenone photosensitizer 8.4, cyanine blue 4927 46, and methyl Cellosolve 273 parts, dried at 60° for 5 min, exposed from the film side to a 1 kW metal halide light source, developed in aqueous Na2CO3 (pH 9) at 25°, and the image formed was heat transferred to paper at 110°/5 kg/cm2 at 70 cm/min to give a print-quality image, while a control using m-cresol novolak in place of I was not developable by the alkali and showed poor storability at 55°.

ST petroleum resin alicyclic photothermal transfer; acrylic polymer photothermal transfer; petroleum resin fusible photothermal transfer

IT Photothermographic copying
(photocurable acrylic polymers and fusible petroleum presence in)
IT Petroleum resins
RL: USES (Uses)
(alicyclic, hydrogenated, fusible layers containing, in photothermal transfer)
IT Rubber, butadiene-styrene, uses and miscellaneous
RL: USES (Uses)
(block, fusible layers containing, in photothermal transfer imaging material, Tufprene A)
IT Petroleum resins
RL: USES (Uses)
(hydrogenated, fusible layers containing, in photothermal transfer imaging)
IT 110586-14-6 115324-80-6 122024-02-6
RL: USES (Uses)
(photocurable, in color photothermal transfers)
IT 106107-54-4
RL: USES (Uses)
(rubber, block, fusible layers containing, in photothermal transfer imaging material, Tufprene A)

L12 ANSWER 43 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1989:240258 CAPLUS
DN 110:240258
OREF 110:39695a,39698a
ED Entered STN: 25 Jun 1989
TI Quinonediazide-containing photosensitive composition for positive-working presensitized lithographic plate
IN Yamamoto, Takeshi; Goto, Sei; Nakai, Hideyuki; Tomiyasu, Hiroshi; Kobayashi, Yoshiko
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03C001-72
ICS G03F007-08
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 63311247	A	19881220	JP 1987-147327	19870612
PRAI JP 1987-147327		19870612		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 63311247	ICM	G03C001-72
	ICS	G03F007-08
	IPCI	G03C0001-72 [ICM,4]; G03F0007-08 [ICS,4]
	IPCR	G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]

AB The composition comprises quinonediazide compound, a compound generating radical by

activating beam, and vinylic copolymer. N-(4-Hydroxyphenyl)acrylamide, prepared from methacrylic chloride and p-hydroxyaniline, was treated with acrylonitrile, Et acrylate, and Me methacrylate to give a binder. Al plate was coated with a composition containing acetone-pyrogallol copolymer naphthoquinone-(1,2)-diazide-(2)-5-sulfonate, the binder, 2-trichloromethyl-5-(p-butoxystyryl)-1,3,4-oxadiazol, Victoria Pure Blue BOH, and p-tert-octylphenol-formaldehyde copolymer naphthoquinone-(1,2)-diazide-(2)-5-sulfonate and UV.-irradiated to give a lithog. plate showing excellent overdevelopability, underdevelopability, and chemical resistance to plate-cleaners.

ST lithog plate quinonediazide photosensitive layer

IT Lithographic plates
(presensitized, pos.-type, containing quinonediazides)

IT 123-30-8, p-Hydroxyaniline
RL: USES (Uses)
(methacrylation of, acrylamide derivative from)

IT 119553-98-9P
RL: PREP (Preparation)
(photosensitive layer using, binder, preparation of, for pos.-type lithog. plate)

IT 68584-99-6 84135-66-0
RL: USES (Uses)
(photosensitive layer using, for pos.-type lithog. plate, preparation of)

IT 72015-26-0
RL: USES (Uses)
(radical source, photosensitive layer using, for pos.-type lithog. plate)

IT 920-46-7, Methacrylic chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with hydroxyaniline, acrylamide derivative from)

L12 ANSWER 44 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1989:202929 CAPLUS
DN 110:202929
OREF 110:33524h,33525a
ED Entered STN: 26 May 1989
TI Photosensitive compositions with good chemical resistance and ink adhesion
IN Yamamoto, Takeshi; Goto, Sei; Tomiyasu, Hiroshi; Kobayashi, Yoshiko
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03C001-72
ICS G03F007-08
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

PI JP 63183441 A 19880728 JP 1987-15851 19870126
PRAI JP 1987-15851 19870126
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 63183441	ICM	G03C001-72
	ICS	G03F007-08
	IPCI	G03C0001-72 [ICM,4]; G03F0007-08 [ICS,4]
	IPCR	G03C0001-72 [I,C*]; G03C0001-72 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]

AB The title compns., suitable for pos.-type lithog. plates, comprise a polymer of repeating unit -CR1R2CR3(CONR4XnYOH)- [R1, R2 = H, halogen, alkyl, aryl, carboxy or salt; R3 = H, halogen, alkyl, aryl; R4 = H, alkyl, aryl, aralkyl; Y = (un)substituted aromatic group; X = divalent organic group; n = 0-5] and substituted phenol R5R6R7C6H2OH (R5, R6 = H, alkyl, halogen; R7 = C≥2 alkyl, cycloalkyl)-aldehyde condensate and/or its ester with o-naphthoquinonediazide sulfonic acid. A typical composition, providing printing plates with good resistance to cleaners and oils and good printability, comprised m- and p-cresol-HCHO novolak o-naphthoquinonediazide-5-sulfonate (weight-average mol. weight 1700) 3.6, 106.4:32:7.2:73.2 (feed weight ratio) N-(4-hydroxyphenyl)acrylamide-acrylonitrile-Et acrylate-Me methacrylate copolymer binder 4.8, p-tert-butylphenol-BzH condensate o-naphthoquinonediazide-5-sulfonate 0.168, Victoria Pure Blue BOH 0.084, and 2-trichloromethyl-5-[β-(2-benzofuryl)vinyl]-1,3,4-oxadiazole 0.126 g in 67 mL Et Cellosolve and 33 mL methyl Cellosolve.

ST photosensitive acrylic lithog plate; phenolic resin lithog plate; naphthoquinonediazidesulfonate phenolic resin lithog plate; chem resistant lithog plate; ink adhesion lithog plate

IT Phenolic resins, uses and miscellaneous
RL: USES (Uses)
(acrylic lithog. plates containing, with good chemical resistance and ink adhesion)

IT Chemically resistant materials
(acrylic lithog. plates, containing phenolic resins and phenolic resin naphthoquinonediazidesulfonates)

IT Lithographic plates
(photosensitive pos. acrylic polymers, containing phenolic resins and phenolic resin naphthoquinonediazidesulfonates, with good chemical resistance and ink adhesion)

IT 25085-50-1, p-tert-Butylphenol-formaldehyde copolymer 84135-66-0 103219-97-2 103735-35-9
RL: USES (Uses)
(acrylic lithog. plates containing, with good chemical resistance and ink adhesion)

IT 119553-98-9
RL: USES (Uses)
(lithog. plates, photosensitive, containing phenolic resins and phenolic resin naphthoquinonediazidesulfonates, with good chemical resistance and ink adhesion)

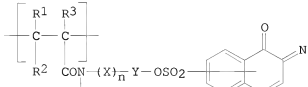
L12 ANSWER 45 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1989:125485 CAPLUS
DN 110:125485
OREF 110:20537a,20540a
ED Entered STN: 03 Apr 1989
TI Photosensitive composition with improved chemical resistance and ink acceptability
IN Yamamoto, Takeshi; Goto, Sei; Tomiyasu, Hiroshi; Kobayashi, Yoshiko
PA Konica Co., Japan; Mitsubishi Kasei Corp.
SO Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03C001-72
ICS C08L061-08
ICA C08F008-34; C08F020-54; C08L033-24; G03F007-08
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 63198046	A	19880816	JP 1987-31213	19870213
PRAI JP 1987-31213		19870213		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 63198046	ICM	G03C001-72
	ICS	C08L061-08
	ICA	C08F008-34; C08F020-54; C08L033-24; G03F007-08
	IPCI	G03C0001-72 [ICM,4]; C08L0061-08 [ICS,4]; C08L0061-00 [ICS,4,C*]; C08F0008-34 [ICA,4]; C08F0008-00 [ICA,4,C*]; C08F0020-54 [ICA,4]; C08F0020-00 [ICA,4,C*]; C08L0033-24 [ICA,4]; C08L0033-00 [ICA,4,C*]; G03F0007-08 [ICA,4]
	IPCR	G03C0001-72 [I,C*]; G03C0001-72 [I,A]; C08F0008-00 [I,C*]; C08F0008-34 [I,A]; C08F0020-00 [I,C*]; C08F0020-00 [I,A]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; C08L0061-00 [I,C*]; C08L0061-04 [I,A]; C08L0061-08 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]

GI



AB The title composition comprises: I [R1, R2 = H, halo, alkyl, aryl, carboxyl or

its salt; R3 = H, halo, alkyl, aryl; R4 = H, alkyl, aryl, aralkyl; X = divalent organic group; n = 0-5; Y = (substituted) divalent aromatic group]; and
a resin prepared by condensation of an aldehyde derivative with II [R5, R5 = H,
alkyl, halo; R7 = C≥2 alkyl or cycloalkyl] and/or its
o-naphthoquinonediazido sulfonic acid ester. This composition is useful for
pos.-working presensitized lithog. plates.
ST alkali sol resin photosensitive compn; novolak sensitizer
photosensitive compn lithog; presensitized lithog plate
photosensitive compn
IT Photoimaging compositions and processes
(containing sensitize and alkali-soluble resin for presensitized lithog.
plate)
IT Lithographic plates
(presensitized, pos.-working, photosensitize composition containing sensitizer and alkali-soluble resin for)
IT 57167-08-5DP, Poly(p-hydroxymethacrylanilide), reaction product with o-naphthoquinonediazido-5-sulfonyl chloride
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, in preparation of pos.-working lithog. photosensitive composition)
IT 3770-97-6DP, reaction product with poly(p-hydroxymethacrylanilide)
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, pos.-working lithog. photosensitive composition from)
IT 35464-74-5P, m-Cresol-p-cresol-formaldehyde-phenol copolymer 119553-98-9P
RL: PREP (Preparation)
(preparation of, as alkali-soluble resin)
IT 26678-93-3DP, Formaldehyde-p-tert-octylphenol copolymer, reaction product with o-naphthoquinonediazido-5-sulfonyl chloride
RL: PREP (Preparation)
(preparation of, as sensitizer)
IT 19243-95-9
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, poly(p-hydroxymethacylanilide) from)
IT 123-30-8, p-Hydroxy aniline 920-46-7, Methacrylic acid chloride
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, p-hydroxymethacrylanilide from)

L12 ANSWER 46 OF 46 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1976:600573 CAPLUS
DN 85:200573
OREF 85:31935a,31938a
ED Entered STN: 12 May 1984
TI Presensitized lithographic plates
IN Kawada, Hiroo; Yumiki, Keiichi; Seino, Minoru
PA Konishiroku Photo Industry Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese

10/593972 BY Primary Exr. Cynthia Hamilton

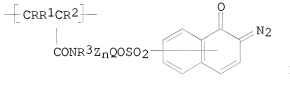
IC G03F007-08
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 51077405	A	19760705	JP 1975-2554	19741226
PRAI	JP 1975-2554	A	19741226		

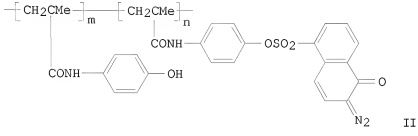
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 51077405	IC	G03F007-08
	IPCI	G03F0007-08; B41C0001-10

GI



I



II

AB Presensitized lithog. plates are obtained by depositing on a wet-honed Al plate a layer of a photosensitive composition containing a polymer having the structural unit I [R,R1 = H, alkyl, CO2H; R2 = H, halo, alkyl; R3 = H, alkyl, Ph, aralkyl; Z = a divalent organic moiety linking the N atom to the C atom of an aromatic ring; n = 0, 1; and Q = a phenylene group or naphthylene group]. Thus, an Al 1100 plate (0.24 mm) was degreased, rinsed, then placed on a rotary drum and rotated at 12 m/min. A mixture of an alumina polishing agent (250 mesh) 20 and water 80 parts (volume) was then sprayed on with a centrifugal sprayer. After rinsing, the spraying was continued with a 25:75 volume part mixture of H2O and alumina (2000 mesh). After rinsing, the back surface was sprayed with a 10:90 glass beads (100 mesh)-H2O mixture, rinsed and dried. The top surface was then coated with II[number average mol. weight = 32,000, m/n = 70/30] 10 g and Et cellulose 20 mg

dissolved in Me cellusolve 200 ml and dried. The plate was exposed for 1 min through a pos. original with a 3-kW Hg lamp then rubbed with a sponge after dipping in a 3% aqueous Na metasilicate solution for 1 min. A pos. relief image was obtained with good half-tone reproducibility. When used in an offset printing press, the plate showed good moisture retention, good printing characteristics, good chemical resistance, and excellent wear resistance.

ST acrylic photopolymer lithog plate; graining aluminum lithog plate

IT Acrylic polymers
RL: USES (Uses)
(photosensitive compns. containing, for lithog. plates)

IT Lithographic plates
(presensitized, photosensitive compns. containing acrylic photopolymers for)

IT Glass
RL: USES (Uses)
(spheres, aluminum lithographic plate graining by spraying with dispersions of)

IT 1344-28-1, uses and miscellaneous
RL: USES (Uses)
(aluminum lithographic plate graining by spraying with dispersions of)

IT 7429-90-5, uses and miscellaneous
RL: USES (Uses)
(lithographic plates supports from, graining of, by spraying with alumina dispersion)

IT 61163-35-7
RL: USES (Uses)
(photosensitive compns. containing, for lithographic plates)

=> d his

(FILE 'HOME' ENTERED AT 15:27:54 ON 09 SEP 2008)

FILE 'REGISTRY' ENTERED AT 15:28:04 ON 09 SEP 2008
L1 1742 S C9H9NO2
L2 1271 S C9H9NO2/MF
L3 4 S L2 AND ACRYLAMIDE

FILE 'REGISTRY' ENTERED AT 15:34:11 ON 09 SEP 2008
L4 1 S 53854-70-9/RN
SET NOTICE 1 DISPLAY
SET NOTICE LOGIN DISPLAY
L5 1 S 194091-51-5
L6 0 S 194091-51-5/CRN
L7 1 S 34443-04-4
L8 53 S 34443-04-4/CRN
L9 1 S 53854-70-9
L10 15 S 53854-70-9/CRN

FILE 'CAPLUS' ENTERED AT 15:37:04 ON 09 SEP 2008
L11 67 S L8 OR L10
L12 46 S L11 AND PHOTO?

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=> log y
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
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FULL ESTIMATED COST                                   153.50     190.06

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                      ENTRY    SESSION
CA SUBSCRIBER PRICE                                   -36.80     -36.80

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PASSWORD:
TERMINAL (ENTER 1, 2, 3, OR ?):2


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 NEWS  1          Web Page for STN Seminar Schedule - N. America
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 NEWS  3  APR 15  WPIDS, WPINDEX, and WPIX enhanced with new
                  predefined hit display formats
 NEWS  4  APR 28  EMBASE Controlled Term thesaurus enhanced
 NEWS  5  APR 28  IMSRESEARCH reloaded with enhancements
 NEWS  6  MAY 30  INPAFAMDB now available on STN for patent family
                  searching
 NEWS  7  MAY 30  DGENE, PCTGEN, and USGENE enhanced with new homology
                  sequence search option
 NEWS  8  JUN 06  EPFULL enhanced with 260,000 English abstracts
 NEWS  9  JUN 06  KOREAPAT updated with 41,000 documents
 NEWS 10  JUN 13  USPATFULL and USPAT2 updated with 11-character
                  patent numbers for U.S. applications
 NEWS 11  JUN 19  CAS REGISTRY includes selected substances from
                  web-based collections
 NEWS 12  JUN 25  CA/CAplus and USPAT databases updated with IPC
                  reclassification data
 NEWS 13  JUN 30  AEROSPACE enhanced with more than 1 million U.S.
                  patent records
 NEWS 14  JUN 30  EMBASE, EMBAL, and LEMBASE updated with additional
                  options to display authors and affiliated
                  organizations
 NEWS 15  JUN 30  STN on the Web enhanced with new STN AnaVist
                  Assistant and BLAST plug-in
 NEWS 16  JUN 30  STN AnaVist enhanced with database content from EPFULL
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 NEWS 17  JUL 28  CA/CAplus patent coverage enhanced
 NEWS 18  JUL 28  EPFULL enhanced with additional legal status
                  information from the epoline Register
 NEWS 19  JUL 28  IFICDB, IFIPAT, and IFIUDB reloaded with enhancements
 NEWS 20  JUL 28  STN Viewer performance improved
 NEWS 21  AUG 01  INPADOCDB and INPAFAMDB coverage enhanced
 NEWS 22  AUG 13  CA/CAplus enhanced with printed Chemical Abstracts
                  page images from 1967-1998
 NEWS 23  AUG 15  CAOLD to be discontinued on December 31, 2008
 NEWS 24  AUG 15  CAplus currency for Korean patents enhanced
 NEWS 25  AUG 25  CA/CAplus, CASREACT, and IFI and USPAT databases
                  enhanced for more flexible patent number searching
 NEWS 26  AUG 27  CAS definition of basic patents expanded to ensure
                  comprehensive access to substance and sequence
                  information

 NEWS EXPRESS JUNE 27 08 CURRENT WINDOWS VERSION IS V8.3,
              AND CURRENT DISCOVER FILE IS DATED 23 JUNE 2008.

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FILE 'HOME' ENTERED AT 17:01:43 ON 09 SEP 2008

=> FILE REG
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                       ENTRY    SESSION
FULL ESTIMATED COST                                     0.21       0.21

FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
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STRUCTURE FILE UPDATES:    8 SEP 2008  HIGHEST RN 1047724-15-1
DICTIONARY FILE UPDATES:   8 SEP 2008  HIGHEST RN 1047724-15-1

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TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.
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REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

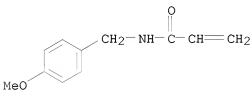
http://www.cas.org/support/stngen/stndoc/properties.html

=> S C11H13NO2/MF
L1 4064 C11H13NO2/MF

=> S L1 AND ACRYLAMIDE
18439 ACRYLAMIDE
L2 5 L1 AND ACRYLAMIDE

=> D 1-5

L2 ANSWER 1 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 70875-53-5 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(4-methoxyphenyl)methyl]- (CA INDEX NAME)
OTHER NAMES:
CN N-(4-Methoxybenzyl)acrylamide
MF C11 H13 N O2
LC STN Files: BEILSTEIN*, CA, CAPLUS, CASREACT, TOXCENTER, USPATFULL
(*File contains numerically searchable property data)

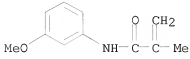


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

7 REFERENCES IN FILE CA (1907 TO DATE)
7 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L2 ANSWER 2 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 15271-60-0 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(3-methoxyphenyl)-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN m-Methacrylanisidide (6CI, 8CI)
OTHER NAMES:
CN N-(m-Methoxyphenyl)methacrylamide
MF C11 H13 N O2
CI COM

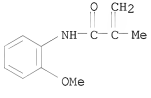
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, TOXCENTER
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

11 REFERENCES IN FILE CA (1907 TO DATE)
11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
4 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L2 ANSWER 3 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13910-91-3 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(2-methoxyphenyl)-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN o-Methacrylanisidide (6CI, 8CI)
OTHER NAMES:
CN N-(o-Methoxyphenyl)methacrylamide
MF C11 H13 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

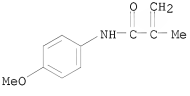
11 REFERENCES IN FILE CA (1907 TO DATE)
11 REFERENCES IN FILE CAPLUS (1907 TO DATE)
4 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

L2 ANSWER 4 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13890-05-6 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(phenylmethoxy)methyl]- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-[(benzyloxy)methyl]- (8CI)
MF C11 H13 N O2
CI COM
LC STN Files: CA, CAPLUS, USPATOLD

PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L2 ANSWER 5 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 7274-71-7 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-(4-methoxyphenyl)-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN p-Methacrylanisidide (6CI, 7CI, 8CI)
OTHER NAMES:
CN 4-Methoxyphenylmethacrylamide
CN N-(4-Methoxyphenyl)-2-methyl-2-propenamide
CN N-(p-Methoxyphenyl)methacrylamide
MF C11 H13 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS, CHEMINFORMRX, USPATFULL
(*File contains numerically searchable property data)



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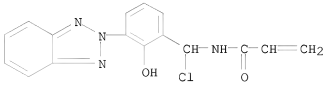
28 REFERENCES IN FILE CAPLUS (1907 TO DATE)
6 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> S hydroxybenzylacrylamide
L3 0 HYDROXYBENZYLACRYLAMIDE

=> S hydroxybenzyl and acrylamide
5831 HYDROXYBENZYL
18439 ACRYLAMIDE
L4 26 HYDROXYBENZYL AND ACRYLAMIDE

=> d 26

L4 ANSWER 26 OF 26 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13394-52-0 REGISTRY
ED Entered STN: 16 Nov 1984
CN Acrylamide, N-[3-(2H-benzotriazol-2-yl)-α-chloro-2-hydroxybenzyl]- (8CI) (CA INDEX NAME)
MF C16 H13 Cl N4 O2

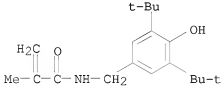


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

=> s l4 not chloro
6444251 CHLORO
L5 24 L4 NOT CHLORO

=> d 24

L5 ANSWER 24 OF 24 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13560-54-8 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[[3,5-bis(1,1-dimethylethyl)-4-hydroxyphenyl]methyl]-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-di-tert-butyl-4-hydroxybenzyl)-2-methyl- (7CI, 8CI)
MF C19 H29 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, CHEMCATS, IFICDB, IFIPAT, IFIUDB, USPATOLD
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

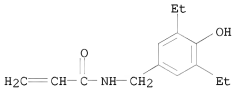
4 REFERENCES IN FILE CA (1907 TO DATE)

4 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> s l5 not tert
135326 TERT
L6 15 L5 NOT TERT

=> d 15

L6 ANSWER 15 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13560-55-9 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(3,5-diethyl-4-hydroxyphenyl)methyl]- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-diethyl-4-hydroxybenzyl)- (7CI, 8CI)
OTHER NAMES:
CN 4-Acryloylaminomethyl-2,6-diethylphenol
MF C14 H19 N O2
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, IFICDB, IFIPAT, IFIUDB, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> s 13560-55-9/crn
L7 0 13560-55-9/CRN

=> file caplus; s l6

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	54.35	54.56

FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
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FILE COVERS 1907 - 9 Sep 2008 VOL 149 ISS 11
FILE LAST UPDATED: 8 Sep 2008 (20080908/ED)

Caplus now includes complete International Patent Classification (IPC) reclassification data for the second quarter of 2008.

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L8 13 L6

=> s l8 and photo?
1604210 PHOTO?
L9 4 L8 AND PHOTO?

=> d all 1-4

L9 ANSWER 1 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2007:356592 CAPLUS
DN 146:368744
ED Entered STN: 30 Mar 2007
TI Negative-working photosensitive resin composition for forming two layer-structure film for forming bump contacts
IN Yokoyama, Kenichi; Sakai, Yoko; Hasegawa, Satomi; Ota, Suguru; Iwanaga, Shinichiro
PA JSR Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 36pp.
CODEN: JKXXAF
DT Patent
LA Japanese
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 76
FAN.CNT 1

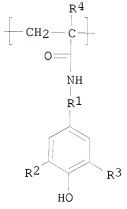
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2007079550	A	20070329	JP 2006-182282	20060630
PRAI JP 2005-238795	A	20050819		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2007079550	IPCI	G03F0007-11 [I,A]; G03F0007-004 [I,A]; G03F0007-40 [I,A]; H01L0021-027 [I,A]; H05K0003-34 [I,A];

H01L0021-60 [I,A]; H01L0021-02 [I,C*]
IPCR G03F0007-11 [I,C]; G03F0007-11 [I,A]; G03F0007-004 [I,C]; G03F0007-004 [I,A]; G03F0007-40 [I,C]; G03F0007-40 [I,A]; H01L0021-02 [I,C]; H01L0021-027 [I,A]; H01L0021-60 [I,A]; H05K0003-34 [I,C]; H05K0003-34 [I,A]
FTERM 2H025/AA03; 2H025/AA04; 2H025/AA16; 2H025/AB11; 2H025/AB15; 2H025/AB17; 2H025/AC01; 2H025/AD01; 2H025/BC13; 2H025/BC42; 2H025/CA00; 2H025/CB43; 2H025/CB45; 2H025/CB60; 2H025/CC03; 2H025/CC05; 2H025/DA35; 2H025/DA40; 2H025/FA17; 2H025/FA43; 2H096/AA26; 2H096/AA27; 2H096/BA05; 2H096/CA05; 2H096/EA02; 2H096/GA08; 2H096/HA27; 5E319/AA03; 5E319/AB05; 5E319/BB05; 5E319/CC33; 5E319/CD04; 5E319/CD26; 5E319/GG15

GI



I

AB Title composition contains a polymer having repeating unit I(R1 = -(CH2)n-; n = integer 1-3; R2-4 = H, C1-4 alkyl), an organic solvent, and compound R1O-[-(CH2)p-O-]m-[-(CH2)q-O-]n-R2(p, q = 2,3; m, n = integer ≥0 with 3<m=n≤12; R1-2 = H, organic group). The composition provides good characteristics such as good solder pattern formation and easy removal from a substrate.

ST neg photosensitive resin compn bump contact solder

IT Alcohols, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(C12-14-secondary, ethoxylated; neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

IT Bump contacts
(neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

IT Photoimaging materials

(photopolymerizable; neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

IT 863455-99-6P, N-(4-Hydroxy-3,5-dimethylbenzyl)acrylamide-styrene-2-hydroxyethyl acrylate copolymer 926636-49-9P, N-(4-Hydroxy-3,5-dimethylbenzyl)acrylamide-styrene-2-hydroxyethyl acrylate-butyl acrylate copolymer
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

IT 24991-55-7, Uniox MM 500 865783-27-3, p-Isopropenylphenol-N-(p-Hydroxyphenyl)methacrylamide-methacrylic acid-butyl methacrylate-Tricyclo[5.2.1.02,6]decanyl-8-ol methacrylate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

IT 97-64-3, Ethyl 2-hydroxypropionate 1320-67-8, Propylene glycol monomethyl ether
RL: NUU (Other use, unclassified); USES (Uses)
(organic solvent; neg.-working photosensitive resin composition for forming two layer-structure film for forming bump contacts)

L9 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2005:962527 CAPLUS
DN 143:258087
ED Entered STN: 02 Sep 2005
TI Bilayer laminated film for bump formation and method of bump formation
IN Nishimura, Hiroko; Ohta, Masaru; Inomata, Katsumi; Iwanaga, Shin-Ichiro
PA JSR Corporation, Japan
SO PCT Int. Appl., 56 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
IC ICM G03F007-11
ICS H05K003-34
CC 76-2 (Electric Phenomena)
Section cross-reference(s): 74
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 2005081064	A1	20050901	WO 2005-JP2575	20050218
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
JP 2005266795	A	20050929	JP 2005-40827	20050217

EP 1739487	A1	20070103	EP 2005-710408	20050218	
R: DE, FR, IT					
CN 1922546	A	20070228	CN 2005-80005594	20050218	
US 20070237890	A1	20071011	US 2006-587897	20060728	
PRAI JP 2004-44929	A	20040220			
WO 2005-JP2575	W	20050218			

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 2005081064	ICM	G03F007-11
	ICS	H05K003-34
	IPCI	G03F0007-11 [ICM,7]; H05K0003-34 [ICS,7]
	IPCR	G03F0007-033 [I,C*]; G03F0007-033 [I,A]; G03F0007-11 [I,C*]; G03F0007-11 [I,A]; H01L0021-02 [I,C*]; H01L0021-48 [I,A]; H01L0021-60 [I,A]; H05K0003-34 [I,C*]; H05K0003-34 [I,A]
	ECLA	H01L021/60B2; G03F007/033; G03F007/11; H01L021/48C4C; H05K003/34F6B
JP 2005266795 G03F0007-033	IPCI	G03F0007-11 [ICM,7]; G03F0007-004 [ICS,7]; [ICS,7]; G03F0007-40 [ICS,7]; H01L0021-60 [ICS,7]; H01L0021-02 [ICS,7,C*]
	IPCR	G03F0007-004 [I,A]; G03F0007-004 [I,C*]; G03F0007-033 [I,A]; G03F0007-033 [I,C*]; G03F0007-11 [I,A]; G03F0007-11 [I,C*]; G03F0007-40 [I,A]; G03F0007-40 [I,C*]; H01L0021-02 [I,C*]; H01L0021-60 [I,A]
	FTERM	2H025/AA03; 2H025/AA10; 2H025/AA16; 2H025/AB11; 2H025/AB15; 2H025/AB17; 2H025/AC01; 2H025/AD01; 2H025/BC13; 2H025/BC42; 2H025/CA00; 2H025/CB13; 2H025/CB17; 2H025/CB43; 2H025/CB45; 2H025/CC03; 2H025/DA36; 2H025/DA40; 2H025/FA39; 2H096/AA26; 2H096/AA27; 2H096/BA01; 2H096/CA05; 2H096/GA08
EP 1739487	IPCI	G03F0007-11 [I,A]; H05K0003-34 [I,A]
	IPCR	G03F0007-11 [I,C]; G03F0007-11 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; H01L0021-02 [I,C*]; H01L0021-48 [I,A]; H01L0021-60 [I,A]; H05K0003-34 [I,C]; H05K0003-34 [I,A]
	ECLA	H01L021/60B2; G03F007/033; G03F007/11; H01L021/48C4C; H05K003/34F6B
CN 1922546	IPCI	G03F0007-11 [I,A]; H05K0003-34 [I,A]
	IPCR	G03F0007-11 [I,C]; G03F0007-11 [I,A]; G03F0007-033 [I,C*]; G03F0007-033 [I,A]; H01L0021-02 [I,C*]; H01L0021-48 [I,A]; H01L0021-60 [I,A]; H05K0003-34 [I,C*]; H05K0003-34 [I,A]
	ECLA	H01L021/60B2; G03F007/033; G03F007/11; H01L021/48C4C; H05K003/34F6B
US 20070237890	IPCI	B05D0005-12 [I,A]; B32B0027-00 [I,A]; C08J0003-28 [I,A]; C08L0061-00 [I,A]
	NCL	427/098.400; 257/E21.508; 428/500.000; 522/109.000; 525/471.000

AB A neg. radiation-sensitive bilayer laminated film for bump formation is described, characterized in that a composition comprising a polymer with specified structural unit and organic solvent is used as an underlayer of the bilayer laminated film for bump formation. A method of bump formation

using the laminated film is also described. Thus, there is provided a neg. radiation-sensitive bilayer laminated film for bump formation that excels in solder paste printability and pattern configuration and that can be easily detached from substrates, and further provided a method of bump production therewith.
ST bilayer polymer photoresist film bump solder paste
IT Bump contacts
Multilayers
Negative photoresists
(bilayer photoresist laminated film for bump formation using solder paste)
IT Soldering
(paste; bilayer photoresist laminated film for bump formation using solder paste)
IT 3524-68-3, Aronix M-305 62886-89-9, Aronix M 8060 863455-98-5 863455-99-6, 2-Hydroxyethyl acrylate-N-(3,5-dimethyl-4-hydroxybenzyl)acrylamide-styrene copolymer 863456-00-2, N-(P-Hydroxyphenol)methacrylamide-iso-propenylphenol-methacrylic acid-8-tricyclo[5.2.1.02.6]decanyl methacrylate copolymer 863456-01-3, Butyl acrylate-isopropenylphenol-methacrylic acid-isobornyl acrylate-8-tricyclo[5.2.1.02.6]decanyl methacrylate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(bilayer photoresist laminated film for bump formation using solder paste)
RE.CNT 17 THERE ARE 17 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Arch Specialty Chemicals Inc; WO 200053645 A1 2002
(2) Arch Specialty Chemicals Inc; JP 2002539282 A 2002
(3) Arch Specialty Chemicals Inc; US 6492092 B1 2002 CAPLUS
(4) Casio Computer Co Ltd; JP 10-107037 A 1998
(5) Fuji Photo Film Co Ltd; JP 07-333836 A 1995 CAPLUS
(6) Fuji Photo Film Co Ltd; JP 200420643 A 2004
(7) Japan Synthetic Rubber Co Ltd; JP 08-31733 A 1996 CAPLUS
(8) Jsr Corp; JP 200039709 A 2000
(9) Jsr Corp; JP 2004140313 A 2004 CAPLUS
(10) Jsr Corp; WO 200419667 A1 2004
(11) Matsushita Electric Industrial Co Ltd; JP 200156570 A 2001
(12) Sony Corp; JP 07-74251 A 1995
(13) Tokyo Ohka Kogyo Co Ltd; JP 2003140347 A 2003 CAPLUS
(14) Tokyo Ohka Kogyo Co Ltd; US 200387187 A1 2003
(15) Toshiba Corp; JP 09-321049 A 1997 CAPLUS
(16) Toyama Nihon Denki Kabushiki Kaisha; JP 2000208911 A 2000 CAPLUS
(17) Toyama Nihon Denki Kabushiki Kaisha; US 6420255 B1 2000 CAPLUS

L9 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:549504 CAPLUS
DN 119:149504
OREF 119:26551a,26554a
ED Entered STN: 02 Oct 1993
TI Photosensitive composition with polymeric binder comprising alpha-beta unsaturated carboxylic acid residue
IN Roeschert, Horst; Pawlowski, Georg; Przybilla, Klaus Juergen
PA Hoechst A.-G., Germany
SO Ger. Offen., 10 pp.

CODEN: GWXXBX
DT Patent
LA German
IC ICM C07C233-20
ICS C08F020-58; C07F007-18; C07D307-20; C07D309-10; G03F007-004; H01L021-312
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

FAN.CNT 1

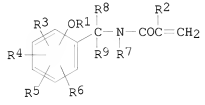
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI DE 4126409	A1	19930211	DE 1991-4126409	19910809
EP 528203	A1	19930224	EP 1992-112588	19920723
EP 528203	B1	19951011		
R: BE, CH, DE, FR, GB, IT, LI				
US 5328973	A	19940712	US 1992-922507	19920731
JP 05255216	A	19931005	JP 1992-234193	19920810
PRAI DE 1991-4126409	A	19910809		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 4126409	ICM	C07C233-20
	ICS	C08F020-58; C07F007-18; C07D307-20; C07D309-10; G03F007-004; H01L021-312
	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]; C08F0020-58 [ICS,5]; C08F0020-00 [ICS,5,C*]; C07F0007-18 [ICS,5]; C07F0007-00 [ICS,5,C*]; C07D0307-20 [ICS,5]; C07D0307-00 [ICS,5,C*]; C07D0309-10 [ICS,5]; C07D0309-00 [ICS,5,C*]; G03F0007-004 [ICS,5]; H01L0021-312 [ICS,5]; H01L0021-02 [ICS,5,C*]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
EP 528203	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]; C08F0020-58 [ICS,5]; C08F0020-00 [ICS,5,C*]; G03F0007-039 [ICS,5]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	ECLA	C07C233/20; C08F020/58; G03F007/039
US 5328973	IPCI	C08F0020-60 [ICM,5]; C08F0020-00 [ICM,5,C*]; C08F0024-00 [ICS,5]; C08F0030-08 [ICS,5]; C08F0030-00 [ICS,5,C*]
	NCL	526/262.000; 430/270.100; 430/906.000; 430/910.000; 526/266.000; 526/270.000; 526/279.000; 526/292.500; 526/292.900; 526/298.000; 526/304.000
	ECLA	C07C233/20; C08F020/58; G03F007/039
JP 05255216	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]

OS MARPAT 119:149504

GI



I

AB The compds. I [R1 = acid-splittable group; R2 = alkyl, H, halogen, CN; R3-R6 = aliphatic, aromatic, araliph., halogen, OH, H; R7 = H, alkyl; R8, R9 = H, alkyl, aryl], the polymers containing ≥10 mol% of I, and photosensitive compns. containing the polymer are claimed. The composition is useful for resist material for deep-UV lithog.

ST acrylamide polymer photosensitive compn photoresist; lithog deep UV resist acrylamide

IT Resists
(photo-, deep-UV, acrylamide polymers for)

IT Lithography
(photo-, UV, light-sensitive compns. containing acrylamide polymers for)

IT 13560-56-0P 13579-40-3P 104835-82-7P 149450-93-1P 149450-94-2P 149450-95-3P 149450-96-4P 149450-97-5P 149450-98-6P 149450-99-7P 149451-00-3P 149451-01-4P 149451-02-5P 149451-03-6P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation and reaction of, polymer binder for photosensitive composition from)

IT 149787-50-8P 149787-51-9P 149787-52-0P 149787-53-1P 149787-54-2P 149787-55-3P 149787-56-4P 149787-57-5P 149787-60-0P 149787-61-1P 149826-03-9P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, in photosensitive composition)

L9 ANSWER 4 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1990:468392 CAPLUS
DN 113:68392
OREF 113:11389a,11392a
ED Entered STN: 17 Aug 1990
TI Positive-working radiation-sensitive mixture and recording materials therefrom
IN Elsaesser, Andreas; Frass, Hans Werner; Mohr, Dieter
PA Hoechst A.-G., Fed. Rep. Ger.
SO Ger. Offen., 15 pp.
CODEN: GWXXBX
DT Patent
LA German

IC G03F007-08; G03F007-10; C09D003-80; C09D007-12; G03F007-16
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3820699	A1	19891221	DE 1988-3820699	19880618
	US 5068163	A	19911126	US 1989-362688	19890607
	EP 347660	A2	19891227	EP 1989-110425	19890609
	EP 347660	A3	19910605		
	EP 347660	B1	19950322		
	R: CH, DE, FR, GB, IT, LI, NL				
	BR 8902919	A	19900206	BR 1989-2919	19890616
	KR 161965	B1	19990115	KR 1989-8362	19890617
	JP 02052349	A	19900221	JP 1989-154797	19890619
	JP 2559852	B2	19961204		

PRAI DE 1988-3820699 A 19880618
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 3820699	IC	G03F007-08; G03F007-10; C09D003-80; C09D007-12; G03F007-16
	IPCI	G03F0007-08 [ICM]; G03F0007-10 [ICS]; C09D0003-80 [ICS]; C09D0007-12 [ICS]; G03F0007-16 [ICS]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]
US 5068163	IPCI	G03C0001-52 [ICM,5]; G03C0001-492 [ICS,5]; G03C0001-005 [ICS,5,C*]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]
	NCL	430/192.000; 430/165.000; 430/270.100; 430/326.000
	ECLA	G03F007/004D; G03F007/023P
EP 347660	IPCI	G03F0007-02 [ICM,4]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]
	ECLA	G03F007/004D; G03F007/023P
BR 8902919	IPCI	G03F0007-10 [ICM,4]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30

		[I,A]
KR 161965	IPCI	G03F0007-023 [ICM,7]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]
JP 02052349	IPCI	G03F0007-022 [ICM,6]; G03F0007-032 [ICS,6]; G03F0007-039 [ICS,6]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-032 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]; H01L0021-30 [I,A]

OS CASREACT 113:68392

GI For diagram(s), see printed CA Issue.

AB Pos.-working radiation-sensitive mixts., which are capable of producing photoresists of high heat resistance and lithog. plates with a high printing durability, are composed of essentially a 1,2-quinone diazide or a combination of a compound that forms a strong acid under the effects of actinic radiation and a compound with ≥1 cleavable C-O-C bond, and a binder with repeating units of the structure I (R1 = , halogen, CN, or alkyl; R2, R3, R4 = H, alkyl, or aryl; R5, R6, R7 = H, halogen, alkyl, aryl, or alkoxy; X = the atoms to complete a carbocyclic aromatic ring system; n = 1, 2, or 3). Thus, a typical mixture consisted of N-(2-hydroxy-1-naphthylmethyl)methacrylamide, 2,3,4-trihydroxybenzophenone 1,2-naphthoquinone-2-diazide-4-sulfonate, and propylene glycol Me either acetate.

ST pos photosensitive compn binder; photoresist pos binder; lithog plate pos photosensitive compn

IT Lithographic plates
(pos.-working photosensitive compns. containing acrylamide derivs. polymer binders for fabrication of, with improved printing durability)

IT Resists
(photo-, pos.-working, containing acrylamide derivative polymer binders, for high-heat resistance)

IT 36451-09-9 84522-08-7
RL: USES (Uses)
(pos.-working photosensitive compns. containing, for lithog. plates)

IT 69432-41-3 69666-56-4 97746-56-0 97802-84-1
RL: USES (Uses)
(pos.-working photosensitive compns. containing, for photoresists)

IT 13560-56-0P 13579-23-2P 109687-01-6P 128067-81-2P
RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(preparation and polymerization of)

IT 128067-80-1P 128067-82-3P 128067-83-4P
RL: PREP (Preparation)
(preparation and pos.-working photosensitive compns. containing, for

lithog. plate fabrication)
IT 128093-71-0P 128093-76-5P 128093-77-6P 128093-78-7P
RL: PREP (Preparation)
(preparation and pos.-working photosensitive compns. containing, for lithog. plates)
IT 128067-84-5P 128088-12-0P 128093-70-9P 128093-71-0P 128093-72-1P
128093-73-2P 128093-74-3P 128093-75-4P
RL: PREP (Preparation)
(preparation and pos.-working photosensitive compns. containing, for lithog. plates and photoresists)
IT 3644-12-0
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with dimethylphenyl)
IT 576-26-1
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with N-methoxymethylmethacrylamide)

=> file reg

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	16.16	70.72
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	-3.20	-3.20

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http://www.cas.org/support/stngen/stndoc/properties.html

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     FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1          4064 S C11H13NO2/MF
L2             5 S L1 AND ACRYLAMIDE
L3             0 S HYDROXYBENZYLACRYLAMIDE
L4            26 S HYDROXYBENZYL AND ACRYLAMIDE
L5            24 S L4 NOT CHLORO
L6            15 S L5 NOT TERT
L7             0 S 13560-55-9/CRN

     FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8            13 S L6
L9             4 S L8 AND PHOTO?

     FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008

=> d l6 1-14

L6   ANSWER 1 OF 15  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   937821-21-1  REGISTRY
ED   Entered STN:  19 Jun 2007
CN   2-Propenamide, N-(1-methylethyl)-, polymer with 5-(hydroxymethyl)-1,3-
     benzenediol, diblock  (CA INDEX NAME)
OTHER NAMES:
CN   3,5-Dihydroxybenzyl alcohol-N-isopropylacrylamide diblock
     copolymer
MF   (C7 H8 O3 . C6 H11 N O)x
CI   PMS
PCT  Polyacrylic, Polyether
SR   CA
LC   STN Files:   CA, CAPLUS

     CM   1

     CRN  29654-55-5
     CMF  C7 H8 O3
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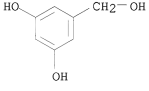


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     CM   2

     CRN  2210-25-5
     CMF  C6 H11 N O
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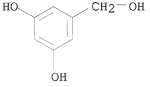
1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 2 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 937738-29-9 REGISTRY
ED Entered STN: 18 Jun 2007
CN 2-Propenamide, N-(1-methylethyl)-, polymer with 5-(hydroxymethyl)-1,3-benzenediol, triblock (CA INDEX NAME)
OTHER NAMES:
CN 3,5-Dihydroxybenzyl alcohol-N-isopropylacrylamide triblock copolymer
MF (C7 H8 O3 . C6 H11 N O)x
CI PMS
PCT Polyacrylic, Polyether
SR CA
LC STN Files: CA, CAPLUS

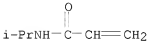
CM 1

CRN 29654-55-5
CMF C7 H8 O3



CM 2

CRN 2210-25-5
CMF C6 H11 N O



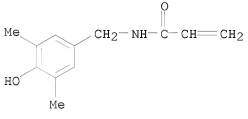
1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 3 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 863455-99-6 REGISTRY
ED Entered STN: 19 Sep 2005

CN 2-Propenoic acid, 2-hydroxyethyl ester, polymer with ethenylbenzene and N-[(4-hydroxy-3,5-dimethylphenyl)methyl]-2-propenamide (9CI) (CA INDEX NAME)
OTHER NAMES:
CN 2-Hydroxyethyl acrylate-N-(3,5-dimethyl-4-hydroxybenzyl)acrylamide-styrene copolymer
CN N-(4-Hydroxy-3,5-dimethylbenzyl)acrylamide-styrene-2-hydroxyethyl acrylate copolymer
DR 930283-80-0
MF (C12 H15 N O2 . C8 H8 . C5 H8 O3)x
CI PMS
PCT Polyacrylic, Polystyrene
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

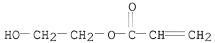
CM 1

CRN 13579-23-2
CMF C12 H15 N O2



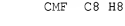
CM 2

CRN 818-61-1
CMF C5 H8 O3



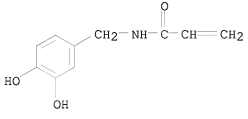
CM 3

CRN 100-42-5
CMF C8 H8



2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 4 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 852923-27-4 REGISTRY
ED Entered STN: 24 Jun 2005
CN 2-Propenamide, N-[(3,4-dihydroxyphenyl)methyl]- (CA INDEX NAME)
OTHER NAMES:
CN N-(3,4-Dihydroxybenzyl)acrylamide
MF C10 H11 N O3
SR CA
LC STN Files: CA, CAPLUS, CASREACT



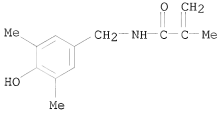
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 5 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 849686-90-4 REGISTRY
ED Entered STN: 03 May 2005
CN 2-Propenamide, N,N-dimethyl-, polymer with N-[(4-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-2-propenamide (9CI) (CA INDEX NAME)
OTHER NAMES:
CN N,N-Dimethylacrylamide-N-(3,5-dimethyl-4-hydroxybenzyl)methacrylamide copolymer
MF (C13 H17 N O2 . C5 H9 N O)x
CI PMS
PCT Polyacrylic
SR CA
LC STN Files: CA, CAPLUS

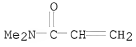
CM 1

CRN 104835-82-7
CMF C13 H17 N O2



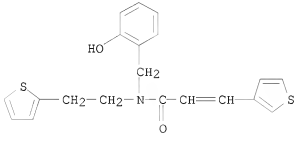
CM 2

CRN 2680-03-7
CMF C5 H9 N O



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

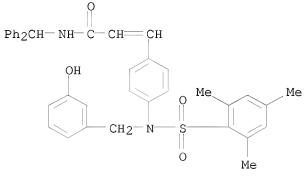
L6 ANSWER 6 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 780768-62-9 REGISTRY
ED Entered STN: 15 Nov 2004
CN 2-Propenamide, N-[(2-hydroxyphenyl)methyl]-3-(3-thienyl)-N-[2-(2-thienyl)ethyl]- (CA INDEX NAME)
OTHER NAMES:
CN N-(2-Hydroxybenzyl)-3-(thiophen-3-yl)-N-[2-(thiophen-2-yl)ethyl]acrylamide
MF C20 H19 N O2 S2
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 7 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-42-5 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, N-(diphenylmethyl)-3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]- (CA INDEX NAME)
OTHER NAMES:
CN N-Benzhydryl-3-[4-[(3-hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]acrylamide
MF C38 H36 N2 O4 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL

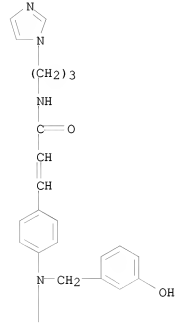


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

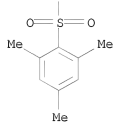
1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 8 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-41-4 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, 3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]-N-[3-(1H-imidazol-1-yl)propyl]- (CA INDEX NAME)
OTHER NAMES:
CN 3-[4-[(3-Hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]-N-[3-(imidazol-1-yl)propyl]acrylamide
MF C31 H34 N4 O4 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL

PAGE 1-A



PAGE 2-A

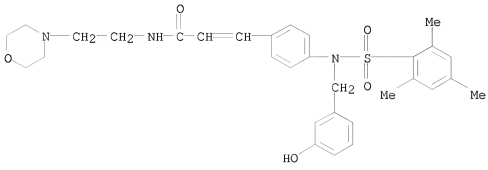


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 9 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-40-3 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, 3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]-N-[2-(4-morpholinyl)ethyl]- (CA INDEX NAME)
OTHER NAMES:

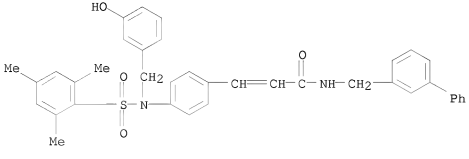
CN 3-[4-[(3-Hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]-N-[2-(morpholin-4-yl)ethyl]acrylamide
MF C31 H37 N3 O5 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

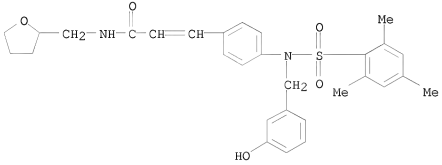
L6 ANSWER 10 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-39-0 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, N-([1,1'-biphenyl]-3-ylmethyl)-3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]- (CA INDEX NAME)
OTHER NAMES:
CN N-[(Biphenyl-3-yl)methyl]-3-[4-[(3-hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]acrylamide
MF C38 H36 N2 O4 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

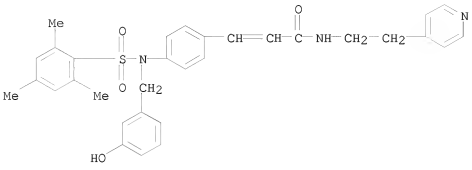
L6 ANSWER 11 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-37-8 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, 3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]-N-[(tetrahydro-2-furanyl)methyl]- (CA INDEX NAME)
OTHER NAMES:
CN 3-[4-[(3-Hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]-N-[(tetrahydrofuran-2-yl)methyl]acrylamide
MF C30 H34 N2 O5 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

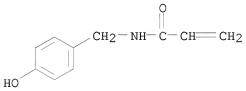
L6 ANSWER 12 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 675868-28-7 REGISTRY
ED Entered STN: 16 Apr 2004
CN 2-Propenamide, 3-[4-[[(3-hydroxyphenyl)methyl][(2,4,6-trimethylphenyl)sulfonyl]amino]phenyl]-N-[2-(4-pyridinyl)ethyl]- (CA INDEX NAME)
OTHER NAMES:
CN 3-[4-[(3-Hydroxybenzyl)(2,4,6-trimethylbenzenesulfonyl)amino]phenyl]-N-[2-(pyridin-4-yl)ethyl]acrylamide
MF C32 H33 N3 O4 S
SR CA
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 13 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 23281-77-8 REGISTRY
ED Entered STN: 16 Nov 1984
CN Acrylamide, N-(p-hydroxybenzyl)- (8CI) (CA INDEX NAME)
MF C10 H11 N O2
CI COM
LC STN Files: CA, CAPLUS

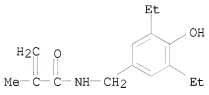


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L6 ANSWER 14 OF 15 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13560-56-0 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(3,5-diethyl-4-hydroxyphenyl)methyl]-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-diethyl-4-hydroxybenzyl)-2-methyl- (8CI)
OTHER NAMES:
CN 2,6-Diethyl-4-methacryloylaminomethylphenol
MF C15 H21 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, IFICDB, IFIPAT, IFIUDB,

USPATFULL
(*File contains numerically searchable property data)



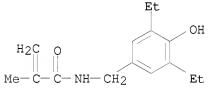
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

4 REFERENCES IN FILE CA (1907 TO DATE)
4 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> s 13560-56-0
L10 1 13560-56-0
(13560-56-0/RN)

=> d

L10 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13560-56-0 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(3,5-diethyl-4-hydroxyphenyl)methyl]-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-diethyl-4-hydroxybenzyl)-2-methyl- (8CI)
OTHER NAMES:
CN 2,6-Diethyl-4-methacryloylaminomethylphenol
MF C15 H21 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS, IFICDB, IFIPAT, IFIUDB, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

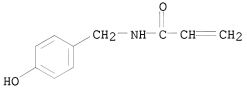
4 REFERENCES IN FILE CA (1907 TO DATE)
4 REFERENCES IN FILE CAPLUS (1907 TO DATE)

1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> s 23281-77-8
L11 1 23281-77-8
(23281-77-8/RN)

=> d

L11 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 23281-77-8 REGISTRY
ED Entered STN: 16 Nov 1984
CN Acrylamide, N-(p-hydroxybenzyl)- (8CI) (CA INDEX NAME)
MF C10 H11 N O2
CI COM
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

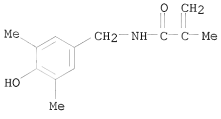
=> s 849686-90-4
L12 1 849686-90-4
(849686-90-4/RN)

=> d

L12 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 849686-90-4 REGISTRY
ED Entered STN: 03 May 2005
CN 2-Propenamide, N,N-dimethyl-, polymer with N-[(4-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-2-propenamide (9CI) (CA INDEX NAME)
OTHER NAMES:
CN N,N-Dimethylacrylamide-N-(3,5-dimethyl-4-hydroxybenzyl)methacrylamide copolymer
MF (C13 H17 N O2 . C5 H9 N O)x
CI PMS
PCT Polyacrylic
SR CA
LC STN Files: CA, CAPLUS

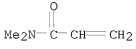
CM 1

CRN 104835-82-7
CMF C13 H17 N O2



CM 2

CRN 2680-03-7
CMF C5 H9 N O

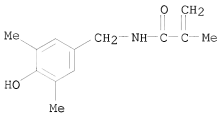


1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> s 104835-82-7
L13 1 104835-82-7
(104835-82-7/RN)

=> d

L13 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 104835-82-7 REGISTRY
ED Entered STN: 25 Oct 1986
CN 2-Propenamide, N-[(4-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl- (CA INDEX NAME)
MF C13 H17 N O2
CI COM
SR CAS Client Services
LC STN Files: CA, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, USPAT2, USPATFULL



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> s 104835-82-7/crn
L14 16 104835-82-7/CRN

=> s 849686-90-4/crn
L15 0 849686-90-4/CRN

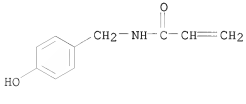
=> s 23281-77-8/crn
L16 2 23281-77-8/CRN

=> d 1-2

L16 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2008 ACS on STN
RN 845725-93-1 REGISTRY
ED Entered STN: 16 Mar 2005
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-[(4-hydroxyphenyl)methyl]-2-propenamide, 1-(4-hydroxyphenyl)-1H-pyrrole-2,5-dione and 2-propenenitrile (9CI) (CA INDEX NAME)
MF (C10 H11 N O2 . C10 H7 N O3 . C5 H8 O2 . C3 H3 N)x
CI PMS
PCT Polyacrylic, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

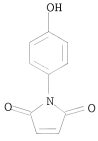
CM 1

CRN 23281-77-8
CMF C10 H11 N O2



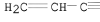
CM 2

CRN 7300-91-6
CMF C10 H7 N O3



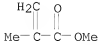
CM 3

CRN 107-13-1
CMF C3 H3 N



CM 4

CRN 80-62-6
CMF C5 H8 O2



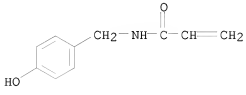
1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L16 ANSWER 2 OF 2 REGISTRY COPYRIGHT 2008 ACS on STN
RN 845725-90-8 REGISTRY
ED Entered STN: 16 Mar 2005
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with N-[(4-hydroxyphenyl)methyl]-2-propenamide, 1-(4-hydroxyphenyl)-1H-pyrrole-2,5-dione, methyl 2-methyl-2-propenoate and 2-propenenitrile (9CI) (CA INDEX NAME)
MF (C10 H11 N O2 . C10 H7 N O3 . C6 H10 O3 . C5 H8 O2 . C3 H3 N)x
CI PMS

PCT Polyacrylic, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

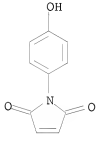
CM 1

CRN 23281-77-8
CMF C10 H11 N O2



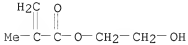
CM 2

CRN 7300-91-6
CMF C10 H7 N O3



CM 3

CRN 868-77-9
CMF C6 H10 O3

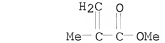


CM 4

CRN 107-13-1
CMF C3 H3 N

CM 5

CRN 80-62-6
CMF C5 H8 O2



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

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FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1 4064 S C11H13NO2/MF
L2 5 S L1 AND ACRYLAMIDE
L3 0 S HYDROXYBENZYLACRYLAMIDE
L4 26 S HYDROXYBENZYL AND ACRYLAMIDE
L5 24 S L4 NOT CHLORO
L6 15 S L5 NOT TERT
L7 0 S 13560-55-9/CRN

FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8 13 S L6
L9 4 S L8 AND PHOTO?

FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008
L10 1 S 13560-56-0
L11 1 S 23281-77-8
L12 1 S 849686-90-4
L13 1 S 104835-82-7
L14 16 S 104835-82-7/CRN
L15 0 S 849686-90-4/CRN
L16 2 S 23281-77-8/CRN

=> file caplus

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FULL ESTIMATED COST	42.76	113.48

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	0.00	-3.20

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FILE COVERS 1907 - 9 Sep 2008 VOL 149 ISS 11
FILE LAST UPDATED: 8 Sep 2008 (20080908/ED)

Caplus now includes complete International Patent Classification (IPC) reclassification data for the second quarter of 2008.

Effective October 17, 2005, revised CAS Information Use Policies apply. They are available for your review at:

http://www.cas.org/legal/infopolicy.html

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=> s l10 or l11 or l12 or l13 or l14 or l16
             4 L10
             2 L11
             1 L12
             2 L13
            10 L14
             1 L16
L17         16 L10 OR L11 OR L12 OR L13 OR L14 OR L16

=> s l17 not l9
L18         14 L17 NOT L9

=> d all 1-14

L18  ANSWER 1 OF 14  CAPLUS  COPYRIGHT 2008 ACS on STN
AN   2007:729107  CAPLUS
DN   147:128983
ED   Entered STN:  06 Jul 2007
TI   Radiation-sensitive resin compositions, interlayer insulators and
     microlenses therefrom, and manufacture thereof
IN   Hanamura, Masaaki; Takamoto, Eiji; Minowa, Takaki
PA   Jsr Ltd., Japan
SO   Jpn. Kokai Tokkyo Koho, 36pp.
     CODEN: JKXXAF
DT   Patent
LA   Japanese
CC   74-4 (Radiation Chemistry, Photochemistry, and Photographic and Other
     Reprographic Processes)
```

Section cross-reference(s): 38, 73

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2007171572	A	20070705	JP 2005-369301	20051222
	KR 2007066852	A	20070627	KR 2006-104391	20061026
	CN 101206401	A	20080625	CN 2006-10161738	20061219
PRAI	JP 2005-369301	A	20051222		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2007171572	IPCI	G03F0007-027 [I,A]; G03F0007-40 [I,A]; G02B0003-00 [I,A]
	IPCR	G03F0007-027 [I,C]; G03F0007-027 [I,A]; G02B0003-00 [I,C]; G02B0003-00 [I,A]; G03F0007-40 [I,C]; G03F0007-40 [I,A]
	FTERM	2H025/AA01; 2H025/AA04; 2H025/AA14; 2H025/AB14; 2H025/AB17; 2H025/AC01; 2H025/AD03; 2H025/BE01; 2H025/CB41; 2H025/CB43; 2H025/FA29; 2H096/AA27; 2H096/AA28; 2H096/BA10; 2H096/EA02; 2H096/HA01; 2H096/JA04
KR 2007066852	IPCI	C08L0067-02 [I,A]; C08L0067-00 [I,C*]
CN 101206401	IPCI	G03F0007-027 [I,A]; G03F0007-012 [I,A]; G03F0007-008 [I,C*]; G03F0007-004 [I,A]; G03F0007-16 [I,A]; G03F0007-20 [I,A]; G03F0007-26 [I,A]; G02B0003-00 [I,A]; H01L0021-027 [I,A]; H01L0021-02 [I,C*]

AB The compns. contain (A) copolymers of unsatd. carboxylic acids and/or their anhydrides, epoxy group-containing unsatd. compds., phenolic compds. R1C(:CH2)B(CH2)mC6R2R3R4R5R6 (R1 = H, C1-4 alkyl; R2-R6 = H, OH, C1-4 alkyl, where ≥1 of them is OH; B = single bond, CO2, CONH; m = 0-3), and unsatd. comonomers and (B) 1,2-quinonediazide compds. Photolithog. processing of the compns. for forming microlenses or interlayer insulators are also claimed. The compns. show improved development margin and provide patterns with fine profile and good heat and solvent resistance.

ST radiation sensitive resin compn microlens interlayer insulator; dimethylhydroxybenzylmethacrylamide glycidyl methacrylate resin compn photosensitivity; naphthoquinonendiazidesulfonate photosensitizer microlens insulator patternable compn

IT Dielectric films
Microlenses
Photoimaging materials
(photoimaging compns. containing resins polymerizing (meth)acryl-containing phenol compds. and epoxy compds. and showing good development margin)

IT 914090-16-7P 943128-53-8P 943128-54-9P 943128-55-0P 943128-56-1P 943128-57-2P 943128-58-3P 943128-59-4P 943128-60-7P 943128-61-8P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photoimaging compns. containing resins polymerizing (meth)acryl-containing phenol compds. and epoxy compds. and showing good development margin)

IT 107761-81-9, 2,3,4,4'-Tetrahydroxybenzophenone
1,2-naphthoquinonediazide-5-

sulfonate 142542-03-8 142542-04-9
RL: TEM (Technical or engineered material use); USES (Uses)
(photoimaging compns. containing resins polymerizing
(meth)acryl-containing phenol
compds. and epoxy compds. and showing good development margin)

L18 ANSWER 2 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2007:9640 CAPLUS
DN 146:111246
ED Entered STN: 04 Jan 2007
TI Method for preparing a lithographic printing plate precursor
IN Lingier, Stefaan; Vermeersch, Joan
PA Agfa-Gevaert, Belg.
SO Eur. Pat. Appl., 13pp.
CODEN: EPXXDW
DT Patent
LA English
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 1738902	A1	20070103	EP 2005-105882	20050630
R: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LI, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, AL, BA, HR, LV, MK, YU				
US 20070003875	A1	20070104	US 2006-477997	20060629
CN 1891455	A	20070110	CN 2006-10100200	20060630
IN 2006CH01133	A	20070622	IN 2006-CH1133	20060630
PRAI EP 2005-105882	A	20050630		
US 2005-700134P	P	20050718		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 1738902	IPCI	B41C0001-10 [I,A]
	IPCR	B41C0001-10 [I,C]; B41C0001-10 [I,A]
	ECLA	B41C001/10A
US 20070003875	IPCI	G03F0007-00 [I,A]
	IPCR	G03F0007-00 [I,C]; G03F0007-00 [I,A]
	NCL	430/302.000
CN 1891455	IPCI	B41C0001-055 [I,A]; B41C0001-10 [I,A]; B41M0005-36 [I,A]
	IPCR	B41C0001-055 [I,C]; B41C0001-055 [I,A]
	ECLA	B41C001/10A
IN 2006CH01133	IPCI	G03C0001-76 [ICM,7]

AB A method is disclosed wherein a pos.-working heat-sensitive lithog. printing plate precursor is prepared comprising the steps of: (i) providing
a support having a hydrophilic surface or which is provided with a hydrophilic layer, (ii) coating a first solution comprising a first polymer,
said first polymer being soluble in an alkaline solution, (iii) coating a second
solution comprising a heat-sensitive pos.-working imaging composition, and (iv)

coating a third solution comprising a third polymer or surfactant wherein said third polymer or said surfactant reduce the penetrability of an alkaline developer solution into the coating. The printing plates obtained by this method exhibits a reduced dot-loss, resulting in an improved developing latitude.

ST lithog printing plate precursor prepn

IT Lithographic plates
(method for preparing lithog. printing plate precursor)

IT Polysiloxanes, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(polyether-, Tegowet 265; method for preparing lithog. printing plate precursor)

IT Polysiloxanes, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(polyoxyalkylene-, graft, Tegoglide 410; method for preparing lithog. printing plate precursor)

IT Polyoxyalkylenes, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(polysiloxane-, graft, Tegoglide 410; method for preparing lithog. printing plate precursor)

IT Polyethers, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(siloxane-, Tegowet 265; method for preparing lithog. printing plate precursor)

IT 7429-90-5, Aluminum, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(electrochem. treated; method for preparing lithog. printing plate precursor)

IT 476436-67-6P
RL: POF (Polymer in formulation); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(method for preparing lithog. printing plate precursor)

IT 100346-90-5, Alnovol SPN 452
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(method for preparing lithog. printing plate precursor)

IT 90-50-6, 3,4,5-Trimethoxycinnamic acid 2580-56-5, Basonyl Blue 640 134127-48-3, S 0094
RL: TEM (Technical or engineered material use); USES (Uses)
(method for preparing lithog. printing plate precursor)

RE.CNT 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Kitson, P; WO 2005018934 A 2005 CAPLUS
(2) Luiz, A; US 2004152018 A1 2004

L18 ANSWER 3 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN

AN 2006:873569 CAPLUS

DN 147:199933

ED Entered STN: 29 Aug 2006

TI Lithographic printing plates by means of ink-jet printing
AU Anon.
CS UK
SO Research Disclosure (2006), 507(July), P886-P891 (No. 507035)
CODEN: RSDSBB; ISSN: 0374-4353
PB Kenneth Mason Publications Ltd.
DT Journal; Patent
LA English
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI RD 507035		20060710	RD 2006-507035	20060710
PRAI RD 2006-507035		20060710		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES

AB Preparation of lithog. printing plates by direct ink-jet printing is described.
By image-wise jetting droplets on a substrate, for example an aluminum support, a printing master is formed. A major problem associated with such printing techniques is the chemical resistance of the jetted drops towards press chems. during the printing step. The lower the chemical resistance of the droplets, the lower the run length of the plate will be. As a solution to this problem, a UV-curing step or a heat step is often performed prior to using the plate. In this work, the authors have identified an ink-jet fluid comprising a specific binder which is characterized by a min. Chemical Resistance Parameter value or CRP value. It was found that printing masters prepared by jetting these specific binders on an aluminum substrate, allow a high number of printed copies without the need for an addnl. UV-curing or heat-step.
ST lithog printing plate fabrication ink jet printing; ink jet printing phenolic resin binder lithog plate fabrication
IT Ink-jet printing
Lithographic plates
(fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)
IT Inks
(jet-printing; fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)
IT Polysiloxanes, uses
RL: NUU (Other use, unclassified); USES (Uses)
(polyoxyalkylene-, graft, Tegoglide 410; characterization of chemical

resistance of polymer binder coatings for ink-jet printing fabrication of lithog. printing plates)
IT Polyoxyalkylenes, uses
RL: NUU (Other use, unclassified); USES (Uses)
(polysiloxane-, graft, Tegoglide 410; characterization of chemical resistance of polymer binder coatings for ink-jet printing fabrication of lithog. printing plates)
IT 2580-56-5, Basonyl blue 640
RL: TEM (Technical or engineered material use); USES (Uses)
(Basonyl blue 640; fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)
IT 57534-43-7, Zonyl FSA
RL: TEM (Technical or engineered material use); USES (Uses)
(Zonyl FSA, substrate coating; fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)
IT 67-64-1, Acetone, uses 111-76-2
RL: NUU (Other use, unclassified); USES (Uses)
(characterization of chemical resistance of polymer binder coatings for ink-jet printing fabrication of lithog. printing plates)
IT 141634-00-6 182364-71-2 855472-18-3 917976-88-6 944250-49-1 944250-53-7 944250-56-0 944250-57-1
RL: PRP (Properties)
(characterization of chemical resistance of polymer binders for jetting formulations for ink-jet printing fabrication of lithog. printing plates)
IT 883726-92-9 944250-50-4 944250-51-5 944250-54-8
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)
IT 96-48-0 1320-67-8 7429-90-5, Aluminum, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(fabrication of lithog. printing plates by ink-jet printing using jetting formulation based on phenolic resin with N-containing pendants for increased chemical resistance towards press room chems.)

L18 ANSWER 4 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2005:1155390 CAPLUS
DN 143:413519
ED Entered STN: 28 Oct 2005
TI Negative working, heat-sensitive lithographic printing plate precursor
IN Vermeersch, Joan; Van, Damme Marc
PA Agfa-Gevaert N.V., Belg.
SO U.S. Pat. Appl. Publ., 15 pp.

CODEN: USXXCO
DT Patent
LA English
IC ICM G03C001-492
INCL 430270100
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 20050238994	A1	20051027	US 2005-113878	20050425
	US 7348126	B2	20080325		
	EP 1604818	A1	20051214	EP 2004-102654	20040611
	EP 1604818	B1	20070425		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
	JP 2005316471	A	20051110	JP 2005-126863	20050425
	CN 1690850	A	20051102	CN 2005-10067057	20050427
PRAI	EP 2004-101766	A	20040427		
	US 2004-570767P	P	20040513		
	EP 2004-102654	A	20040611		
	US 2004-579618P	P	20040615		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 20050238994	ICM	G03C001-492
	INCL	430270100
	IPCI	G03C0001-76 [I,A]; G03F0007-038 [I,A]; G03F0007-20 [I,A]; G03F0007-30 [I,A]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; G03C0001-005 [I,C*]; G03C0001-492 [I,A]
	NCL	430/270.100; 430/271.100; 430/302.000; 430/325.000; 430/944.000
	ECLA	B41C001/10A2
EP 1604818	IPCI	B41C0001-10 [I,C]; B41C0001-10 [I,A]
	IPCR	B41C0001-10 [I,C]; B41C0001-10 [I,A]
	ECLA	B41C001/10A2
JP 2005316471	IPCI	G03F0007-11 [ICM,7]; B41N0001-14 [ICS,7]; B41N0001-12 [ICS,7,C*]; G03F0007-00 [ICS,7]; G03F0007-004 [ICS,7]
	FTERM	2H025/AB03; 2H025/AC08; 2H025/AD01; 2H025/CB28; 2H025/CB41; 2H025/CB54; 2H025/CC20; 2H025/DA18; 2H025/DA35; 2H025/DA36; 2H025/DA40; 2H096/AA08; 2H096/BA20; 2H096/CA05; 2H096/EA04; 2H114/AA04; 2H114/AA22; 2H114/AA24; 2H114/AA30; 2H114/BA01; 2H114/BA05; 2H114/BA10; 2H114/DA59; 2H114/DA75; 2H114/EA01; 2H114/EA02; 2H114/FA10; 2H114/FA16
CN 1690850	IPCI	G03F0007-00 [ICM,7]; B41C0001-00 [ICS,7]
	IPCR	G03F0007-00 [I,C*]; G03F0007-00 [I,A]

AB A neg.-working lithog. printing plate precursor is disclosed comprising on
a support having a hydrophilic surface or which is provided with a hydrophilic layer, a coating comprising an IR absorbing agent, a first layer comprising an aqueous dispersion comprising hydrophobic thermoplastic

polymer particles and a first hydrophobic binder, and a second layer located between said first layer and said support which comprises a second hydrophobic binder, characterized in that said first hydrophobic binder is a phenolic resin and said second hydrophobic binder is a polymer comprising at least one sulfonamide group.

ST neg working heat sensitive lithog printing plate precursor

IT Lithographic plates
(neg. working, heat-sensitive lithog. printing plate precursor)

IT 476436-67-6P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(neg. working, heat-sensitive lithog. printing plate precursor containing)

IT 3251-84-1, Flexo-blue 630 9003-54-7, Acrylonitrile-styrene copolymer 100346-90-5, Alnovol SPN 452 134127-48-3, S0094
RL: TEM (Technical or engineered material use); USES (Uses)
(neg. working, heat-sensitive lithog. printing plate precursor containing)

RE.CNT 56 THERE ARE 56 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Anon; JP 2004117534 CAPLUS
(2) Anon; GB 1084070 1967 CAPLUS
(3) Anon; DE 1447963 1968
(4) Anon; GB 1154749 1969
(5) Anon; GB 1419512 1975 CAPLUS
(6) Anon; FR 2300354 1976 CAPLUS
(7) Anon; EP 0291760 1988 CAPLUS
(8) Anon; EP 0292801 1988 CAPLUS
(9) Anon; DE 4001466 A1 1991 CAPLUS
(10) Anon; EP 0537633 A1 1993 CAPLUS
(11) Anon; EP 0601240 A1 1994 CAPLUS
(12) Anon; EP 0625728 A2 1994 CAPLUS
(13) Anon; EP 0659909 A1 1995 CAPLUS
(14) Anon; DE 4417907 A1 1995 CAPLUS
(15) Anon; DE 4423140 A1 1996 CAPLUS
(16) Anon; EP 0770494 A2 1997 CAPLUS
(17) Anon; EP 0770495 A1 1997 CAPLUS
(18) Anon; EP 0770496 A1 1997 CAPLUS
(19) Anon; EP 0770497 A1 1997 CAPLUS
(20) Anon; EP 0800928 1997 CAPLUS
(21) Anon; WO 9739894 A1 1997 CAPLUS
(22) Anon; EP 0823327 A2 1998 CAPLUS
(23) Anon; EP 0864420 A1 1998 CAPLUS
(24) Anon; EP 0881096 A1 1998 CAPLUS
(25) Anon; EP 0894622 A2 1999 CAPLUS
(26) Anon; EP 0901902 A2 1999 CAPLUS
(27) Anon; EP 0933682 A2 1999 CAPLUS
(28) Anon; WO 0029214 A1 2000 CAPLUS
(29) Anon; WO 0032705 A1 2000 CAPLUS
(30) Anon; EP 1029667 A1 2000
(31) Anon; EP 1053868 A2 2000 CAPLUS
(32) Anon; EP 1093934 A1 2001 CAPLUS
(33) Anon; EP 1216831 2002 CAPLUS

(34) Anon; EP 1243413 A1 2002
(35) Anon; WO 03087942 A1 2003
(36) Anon; EP 04102654 2004
(37) Anon; JP 2004117534 2004 CAPLUS
(38) Boergerding; US 4897168 A 1990 CAPLUS
(39) Brenk; US 5637441 A 1997 CAPLUS
(40) DeSanto; US 4981517 A 1991 CAPLUS
(41) Denzinger; US 6190825 B1 2001 CAPLUS
(42) Elsaesser; US 5314787 A 1994
(43) Elsaesser; US 5695903 A 1997 CAPLUS
(44) Grunwald; US 5641608 A 1997 CAPLUS
(45) Kawamura; US 20020117066 A1 2002
(46) Kline; US 5174205 A 1992
(47) Mohr; US 4458005 A 1984 CAPLUS
(48) Parkinson; US 4045232 A 1977 CAPLUS
(49) Pensavecchia; US 5163368 A 1992
(50) Phlipot; US 4284705 A 1981 CAPLUS
(51) Pliefke; US 4840713 A 1989 CAPLUS
(52) Pliefke; US 5156723 A 1992 CAPLUS
(53) Staehle; US 3971660 A 1976 CAPLUS
(54) Van Damme; US 20020168582 A1 2002
(55) Vrancken; US 3476937 A 1969
(56) Zertani; US 5229253 A 1993 CAPLUS

L18 ANSWER 5 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2005:160711 CAPLUS
DN 142:269261
ED Entered STN: 25 Feb 2005
TI Base plate for lithographic printing plate
IN Ozaki, Jun; Uozumi, Yasuhiro
PA Okamoto Chemical Industry Co. Ltd., Japan
SO U.S. Pat. Appl. Publ., 12 pp.
CODEN: USXXCO
DT Patent
LA English
IC ICM G03F007-00
INCL 430302000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
FAN.CNT 1

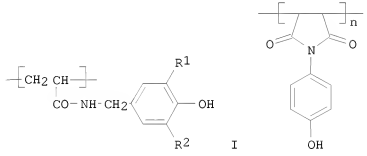
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 20050042546	A1	20050224	US 2004-921935	20040820
	JP 2005097546	A	20050414	JP 2004-209456	20040716
	EP 1577330	A1	20050921	EP 2004-254951	20040818
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
PRAI	JP 2003-298043	A	20030822		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 20050042546	ICM	G03F007-00
	INCL	430302000

	IPCI	G03F0007-00 [ICM,7]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; C08F0220-00 [I,C*]; C08F0220-58 [I,A]; C08F0222-00 [I,C*]; C08F0222-40 [I,A]
	NCL	430/302.000
	ECLA	B41C001/10A; C08F220/58; C08F222/40
JP 2005097546	IPCI	C08F0220-58 [ICM,7]; C08F0220-00 [ICM,7,C*]; C08F0222-40 [ICS,7]; C08F0222-00 [ICS,7,C*]; G03F0007-00 [ICS,7]; G03F0007-004 [ICS,7]; G03F0007-023 [ICS,7]; G03F0007-033 [ICS,7]
	IPCR	C08F0220-00 [I,C*]; C08F0220-58 [I,A]; C08F0222-00 [I,C*]; C08F0222-40 [I,A]; G03F0007-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-004 [I,A]; G03F0007-004 [I,C*]; G03F0007-023 [I,A]; G03F0007-023 [I,C*]; G03F0007-033 [I,A]; G03F0007-033 [I,C*]
	FTERM	2H025/AA04; 2H025/AA12; 2H025/AB03; 2H025/AC08; 2H025/AD03; 2H025/BE01; 2H025/CB10; 2H025/CB15; 2H025/CB43; 2H025/CB45; 2H025/CC11; 2H096/AA06; 2H096/BA10; 2H096/EA02; 2H096/GA08; 4J100/AB02R; 4J100/AB03R; 4J100/AB07R; 4J100/AJ02R; 4J100/AK32R; 4J100/AL03R; 4J100/AL04R; 4J100/AL05R; 4J100/AL08R; 4J100/AL75R; 4J100/AM02R; 4J100/AM15R; 4J100/AM21P; 4J100/AM21R; 4J100/AM49Q; 4J100/AQ08R; 4J100/AQ12R; 4J100/BA02R; 4J100/BA03P; 4J100/BA03Q; 4J100/BA03R; 4J100/BA59R; 4J100/BC43P; 4J100/BC43R; 4J100/CA04; 4J100/CA05; 4J100/JA37
EP 1577330	IPCI	C08F0220-58 [ICM,7]; C08F0220-00 [ICM,7,C*]; C08F0222-40 [ICS,7]; C08F0222-00 [ICS,7,C*]; G03F0007-023 [ICS,7]; B41C0001-10 [ICS,7]
	IPCR	B41C0001-10 [I,C*]; B41C0001-10 [I,A]; C08F0220-00 [I,C*]; C08F0220-58 [I,A]; C08F0222-00 [I,C*]; C08F0222-40 [I,A]
	ECLA	B41C001/10A; C08F220/58; C08F222/40

GI



I II

AB The object of the present invention is to provide a base plate for a lithog. printing plate comprising a photosensitive layer that prevent the occurrence of the fingerprint rub-off phenomena and abrasion phenomena and

offer superior anti-abrasiveness and chemical resistance. The present invention provides copolymers having monomeric units shown in formulas I and II (R1, R2 = H, C1-12-alkyl); an image-forming composition comprising the copolymer; and a base plate for a lithog. printing plate comprising, on a support structure, a photosensitive layer that contains the copolymer.
ST base lithog printing plate
IT Lithographic plates
(base plate for lithog. printing plate)
IT 845725-90-8P 845725-92-0P 845725-93-1P 845725-94-2P 845725-95-3P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(base plate for lithog. printing plate)

L18 ANSWER 6 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2005:146867 CAPLUS
DN 142:374225
ED Entered STN: 21 Feb 2005
TI Synthesis and applications of novel fluoroalkyl end-capped oligomers containing 3,5-dimethyl-4-hydroxybenzyl and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments
AU Sawada, Hideo; Kawasaki, Nobuhito; Sasazawa, Kazuo; Kawase, Tokuzo
CS Department of Materials Science and Technology, Faculty of Science and Technology, Hirosaki University, Hirosaki, Japan
SO International Journal of Polymeric Materials (2005), 54(4), 311-332
CODEN: IJPMCS; ISSN: 0091-4037
PB Taylor & Francis, Inc.
DT Journal
LA English
CC 35-4 (Chemistry of Synthetic High Polymers)
AB New fluoroalkyl end-capped co-oligomers containing 3,5-dimethyl-4-hydroxybenzyl segments [RF-(DMHB)x-(DMAA)y-RF] were prepared by the reactions of fluoroalkanoyl peroxides with N-(3,5-dimethyl-4-hydroxybenzyl)methacrylamide [DMHB] and N,N-dimethylacrylamide (DMAA). Similarly, fluoroalkyl end-capped homo- and co-oligomers containing 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments [RF-(BTRI)x-(Co-M)y-RF] were prepared by the reactions of fluoroalkanoyl peroxides with 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl methacrylate [BTRI] and co-monomers [Co-M] such as acrylic acid (ACA), DMAA, and acryloylmorpholine (ACMO). The fluoroalkyl end-capped DMHB and BTRI co-oligomers thus obtained were soluble not only in water but also in common organic solvents. In addition, these fluorinated co-oligomers were able to reduce the surface tension of 0.1 N NaOH solns. quite effectively to around 20 mN/m levels, although the corresponding non-fluorinated co-oligomers were not effective in reducing the surface tension of 0.1 N NaOH solns. A modified polystyrene film surface treated with these fluoroalkyl end-capped DMHB and BTRI co-oligomers exhibited a good oleophobicity imparted by fluorine with an excellent hydrophilicity. XPS analyses showed that end-capped fluoroalkyl groups in RF-(BTRI)n-RF homo-oligomer were arranged regularly above the modified polystyrene surface. Of particular interest, it was demonstrated that the self-assembled mol. aggregates formed by RF-(DMHB)x-(DMAA)y-RF

co-oligomers could interact strongly with 7,7,8,8-tetracyanoquinodimethane (TCNQ) as a guest mol. to form a host-guest intermol. complex, though such a host-guest interaction was not observed in the corresponding non-fluorinated DMHB co-oligomer.
ST fluoroalkyl terminated hydroxybenzyl methacrylamide oligomer; benzotriazolyl hydroxyphenylethyl methacrylate oligomer fluoroalkyl terminated; surfactant fluoroalkyl terminated acrylic polymer
IT Surfactants
(fluoroalkyl end-capped oligomers containing 3,5-dimethyl-4-hydroxybenzyl and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments)
IT Polymerization
(of 3,5-dimethyl-4-hydroxybenzyl)methacrylamide and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl methacrylate with acrylic monomers in presence of fluoroalkanoyl peroxides)
IT Hydrophilicity
Self-assembly
Solubility
Surface tension
(of fluoroalkyl end-capped oligomers containing 3,5-dimethyl-4-hydroxybenzyl and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments)
IT Fluoropolymers, preparation
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(oligomeric; synthesis and applications of fluoroalkyl end-capped oligomers containing 3,5-dimethyl-4-hydroxybenzyl and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments)
IT 1518-16-7, TCNQ
RL: RCT (Reactant); RACT (Reactant or reagent)
(guest mol.; in interaction of self-assembled amphiphilic perfluoroalkoxyl-terminated acrylic oligomers)
IT 56347-79-6DP, reaction products with (dimethylhydroxybenzyl)methacrylamide and [(benzotriazolyl)hydroxyphenyl]ethyl methacrylate polymers
96478-13-6DP, α,ω-bis(perfluoroalkoxyl)-terminated
133414-70-7DP, reaction products with (dimethylhydroxybenzyl)methacrylamid e and [(benzotriazolyl)hydroxyphenyl]ethyl methacrylate polymers
133414-71-8DP, reaction products with (dimethylhydroxybenzyl)methacrylamid e and [(benzotriazolyl)hydroxyphenyl]ethyl methacrylate polymers
215384-92-2DP, Acrylic acid-2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl methacrylate copolymer, α,ω-bis(perfluoroalkoxyl)-terminated 464193-86-0DP, α,ω-bis(perfluoroalkoxyl)-terminated 464193-87-1DP, α,ω-bis(perfluoroalkoxyl)-terminated 849686-90-4DP, N,N-Dimethylacrylamide-N-(3,5-dimethyl-4-hydroxybenzyl)methacrylamide copolymer, α,ω-bis(perfluoroalkoxyl)-terminated
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(oligomeric; synthesis and applications of fluoroalkyl end-capped oligomers containing 3,5-dimethyl-4-hydroxybenzyl and 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl segments)

RE.CNT 19 THERE ARE 19 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE
(1) Abe, M; Langmuir 1992, V8, P763 CAPLUS
(2) Ishikawa, N; J Fluorine Chem 1984, V25, P241 CAPLUS
(3) Ishikawa, N; J Jpn Oil Chem Soc 1977, V26, P613 CAPLUS
(4) Issacs, N; Reactive Intermediates in Orgainc Chemistry 1974, P522
(5) Morita, M; Colloid Surface 1996, V109, P183 CAPLUS
(6) Ono, Y; J Jpn Oil Chem Soc 1985, V34, P1035 CAPLUS
(7) Park, I; J Appl Polymn Sci 1994, V54, P1449 CAPLUS
(8) Park, I; J Colloid Interface Sci 1996, V181, P284 CAPLUS
(9) Sawada, H; Bull Chem Soc Jpn 1986, V59, P215 CAPLUS
(10) Sawada, H; Chem Rev 1996, V96, P1779 CAPLUS
(11) Sawada, H; J Fluorine Chem 1990, V51, P117
(12) Sawada, H; J Jpn Oil Chem Soc 1991, V40, P730 CAPLUS
(13) Sawada, H; Kobunshi Ronbunshu 2001, V58, P147
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(17) Strauss, U; J Phys Chem 1961, V65, P1390 CAPLUS
(18) Tanizaki, Y; J Jpn Oil Chem Soc 1985, V34, P973 CAPLUS
(19) Yoshino, N; Langmuir 1995, V11, P466 CAPLUS

L18 ANSWER 7 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1998:653687 CAPLUS
DN 129:283448
OREF 129:57657a,57660a
ED Entered STN: 15 Oct 1998
TI Radiation sensitive composition and registration materials for lithographic printing plates prepared therewith
IN Elsasser, Andreas; Gaschler, Otfried; Haberhauer, Helmut; Eichhorn, Mathias; Grabley, Fritz-Feo; Leichsenring, Thomas; Koletar, Gabor I.; Seeley, Douglas A.
PA AGFA-GEVAERT A.-G., Germany
SO Eur. Pat. Appl., 8 pp.
CODEN: EPXXDW
DT Patent
LA German
IC ICM B41C001-10
ICS B41M005-40
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 867278	A1	19980930	EP 1998-105080	19980320
	EP 867278	B1	20011121		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, MC, PT, IE, SI, LT, LV, FI, RO				
	DE 19712323	A1	19981001	DE 1997-19712323	19970324
	US 6100004	A	20000808	US 1998-38162	19980311
	JP 10293398	A	19981104	JP 1998-66828	19980317
PRAI	DE 1997-19712323	A	19970324		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES

EP 867278	ICM	B41C001-10
	ICS	B41M005-40
	IPCI	B41C0001-10 [ICM,6]; B41M0005-40 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	ECLA	B41C001/10A; B41M005/40F2; B41M005/46B
DE 19712323	IPCI	G03F0007-004 [ICM,6]; G03F0007-021 [ICS,6]; G03F0007-016 [ICS,6,C*]; G03F0007-14 [ICS,6]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	ECLA	B41M005/46B; B41C001/10A
US 6100004	IPCI	G03F0007-021 [ICM,7]; G03F0007-016 [ICM,7,C*]; G03F0007-30 [ICS,7]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; B41C0001-10 [I,C*]; B41C0001-10 [I,A]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]; C09D0011-00 [I,C*]; C09D0011-00 [I,A]; G03F0007-00 [I,C*]; G03F0007-00 [I,A]; G03F0007-016 [I,C*]; G03F0007-021 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-32 [I,C*]; G03F0007-32 [I,A]
	NCL	430/176.000; 430/191.000; 430/192.000; 430/193.000; 430/270.100; 430/281.100; 430/302.000
	ECLA	B41C001/10A; B41M005/40F2
JP 10293398	IPCI	G03F0007-004 [ICM,6]; C09D0011-00 [ICS,6]; G03F0007-00 [ICS,6]; G03F0007-021 [ICS,6]; G03F0007-016 [ICS,6,C*]; G03F0007-022 [ICS,6]; G03F0007-32 [ICS,6]
	IPCR	B41C0001-10 [I,A]; B41C0001-10 [I,C*]; B41M0005-40 [I,C*]; B41M0005-46 [I,A]
	ECLA	B41M005/46B; B41C001/10A

AB A pos.- or neg.-working radiation-sensitive resist mixture contains a soot pigment with a primary particle size of at least 80 nm as an IR-absorbing component, wherein the soot pigment is dispersed in a polymer containing an acid unit having pKs value of smaller than 13.

ST radiation sensitive resist compn printing plate; offset lithog plate soot pigment

IT Lithographic plates
(offset; radiation sensitive composition and registration materials for lithog. printing plates prepared therewith)

IT Photoresists
Soot
(radiation sensitive composition and registration materials for lithog.

printing plates prepared therewith)
IT Carbon black, uses
Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(radiation sensitive composition and registration materials for lithog.
printing plates prepared therewith)
IT 23121-00-8 24979-70-2, Poly(4-hydroxy styrene) 27029-76-1
31693-08-0, 2-Hydroxyethyl methacrylate-methacrylic acid copolymer
38333-84-5, Acetone-pyrogallol copolymer 68510-93-0 110254-07-4
128067-80-1, (4-Hydroxy-3,5-dimethylbenzyl)methacrylamide
homopolymer 155599-65-8 213902-63-7
RL: TEM (Technical or engineered material use); USES (Uses)
(radiation sensitive composition and registration materials for lithog.
printing plates prepared therewith)
RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Clark, F; WO 9401280 A 1994
(2) Davi, H; WO 9620429 A 1996 CAPLUS
(3) Minnesota Mining & Mfg; EP 0562952 A 1993 CAPLUS
(4) Scitex Corp Ltd; WO 9700175 A 1997 CAPLUS

L18 ANSWER 8 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1996:635036 CAPLUS
DN 125:261365
OREF 125:48555a,48558a
ED Entered STN: 28 Oct 1996
TI Polymers of acrylamide derivatives and their use as binders in light-sensitive compositions
IN Eichhorn, Mathias; Elsaeser, Andreas
PA Hoechst A.-G., Germany
SO Ger. Offen., 12 pp.
CODEN: GWXXBX
DT Patent
LA German
IC ICM C08F020-60
ICS G03F007-023
CC 74-10 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 37
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI DE 19507618	A1	19960905	DE 1995-19507618	19950304
EP 731113	A2	19960911	EP 1996-102835	19960226
EP 731113	A3	19970122		
EP 731113	B1	19990113		
R: BE, DE, FR, GB, IT, NL				
US 5700621	A	19971223	US 1996-607809	19960228
JP 08259627	A	19961008	JP 1996-46417	19960304
BR 9600888	A	19971230	BR 1996-888	19960304
PRAI DE 1995-19507618	A	19950304		

CLASS
PATENT NO. CLASS PATENT FAMILY CLASSIFICATION CODES

DE 19507618	ICM	C08F020-60
	ICS	G03F007-023
	IPCI	C08F0020-60 [ICM,6]; C08F0020-00 [ICM,6,C*]; G03F0007-023 [ICS,6]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08F0020-60 [I,A]; C08K0005-00 [I,C*]; C08K0005-28 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-037 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	ECLA	C08F020/60; G03F007/023P
EP 731113	IPCI	C08F0020-60 [ICM,6]; C08F0020-00 [ICM,6,C*]; G03F0007-033 [ICS,6]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08F0020-60 [I,A]; C08K0005-00 [I,C*]; C08K0005-28 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-037 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	ECLA	C08F020/60; G03F007/023P
US 5700621	IPCI	G03C0001-52 [ICM,6]; C08F0020-54 [ICS,6]; C08F0020-00 [ICS,6,C*]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08F0020-60 [I,A]; C08K0005-00 [I,C*]; C08K0005-28 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-037 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	NCL	430/192.000; 430/165.000; 526/306.000
	ECLA	C08F020/60; G03F007/023P
JP 08259627	IPCI	C08F0020-54 [ICM,6]; C08F0020-00 [ICM,6,C*]; C08K0005-28 [ICS,6]; C08K0005-00 [ICS,6,C*]; C08L0033-24 [ICS,6]; C08L0033-00 [ICS,6,C*]; G03F0007-022 [ICS,6]; G03F0007-037 [ICS,6]; G03F0007-032 [ICS,6,C*]; G03F0007-039 [ICS,6]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08F0020-60 [I,A]; C08K0005-00 [I,C*]; C08K0005-28 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-037 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
BR 9600888	IPCI	G03C0001-695 [ICM,6]
	IPCR	G03F0007-022 [I,C*]; G03F0007-022 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-54 [I,A]; C08F0020-60 [I,A]; C08K0005-00 [I,C*]; C08K0005-28 [I,A]; C08L0033-00 [I,C*]; C08L0033-24 [I,A]; G03F0007-023 [I,C*]; G03F0007-023 [I,A]; G03F0007-032 [I,C*]; G03F0007-037 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]

AB Polymers of monomers such as N-(acryloylaminomethyl)phthalimide (I),

N-(methacryloylaminomethyl)phthalimide, and N-(acryloylaminomethyl)-1,1-dioxo-1,2-benzisothiazol-3(2H)-one (II) (e.g., I homopolymer, I-2-hydroxyphenyl methacrylate copolymer, acrylic acid-II-2-hydroxyphenyl methacrylate copolymer, or I-Me methacrylate-styrene copolymer) are prepared
The polymers are insol. in water and soluble or swellable in aqueous alkali
solution and are used as binders for 1,2-quinone diazides in light-sensitive
compns. for the preparation of printing plates with good printing properties
and resistance to organic cleaning solvents.
ST acrylamide polymer binder light sensitive diazide; phthalimide acrylamidomethyl binder light sensitive diazide; saccharin acrylamidomethyl binder light sensitive diazide; acrylamidomethylphthalimide polymer binder light sensitive diazide; acrylamidomethylbenzisothiazolone polymer binder light sensitive diazide; printing plate light sensitive diazide binder
IT Binding materials
(acrylamide derivative polymers; preparation and use with diazides in light-sensitive compns. for manufacture of printing plates)
IT Printing plates
(light-sensitive compns. containing diazo compds. and binders comprising
acrylamide derivative polymers for manufacture of)
IT Light-sensitive materials
(use of diazo compds. with binders comprising acrylamide derivative polymers for manufacture of printing plates)
IT Diazo compounds
RL: MOA (Modifier or additive use); MSC (Miscellaneous); NUU (Other use, unclassified); USES (Uses)
(use with binders comprising acrylamide derivative polymers in light-sensitive compns. for manufacture of printing plates)
IT 80500-95-4P, N-(Acryloylaminomethyl)phthalimide polymer 182364-70-1P, N-(Acryloylaminomethyl)phthalimide-2-hydroxyphenyl methacrylate copolymer 182364-71-2P, 2-Hydroxyphenyl methacrylate-N-(methacryloylaminomethyl)phth
alimide copolymer 182364-72-3P 182364-73-4P, Acrylic acid-N-(Acryloylaminomethyl)phthalimide-2-hydroxyphenyl methacrylate copolymer 182364-74-5P 182364-75-6P 182364-76-7P 182364-77-8P 182364-78-9P
RL: IMF (Industrial manufacture); NUU (Other use, unclassified); PREP (Preparation); USES (Uses)
(preparation and use as binders for diazides in light-sensitive compns. for
manufacture of printing plates)

L18 ANSWER 9 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:994642 CAPLUS
DN 124:86996
OREF 124:16351a
ED Entered STN: 22 Dec 1995
TI Preparation of 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines as antirheumatics
IN Schwab, Wilfired; Anagnostopulos, Hiristo; Ryder, Bartlett Robert;

Schleyerbach, Rudolf; Weithmann, Klaus Ulrich
PA Hoechst A.-G., Germany
SO Ger. Offen., 50 pp.
CODEN: GWXXBX
DT Patent
LA German
IC ICM C07D261-04
ICS C07D413-04; C07D261-20; C07D261-18; C07D261-08; C07D417-04; A61K031-42; A61K031-425; A61K031-44
ICA C07D521-00; C07B051-00
ICI C07D413-04, C07D261-04, C07D213-24, C07D333-06, C07D303-12, C07D257-04; C07D417-04, C07D261-04, C07D277-28
CC 28-6 (Heterocyclic Compounds (More Than One Hetero Atom))
Section cross-reference(s): 1
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4408084	A1	19950914	DE 1994-4408084	19940310
	TW 419469	B	20010121	TW 1994-83108551	19940916
	CA 2185004	A1	19950914	CA 1995-2185004	19950303
	WO 9524397	A1	19950914	WO 1995-EP784	19950303
	W: AU, CA, CN, FI, HU, JP, KR, NO, RU, US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	AU 9519481	A	19950925	AU 1995-19481	19950303
	AU 684914	B2	19980108		
	EP 749429	A1	19961227	EP 1995-912197	19950303
	EP 749429	B1	19990630		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LI, LU, NL, PT, SE				
	CN 1143956	A	19970226	CN 1995-192004	19950303
	CN 1056836	C	20000927		
	HU 76481	A2	19970929	HU 1996-2458	19950303
	HU 225499	B1	20070129		
	JP 09509951	T	19971007	JP 1995-523212	19950303
	AT 181733	T	19990715	AT 1995-912197	19950303
	ES 2135046	T3	19991016	ES 1995-912197	19950303
	NO 9603560	A	19960826	NO 1996-3560	19960826
	FI 9603508	A	19960906	FI 1996-3508	19960906
	US 5814627	A	19980929	US 1996-704743	19961119
PRAI	DE 1994-4408084	A	19940310		
	WO 1995-EP784	W	19950303		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 4408084	ICM	C07D261-04
	ICS	C07D413-04; C07D261-20; C07D261-18; C07D261-08; C07D417-04; A61K031-42; A61K031-425; A61K031-44
	ICA	C07D521-00; C07B051-00
	ICI	C07D413-04, C07D261-04, C07D213-24, C07D333-06, C07D303-12, C07D257-04; C07D417-04, C07D261-04, C07D277-28
	IPCI	C07D0261-04 [ICM,6]; C07D0413-04 [ICS,6]; C07D0261-20 [ICS,6]; C07D0261-18 [ICS,6]; C07D0261-08 [ICS,6]; C07D0417-04 [ICS,6]; A61K0031-42 [ICS,6]; A61K0031-425 [ICS,6]; A61K0031-44 [ICS,6]; C07D0413-04 [ICI,6]; C07D0413-00 [ICI,6,C*]; C07D0261-04 [ICI,6];

		C07D0213-24 [ICI,6]; C07D0213-00 [ICI,6,C*]; C07D0333-06 [ICI,6]; C07D0333-00 [ICI,6,C*]; C07D0303-12 [ICI,6]; C07D0303-00 [ICI,6,C*]; C07D0257-04 [ICI,6]; C07D0257-00 [ICI,6,C*]; C07D0417-04 [ICI,6]; C07D0417-00 [ICI,6,C*]; C07D0261-04 [ICI,6]; C07D0261-00 [ICI,6,C*]; C07D0277-28 [ICI,6]; C07D0277-00 [ICI,6,C*]; C07D0521-00 [ICA,6]; C07B0051-00 [ICA,6]
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	ECLA	C07C205/51; C07D261/04; C07D261/08; C07D261/20; C07D413/04+261+213; C07D413/04+303+261; C07D413/04+317+261; C07D413/04+333B+261; C07D413/12+261+257; C07D417/04+277B+261; C07F009/653
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AU 9519481	IPCI	C07D0261-04 [ICM,6]; A61K0031-42 [ICS,6]; C07D0261-08 [ICS,6]; C07F0009-653 [ICS,6]; C07F0009-00 [ICS,6,C*]; C07D0413-04 [ICS,6]; C07D0413-12 [ICS,6]; C07D0413-00 [ICS,6,C*]; C07D0261-20 [ICS,6]; C07D0261-00 [ICS,6,C*]
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CN 1143956 IPCI C07D0261-04 [ICM,6]; A61K0031-42 [ICS,6]; C07D0261-08 [ICS,6]; C07F0009-653 [ICS,6]; C07F0009-00 [ICS,6,C*]; C07D0413-04 [ICS,6]; C07D0413-12 [ICS,6]; C07D0413-00 [ICS,6,C*]; C07D0261-20 [ICS,6]; C07D0261-00 [ICS,6,C*]

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AT 181733	IPCI	C07D0261-04 [ICM,6]; A61K0031-42 [ICS,6]; C07D0261-08 [ICS,6]; C07F0009-653 [ICS,6]; C07F0009-00 [ICS,6,C*]; C07D0413-04 [ICS,6]; C07D0413-12 [ICS,6]; C07D0413-00 [ICS,6,C*]; C07D0261-20 [ICS,6]; C07D0261-00 [ICS,6,C*]
	IPCR	A61K0031-41 [I,C*]; A61K0031-41 [I,A]; A61K0031-42 [I,C*]; A61K0031-42 [I,A]; A61K0031-423 [I,C*]; A61K0031-423 [I,A]; A61K0031-495 [I,C*]; A61K0031-495 [I,A]; A61K0031-496 [I,C*]; A61K0031-496 [I,A]; A61K0031-535 [I,C*]; A61K0031-535 [I,A]; A61K0031-5375 [I,C*]; A61K0031-5377 [I,A]; A61P0011-00 [I,C*]; A61P0011-00 [I,A]; A61P0029-00 [I,C*]; A61P0029-00 [I,A]; A61P0037-00 [I,C*]; A61P0037-00 [I,A]; C07C0205-00 [I,C*]; C07C0205-51 [I,A]; C07D0261-00 [I,C*]; C07D0261-04 [I,A]; C07D0261-08 [I,A]; C07D0261-18 [I,A]; C07D0261-20 [I,A]; C07D0263-00 [I,C*]; C07D0263-30 [I,A]; C07D0413-00 [I,C*]; C07D0413-04 [I,A]; C07D0413-12 [I,A]; C07D0417-00 [I,C*]; C07D0417-04 [I,A]; C07F0009-00 [I,C*]; C07F0009-653 [I,A]
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	IPCR	A61K0031-41 [I,C*]; A61K0031-41 [I,A]; A61K0031-42 [I,C*]; A61K0031-42 [I,A]; A61K0031-423 [I,C*]; A61K0031-423 [I,A]; A61K0031-495 [I,C*]; A61K0031-495 [I,A]; A61K0031-496 [I,C*]; A61K0031-496 [I,A]; A61K0031-535 [I,C*]; A61K0031-535 [I,A]; A61K0031-5375 [I,C*]; A61K0031-5377 [I,A]; A61P0011-00 [I,C*]; A61P0029-00 [I,C*]; A61P0029-00 [I,A]; A61P0037-00 [I,C*]; A61P0037-00 [I,A]; C07C0205-00 [I,C*]; C07C0205-51 [I,A]; C07D0261-00 [I,C*]; C07D0261-04 [I,A]; C07D0261-08 [I,A]; C07D0261-18 [I,A]; C07D0261-20 [I,A]; C07D0263-00 [I,C*]; C07D0263-30 [I,A]; C07D0413-00 [I,C*]; C07D0413-04 [I,A]; C07D0413-12 [I,A]; C07D0417-00 [I,C*]; C07D0417-04 [I,A]; C07F0009-00 [I,C*]; C07F0009-653 [I,A]
FI 9603508	IPCI	C07D [ICM,6]
	IPCR	A61K0031-41 [I,C*]; A61K0031-41 [I,A]; A61K0031-42 [I,C*]; A61K0031-42 [I,A]; A61K0031-423 [I,C*]; A61K0031-423 [I,A]; A61K0031-495 [I,C*]; A61K0031-495 [I,A]; A61K0031-496 [I,C*]; A61K0031-496 [I,A]; A61K0031-535 [I,C*]; A61K0031-535 [I,A]; A61K0031-5375 [I,C*]; A61K0031-5377 [I,A]; A61P0011-00 [I,C*]; A61P0029-00 [I,C*]; A61P0029-00 [I,A]; A61P0037-00 [I,C*]; A61P0037-00 [I,A]; C07C0205-00 [I,C*]; C07C0205-51 [I,A]; C07D0261-00 [I,C*]; C07D0261-04 [I,A]; C07D0261-08 [I,A]; C07D0261-18 [I,A]; C07D0261-20 [I,A]; C07D0263-00 [I,C*]; C07D0263-30 [I,A]; C07D0413-00 [I,C*]; C07D0413-04 [I,A]; C07D0413-12 [I,A]; C07D0417-00 [I,C*]; C07D0417-04 [I,A]; C07F0009-00 [I,C*]; C07F0009-653 [I,A]
US 5814627	IPCI	A61K0031-42 [ICM,6]; A61K0031-535 [ICS,6]; C07D0261-04 [ICS,6]; C07D0261-00 [ICS,6,C*]; C07D0413-12 [ICS,6]; C07D0413-00 [ICS,6,C*]
	IPCR	A61K0031-41 [I,C*]; A61K0031-41 [I,A]; A61K0031-42 [I,C*]; A61K0031-42 [I,A]; A61K0031-423 [I,C*]; A61K0031-423 [I,A]; A61K0031-495 [I,C*]; A61K0031-495 [I,A]; A61K0031-496 [I,C*]; A61K0031-496 [I,A]; A61K0031-535 [I,C*]; A61K0031-535 [I,A]; A61K0031-5375 [I,C*]; A61K0031-5377 [I,A]; A61P0011-00 [I,C*];

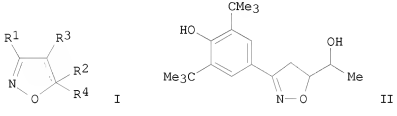
A61P0011-00 [I,A]; A61P0029-00 [I,C*]; A61P0029-00 [I,A]; A61P0037-00 [I,C*]; A61P0037-00 [I,A]; C07C0205-00 [I,C*]; C07C0205-51 [I,A]; C07D0261-00 [I,C*]; C07D0261-04 [I,A]; C07D0261-08 [I,A]; C07D0261-18 [I,A]; C07D0261-20 [I,A]; C07D0263-00 [I,C*]; C07D0263-30 [I,A]; C07D0413-00 [I,C*]; C07D0413-04 [I,A]; C07D0413-12 [I,A]; C07D0417-00 [I,C*]; C07D0417-04 [I,A]; C07F0009-00 [I,C*]; C07F0009-653 [I,A]

NCL 514/236.800; 514/378.000; 544/137.000; 544/367.000; 546/272.100; 548/111.000; 548/119.000; 548/205.000; 548/240.000; 548/247.000; 548/248.000

ECLA C07C205/51; C07D261/04; C07D261/08; C07D261/20; C07D413/04+261+213; C07D413/04+303+261; C07D413/04+317+261; C07D413/04+333B+261; C07D413/12+261+257; C07D417/04+277B+261; C07F009/653

OS CASREACT 124:86996; MARPAT 124:86996

GI



AB Title compds. [I; l of R1,R2 = 4,3,5-HO(Me3C)2C6H2 and the other = pyridyl, thiazolyl, (CH2)nCR5R6(CH2)mZR7, etc.; R3 = H, (hydroxy)alkyl; R4 = H, alkyl; R2R4 = atoms to form an aliphatic ring.; R5,R6 = H, alkyl, OH, Ph, etc.; R7 = H, amino acid residue, CO2H, alkoxycarbonyl, etc.; Z = O, NH; dashed line = optional bond when R4 = null; m = 0-4; n = 0-6] were prepared as non-cyclooxygenase inhibiting antirheumatics. Thus, 4,3,5-HO(Me3C)2C6H2C:NOH (preparation given) was cyclocondensed with CH2:CHCH(OH)Me to give racemic erythro-II which gave 85% inhibition of adjuvant-induced foot swelling in rats receiving 25mg/kg orally.

ST isoxazoline hydroxyditertbutylphenyl prepn antirheumatic

IT Autoimmune disease
(treatment; preparation of 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines as antirheumatics)

IT Bronchodilators
(antiasthmatics, 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines)

IT Inflammation inhibitors
(antirheumatics, 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines)

IT 172412-78-1P 172412-79-2P 172412-80-5P 172412-81-6P 172412-82-7P 172412-83-8P 172412-84-9P 172412-85-0P 172412-86-1P 172412-87-2P 172412-88-3P 172412-89-4P 172412-90-7P 172412-91-8P 172412-92-9P

172412-93-0P 172412-94-1P 172412-95-2P 172412-96-3P 172412-97-4P
172412-98-5P 172412-99-6P 172413-00-2P 172413-01-3P 172413-02-4P
172413-03-5P 172413-04-6P 172413-05-7P 172413-06-8P 172413-07-9P
172413-08-0P 172413-09-1P 172413-10-4P 172413-11-5P 172413-12-6P
172413-13-7P 172413-14-8P 172413-15-9P 172413-16-0P 172413-17-1P
172413-18-2P 172413-19-3P 172413-20-6P 172413-21-7P 172413-23-9P
172413-24-0P 172413-25-1P 172413-26-2P 172413-27-3P 172413-28-4P
172413-29-5P 172413-30-8P 172413-31-9P 172413-32-0P 172413-33-1P
172413-34-2P 172413-35-3P 172413-36-4P 172413-37-5P 172413-38-6P
172413-39-7P 172413-40-0P 172413-42-2P 172413-43-3P 172413-44-4P
172413-45-5P 172413-46-6P 172413-47-7P 172413-48-8P 172413-49-9P
172413-50-2P 172413-51-3P 172413-52-4P 172413-53-5P 172584-74-6P
172584-75-7P 172584-76-8P 172584-77-9P 172584-78-0P 172647-46-0P
172647-47-1P 172735-62-5P
RL: BAC (Biological activity or effector, except adverse); BSU (Biological
study, unclassified); SPN (Synthetic preparation); THU (Therapeutic use);
BIOL (Biological study); PREP (Preparation); USES (Uses)
(preparation of 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines as
antirheumatics)

IT 96-33-3 105-36-2, Ethyl bromoacetate 107-18-6, 2-Propen-1-ol, reactions 112-67-4, Hexadecanoyl chloride 459-73-4, Glycine ethyl ester 598-32-3, 1-Buten-3-ol 930-22-3 1620-98-0 1663-39-4 2883-45-6, 1,6-Heptadien-4-ol 2999-46-4, Ethyl isocyanoacetate 4755-77-5, Ethyl chloroformylformate 6283-74-5 6737-11-7, 1-Buten-3-yl acetate 13679-64-6, 3-Vinylthiophene 13734-34-4, N-tert-Butoxycarbonylphenylalanine 13838-77-2, 2-Thiazolecarboxaldehyde oxime 19781-76-1, 6-Heptene-2,4-diol 39499-34-8, 5-Methylisoxazole-3-carbonyl chloride 92136-39-5, N-tert-Butoxycarbonylpropargylamine 104835-82-7 172413-61-5
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines as
antirheumatics)

IT 787-13-3P 4185-98-2P 14337-43-0P 19263-36-6P, 2,6-Di-tert-butyl-4-vinylphenol 110106-95-1P, tert-Butyl 4-nitrobutyrate 172413-41-1P 172413-54-6P 172413-55-7P 172413-56-8P 172413-57-9P 172413-58-0P 172413-59-1P 172413-60-4P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of 3-(4-hydroxy-3,5-di-tert-butylphenyl)-2-isoxazolines as
antirheumatics)

L18 ANSWER 10 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1991:52926 CAPLUS
DN 114:52926
OREF 114:8953a,8956a
ED Entered STN: 09 Feb 1991
TI Radiation-sensitive mixture containing spiroindolinobenzopyran dye and copying material therefrom
IN Elsaesser, Andreas; Gaschler, Otfried; Mohr, Dieter
PA Hoechst A.-G., Germany

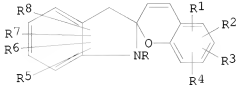
SO Ger. Offen., 9 pp.
CODEN: GWXXBX
DT Patent
LA German
IC ICM G03F007-023
ICA G03F007-16; G03C001-72; G03C001-492; C09B011-00; C09B015-00; C09B017-00; C09B019-00; C09B021-00; C09B023-00; C09B057-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3834300	A1	19900412	DE 1988-3834300	19881008
	CA 2000052	A1	19900408	CA 1989-2000052	19891002
	EP 363776	A3	19910403	EP 1989-118229	19891002
	R: DE, FR, GB, IT, NL				
	BR 8905102	A	19900515	BR 1989-5102	19891006
	JP 02144538	A	19900604	JP 1989-262843	19891007

PRAI DE 1988-3834300 A 19881008
CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 3834300	ICM	G03F007-023
	ICA	G03F007-16; G03C001-72; G03C001-492; C09B011-00; C09B015-00; C09B017-00; C09B019-00; C09B021-00; C09B023-00; C09B057-00
	IPCI	G03F0007-023 [ICM,5]; G03F0007-16 [ICA,5]; G03C0001-72 [ICA,5]; G03C0001-492 [ICA,5]; G03C0001-005 [ICA,5,C*]; C09B0011-00 [ICA,5]; C09B0015-00 [ICA,5]; C09B0017-00 [ICA,5]; C09B0019-00 [ICA,5]; C09B0021-00 [ICA,5]; C09B0023-00 [ICA,5]; C09B0057-00 [ICA,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-09 [I,C*]; G03F0007-105 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]
CA 2000052	IPCI	G03C0001-52 [ICM,5]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-09 [I,C*]; G03F0007-105 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]
EP 363776	IPCI	G03F0007-105 [ICM,5]; G03F0007-09 [ICM,5,C*]
BR 8905102	IPCI	G03C0001-52 [ICM,4]; G03F0007-08 [ICS,4]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-09 [I,C*]; G03F0007-105 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]
JP 02144538	IPCI	G03F0007-022 [ICM,5]; G03F0007-004 [ICS,5]; H01L0021-027 [ICS,5]; H01L0021-02 [ICS,5,C*]
	IPCR	G03F0007-004 [I,C*]; G03F0007-004 [I,A]; G03F0007-022 [I,C*]; G03F0007-022 [I,A]; G03F0007-09 [I,C*]; G03F0007-105 [I,A]; H01L0021-02 [I,C*]; H01L0021-027 [I,A]

OS MARPAT 114:52926
GI



I

AB Radiation-sensitive or photosensitive mixts. and copying materials therefrom are composed of a 1,2-quinonediazide and/or a combination of a compound forming a strong acid under the effects of actinic radiation, a compound containing ≥1 cleavable COC bond, whose solubility in a liquid developer is increased by the effects of an acid; a water-insol., aqueous alkaline solution-soluble polymer binder; and a spiroindolinobenzopyran dye of the structure I (R = H or C1-16 alkyl; R1-R4 = H, halogen, C1-4 alkyl, C1-4 alkoxy, OH, or NO2; R5-R8 = H, halogen, NO2, NH2, C1-5 alkoxy, C1-5 hydroxyalkyl, or C6-10 aryl). Thus, a roughened, anodized, and hydrophilized Al foil was coated with a composition containing a 2,3,4-trihydroxybenzophenone tris(7,2-naphthoquinone-2-diazide-5-sulfonate, a m-cresol-HCHO novolak, 2,6-bis(hydroxymethyl)-4-methylphenol, 2-(4-styrylphenyl)-4,6-bis(trichloromethyl)-s-triazine, and 5'-chloro-1',3',3'-trimethyl-6-nitro-8-methoxyspiro[2H-1-benzopyran-2,2'-indoline], imagewise exposed, and developed to give excellent image contrast and excellent thermal stability.

ST photosensitive compn copying spiroindolinobenzopyran

IT Photoimaging compositions and processes
(containing spiroindolinobenzopyran dye for high image contrast and thermal stability)

IT Printing plates
(photosensitive compns. containing spiroindolinobenzopyran dye for fabrication of, for high image contrast and thermal stability)

IT Phenolic resins, uses and miscellaneous
RL: USES (Uses)
(novolak, photosensitive compns. containing spiroindolinobenzopyran and, for high image contrast and thermal stability)

IT 25086-36-6
RL: USES (Uses)
(novolak, photosensitive compns. containing spiroindolinobenzopyran dye and, for high image contrast and thermal stability)

IT 91-04-3, 2,6-Bis(hydroxymethyl)-4-methylphenol 52125-43-6 69666-56-4 84522-08-7 97802-84-1, 2-(4-Styrylphenyl)-4,6-bis(trichloromethyl)-s-triazine 120504-14-5
RL: USES (Uses)
(photosensitive compns. containing spiroindolinobenzopyran and, for high

image contrast and thermal stability)
IT 24979-71-3 122144-21-2 131272-40-7
RL: USES (Uses)
(photosensitive compns. containing spiroindolinobenzopyran dye and, for
high image contrast and thermal stability)
IT 1498-88-0 1498-89-1 14994-04-8
RL: USES (Uses)
(photosensitive compns. containing, for high image contrast and thermal
stability)

L18 ANSWER 11 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1976:32053 CAPLUS
DN 84:32053
OREF 84:5249a,5252a
ED Entered STN: 12 May 1984
TI Highly heat-stable composition from ring-opening polymerization product
IN Kokuryo, Shiro; Kawahara, Hiroyasu; Akiyama, Hiroshi; Kawasaki, Ueshima; Tsuge, Chutatsu
PA Showa Denko K. K., Japan
SO Ger. Offen., 144 pp.
CODEN: GWXXBX
DT Patent
LA German
IC C08L
CC 36-6 (Plastics Manufacture and Processing)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2518055	A1	19751030	DE 1975-2518055	19750423
	DE 2518055	B2	19810619		
	DE 2518055	C3	19820527		
	JP 50138050	A	19751104	JP 1974-45051	19740423
	JP 51006251	A	19760119	JP 1974-76468	19740705
	JP 51056860	A	19760518	JP 1974-130502	19741114
	JP 51057756	A	19760520	JP 1974-131159	19741115
	JP 51061556	A	19760528	JP 1974-135228	19741126
	JP 51064563	A	19760604	JP 1974-137692	19741203
	US 3991139	A	19761109	US 1975-570425	19750422
	GB 1503703	A	19780315	GB 1975-16587	19750422
	CA 1043494	A1	19781128	CA 1975-225423	19750422
	FR 2366329	A1	19780428	FR 1975-12675	19750423
	FR 2366329	B1	19831007		
	FR 2283175	A1	19760326	FR 1975-36333	19751127
	FR 2283175	B1	19821008		
	FR 2283176	A1	19760326	FR 1975-36334	19751127
	FR 2283176	B1	19821008		
PRAI	JP 1974-45051	A	19740423		
	JP 1974-76468	A	19740705		
	JP 1974-130502	A	19741114		
	JP 1974-131159	A	19741115		
	JP 1974-135228	A	19741126		
	JP 1974-137692	A	19741203		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 2518055	IC	C08L
	IPCI	C08L0045-00
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]
JP 50138050	IPCI	C08L0065-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08L0001-00 [I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0065-00 [I,C*]; C08L0065-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
JP 51006251	IPCI	C08L0065-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08L0065-00 [I,C*]; C08L0065-00 [I,A]; C08K0005-00 [I,C*]; C08K0005-13 [I,A]; C08L0001-00 [I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0077-00 [I,C*]; C08L0077-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
JP 51056860	IPCI	C08L0065-00; C08K0005-36; C08K0005-00 [C*]
	IPCR	C08L0065-00 [I,C*]; C08L0065-00 [I,A]; C08K0005-00 [I,C*]; C08K0005-36 [I,A]; C08L0001-00 [I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0077-00 [I,C*]; C08L0077-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
JP 51057756	IPCI	C08L0065-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-13 [I,A]; C08L0065-00 [I,C*]; C08L0065-00 [I,A]
JP 51061556	IPCI	C08L0065-00; C08K0005-20; C08K0005-00 [C*]
	IPCR	C08L0065-00 [I,C*]; C08L0065-00 [I,A]; C08K0005-00 [I,C*]; C08K0005-20 [I,A]; C08L0001-00 [I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0077-00 [I,C*]; C08L0077-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
JP 51064563	IPCI	C08L0065-00; C08K0005-13; C08K0005-36; C08K0005-37; C08K0005-51; C08K0005-00 [C*]
	IPCR	C08L0065-00 [I,C*]; C08L0065-00 [I,A]; C08K0005-00 [I,C*]; C08K0005-13 [I,A]; C08K0005-36 [I,A]; C08K0005-37 [I,A]; C08K0005-51 [I,A]; C08L0001-00

		[I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0077-00 [I,C*]; C08L0077-00 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
US 3991139	IPCI	C08K0005-53; C08K0005-36; C08K0005-20; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08L0001-00 [I,C*]; C08L0001-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0021-00 [I,C*]; C08L0021-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0027-00 [I,C*]; C08L0027-00 [I,A]; C08L0033-00 [I,C*]; C08L0033-00 [I,A]; C08L0033-02 [I,A]; C08L0051-00 [I,C*]; C08L0051-00 [I,A]; C08L0051-02 [I,A]; C08L0101-00 [I,C*]; C08L0101-00 [I,A]
	NCL	524/151.000; 524/120.000; 524/147.000; 524/153.000; 524/171.000; 524/222.000; 524/289.000; 524/291.000; 524/303.000; 524/304.000; 524/305.000; 524/332.000; 524/343.000; 524/553.000; 526/281.000
GB 1503703	IPCI	C08K0005-36; C08L0045-00; C08K0005-13; C08K0005-06; C08K0005-07; C08K0005-10; C08K0005-20; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]
CA 1043494	IPCI	C08K0005-13; C08K0005-20; C08K0005-36; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]
FR 2366329	IPCI	C08L0045-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]
FR 2283175	IPCI	C08L0045-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]
FR 2283176	IPCI	C08L0045-00; C08K0005-13; C08K0005-00 [C*]
	IPCR	C08K0005-00 [I,C*]; C08K0005-00 [I,A]

AB Phenols, thioethers, and/or phosphites (32) were used as heat stabilizers for polymers (22) prepared by ring-opening polymerization of bicyclo[2.2.1]heptenes
such as 5-cyanobicyclo[2.2.1]hept-2-ene (I). Thus, I polymer [30811-49-5]
containing 3% 2,6-di-tert-butyl-p-cresol [128-37-0] was yellow after 15 min at
220° in air, compared with yellow-brown for unstabilized I polymer.

ST heat stabilizer bicycloheptene polymer; phenol stabilizer bicycloheptene polymer; thioether stabilizer bicycloheptene polymer; phosphite stabilizer
bicycloheptene polymer; norbornene deriv polymer stabilizer

IT Rubber, butadiene-styrene, uses and miscellaneous
(heat stabilizers for bicycloheptene polymers containing)

IT Phenols, uses and miscellaneous
Sulfides, uses and miscellaneous
RL: MOA (Modifier or additive use); USES (Uses)
(heat stabilizers, for bicycloheptene polymers)

IT Heat stabilizers
(phenols and phosphites and thioethers, for bicycloheptene polymers)

IT 9002-86-2 25053-09-2
RL: USES (Uses)
(blends with bicycloheptene polymers, heat stabilizers for)
IT 26935-85-3 26936-09-4 27176-60-9 30421-40-0 30811-49-5
31513-41-4 51243-63-1 51252-30-3 51252-33-6 55636-70-9
55738-35-7 55738-39-1 56663-05-9 57863-31-7 57863-32-8
57863-33-9 57863-34-0 57863-35-1 57863-37-3 57863-38-4
57863-39-5 57863-41-9
RL: USES (Uses)
(heat stabilizers for)
IT 85-60-9 90-66-4 96-69-5 99-24-1 119-47-1 121-00-6 123-28-4
128-37-0 144-35-4 1421-63-2 3164-55-4 3806-34-6 6683-19-8
10361-12-3 10446-37-4 13560-55-9 13560-56-0 13579-30-1
16545-54-3 16857-10-6 26523-78-4 27325-60-6 29492-50-0
31151-27-6 57863-94-2 57863-95-3 57863-96-4 57863-97-5
57863-98-6 57863-99-7
RL: MOA (Modifier or additive use); USES (Uses)
(heat stabilizers, for bicycloheptene polymers)
IT 9003-55-8
(rubber, butadiene-styrene; heat stabilizers for bicycloheptene polymers containing)

L18 ANSWER 12 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1970:456976 CAPLUS
DN 73:56976
OREF 73:9355a,9358a
ED Entered STN: 12 May 1984
TI Modified rubber
IN Hiroshima, Junichi; Makino, Kenjiro
PA Asahi Organic Chemicals Industry Co., Ltd.
SO Jpn. Tokkyo Koho, 3 pp.
CODEN: JAXXAD
DT Patent
LA Japanese
INCL 26D21
CC 38 (Elastomers, Including Natural Rubber)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 45008426	B4	19700326	JP	19660526

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 45008426	INCL	26D21

AB (Acrylamidomethyl)phenol (I) is grafted onto isoprene or natural rubber (II) with a radical initiator. Thus, a mixture of II 1500, I 643, Bz2O2 21.4, and azobisisobutyronitrile 21.4 g was milled at 15-50°, and heated at 80-90° for 10 hr to give the rubber.
ST acrylamidomethylphenol graft rubber; graft rubber acrylamidomethylphenol; isoprene acrylamidomethylphenol graft
IT Rubber, preparation
((acrylamidomethyl)phenol-grafted)
IT Polymerization
(graft, of (acrylamidomethyl)phenol on rubber)
IT 23281-77-8

RL: USES (Uses)
(polymers with rubber, graft)

L18 ANSWER 13 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1969:67894 CAPLUS
DN 70:67894
OREF 70:12669a,12672a
ED Entered STN: 12 May 1984
TI Preparation of phenols having unsaturated residue
IN Hiroshima, Junichi; Makino, Kenjiro; Takagi, Mikio
PA Asahi Yukizai Kogyo Co., Ltd.
SO Jpn. Tokkyo Koho, 2 pp.
CODEN: JAXXAD
DT Patent
LA Japanese
INCL 16C412
CC 25 (Noncondensed Aromatic Compounds)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 43019535	B4	19680823	JP	19650911

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 43019535	INCL	16C412

AB The title compds. such as acrylamidomethyl-phenol or methacrylamidomethylphenol, are prepared by condensation of N-methylolacrylamide or N-methylolmethacrylamide with phenols. Thus, a mixture of 575.5 g. phenol, 765.5 g. N-methylolacrylamide, and 13.4 g. p-toluenesulfonic acid was heated 3 hrs. at 90-100°, washed 4 times with 1 l H2O, boiled with 10 l. H2O to remove phenol, and dried in vacuo to give 88% 1:1 o- and p-substituted phenols, accompanied by a trace of o,o- or o,p-disubstituted phenol.
ST phenols acrylamidomethyl
IT 23281-76-7P 23281-77-8P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)

L18 ANSWER 14 OF 14 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1966:491493 CAPLUS
DN 65:91493
OREF 65:17151e-h
ED Entered STN: 22 Apr 2001
TI Phenolic stabilizers for polymers
PA Farbenfabriken Bayer A.-G.
SO 9 pp.
DT Patent
LA Unavailable
IC C07C
CC 48 (Plastics Technology)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI NL 6515965		19660609	NL 1965-15965	19651208
PRAI DE		19641208		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
NL 6515965	IC	C07C
	IPCI	C07C
	IPCR	C08K0005-00 [I,C*]; C08K0005-20 [I,A]

GI For diagram(s), see printed CA Issue.

AB Substituted phenols of the general formula I, where R is H or Me and R' is Et, iso-Pr, or tert-Bu, were prepared for use as stabilizers for polymers. 2,6-tert-Bu2C6H3OH 206, CH2:CMeCONHCH2OMe (II) 129, p-MeC6H4SO3H (III) 1, and phenothiazine (IV) 0.1 g. heated under CO2 at 150-70° with the overhead removal of 32 g. MeOH yielded 225 g. I (R = Me, R' = tert-Bu) (V), m. 113° (petroleum ether). Latex (28.7%) (4880 g.) of a graft copolymer of 36 parts styrene and 14 parts CH2:CHCN (VI) on 50 parts polybutadiene mixed with 6000 g. 43.4% latex of a copolymer of 70 parts styrene and 30 parts VI (K value 60.3, intrinsic viscosity 0.71-0.80) treated with stirring with 100 g. emulsion of V containing 20% H2O (5% of total polymer), coagulated with 2% AcOH, washed, and dried at 70-80°, a 100-g. portion of the stabilized polymer mixture mixed at 160° with 2 weight-% com. lubricant, granulated, and formed by injection-molding into plates at 200° gave materials of very good heat stability. 2,5-Et2C6H3OH (VII) (150.0 g.), 129.0 g. II, 1.0 g. III, and 0.1 g. IV gave similarly, with the elimination of 21 g. MeOH, 220 g. I (R = Me, R' = Et), m. 118° (EtOAc). VII (150.0 g.), 115.0 g. CH2:CHCONHCH2OMe, 1.0 g. III, and 0.1 g. IV heated at 105-70° with removal of 28 g. MeOH yielded 130 g. I (R = H, R' = Et), m. 137° (EtOAc). 2,6-iso-Pr2C6H3OH (178.0 g.), 129.0 g. II, 1.0 g. III, and 0.1 g. IV gave similarly at 100-30° (28 g. MeOH eliminated) 250 g. yellow, viscous I (R = Me, R' = iso-Pr). 2,6-tert-Bu2C6H3OH (206 g.) in 200 cc. o-C6H4Cl2, 129 g. II, and 1 g. III heated at 100-10° with removal of MeOH gave 220 g. V, m. 113°. Latex of graft-polymer and copolymer mixts. stabilized with I yielded, upon injection molding, products with very good heat stability.

IT Polyoxymethylenes
(stabilization of, by esterification of terminal OH groups with α-substituted vinyl esters)

IT 2206-94-2
(Derived from data in the 7th Collective Formula Index (1962-1966))

IT 9003-17-2, 1,3-Butadiene, homopolymer
(acrylonitrile-styrene graft polymers on, stabilizers for, N-(3,5-diethyl-4-hydroxybenzyl)acrylamide and related compds. as)

IT 13560-54-8, Acrylamide, N-(3,5-di-tert-butyl-4-hydroxybenzyl)-2-methyl-
13560-55-9, Acrylamide, N-(3,5-diethyl-4-hydroxybenzyl)-
13560-56-0, Acrylamide, N-(3,5-diethyl-4-hydroxybenzyl)-2-methyl-
(as stabilizer for acrylonitrile-styrene graft polymers on 1,3-butadiene polymers)

IT 9003-54-7, Styrene, polymer with acrylonitrile
(grafted on 1,3-butadiene polymers, stabilizers for, N-(3,5-diethyl-4-hydroxybenzyl)acrylamide and related compds. as)

IT 106677-58-1, Acrylonitrile, polymer with butadiene and styrene, graft
(stabilizers for, N-(3,5-diethyl-4-hydroxybenzyl)acrylamide and related

compds. as)

```
=> d his

     (FILE 'HOME' ENTERED AT 17:01:43 ON 09 SEP 2008)

     FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1          4064 S C11H13NO2/MF
L2             5 S L1 AND ACRYLAMIDE
L3             0 S HYDROXYBENZYLACRYLAMIDE
L4            26 S HYDROXYBENZYL AND ACRYLAMIDE
L5            24 S L4 NOT CHLORO
L6            15 S L5 NOT TERT
L7             0 S 13560-55-9/CRN

     FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8            13 S L6
L9             4 S L8 AND PHOTO?

     FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008
L10            1 S 13560-56-0
L11            1 S  23281-77-8
L12            1 S   849686-90-4
L13            1 S 104835-82-7
L14           16 S 104835-82-7/CRN
L15            0 S   849686-90-4/CRN
L16            2 S  23281-77-8/CRN

     FILE 'CAPLUS' ENTERED AT 17:09:35 ON 09 SEP 2008
L17           16 S L10 OR L11 OR L12 OR L13 OR L14 OR L16
L18           14 S L17 NOT L9

=> file reg
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                       ENTRY    SESSION
FULL ESTIMATED COST                                    47.22     160.70

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                       ENTRY    SESSION
CA SUBSCRIBER PRICE                                   -11.20     -14.40

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DICTIONARY FILE UPDATES:   8 SEP 2008  HIGHEST RN 1047724-15-1

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http://www.cas.org/support/stngen/stndoc/properties.html

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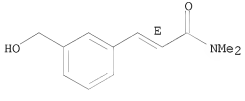
=> s c12h15no2/mf
L19        4952 C12H15NO2/MF

=> s l19 and acrylamide
          18439 ACRYLAMIDE
L20           5 L19 AND ACRYLAMIDE

=> d 1-5

L20  ANSWER 1 OF 5  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   208943-39-9  REGISTRY
ED   Entered STN:  23 Jul 1998
CN   2-Propenamide, 3-[3-(hydroxymethyl)phenyl]-N,N-dimethyl-, (2E)-  (CA
INDEX
     NAME)
OTHER NAMES:
CN   (E)-3-(3-Hydroxymethylphenyl)-N,N-dimethylacrylamide
FS   STEREOSEARCH
MF   C12 H15 N O2
SR   CA
LC   STN Files:   CA, CAPLUS, CASREACT

Double bond geometry as shown.
```

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**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**

               2 REFERENCES IN FILE CA (1907 TO DATE)
               2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L20  ANSWER 2 OF 5  REGISTRY  COPYRIGHT 2008 ACS on STN
RN   91640-39-0  REGISTRY
ED   Entered STN:  16 Nov 1984
CN   2-Propenamide, 2-methyl-N-[(phenylmethoxy)methyl]-  (CA INDEX NAME)
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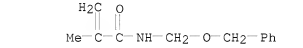
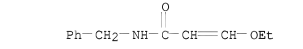
OTHER CA INDEX NAMES:
CN Acrylamide, N-[(benzyloxy)methyl]-2-methyl- (7CI)
MF C12 H15 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAOLD, CAPLUS
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

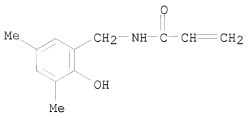
L20 ANSWER 3 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 23980-89-4 REGISTRY
ED Entered STN: 16 Nov 1984
CN Acrylamide, N-benzyl-3-ethoxy- (8CI) (CA INDEX NAME)
MF C12 H15 N O2
LC STN Files: BEILSTEIN*, CA, CAPLUS
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

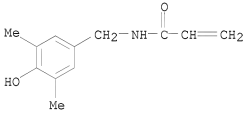
L20 ANSWER 4 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 14800-18-1 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(2-hydroxy-3,5-dimethylphenyl)methyl]- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-dimethylsalicyl)- (8CI)
MF C12 H15 N O2
LC STN Files: BEILSTEIN*, CA, CAPLUS, CASREACT, IFICDB, IFIPAT, IFIUDB, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L20 ANSWER 5 OF 5 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13579-23-2 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(4-hydroxy-3,5-dimethylphenyl)methyl]- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(4-hydroxy-3,5-dimethylbenzyl)- (8CI)
OTHER NAMES:
CN 4-Acrylamidomethyl-2,6-dimethylphenol
DR 845725-91-9
MF C12 H15 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAPLUS, CASREACT, IFICDB, IFIPAT, IFIUDB, USPATFULL, USPATOLD
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

28 REFERENCES IN FILE CA (1907 TO DATE)
28 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> s 13579-23-2 or 14800-18-1
1 13579-23-2
(13579-23-2/RN)
1 14800-18-1
(14800-18-1/RN)

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L21          2 13579-23-2 OR 14800-18-1

=> s  13579-23-2/crn or 14800-18-1/crn
            16 13579-23-2/CRN
             0 14800-18-1/CRN
L22         16 13579-23-2/CRN OR 14800-18-1/CRN

=> file caplus]
'CAPLUS!' IS NOT A VALID FILE NAME
SESSION CONTINUES IN FILE 'REGISTRY'
Enter "HELP FILE NAMES" at an arrow prompt (=>) for a list of files
that are available.  If you have requested multiple files, you can
specify a corrected file name or you can enter "IGNORE" to continue
accessing the remaining file names entered.

=> file caplus
COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                         ENTRY    SESSION
FULL ESTIMATED COST                                      21.68     182.38

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                         ENTRY    SESSION
CA SUBSCRIBER PRICE                                       0.00     -14.40

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FILE LAST UPDATED: 8 Sep 2008  (20080908/ED)

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reclassification data for the second quarter of 2008.

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=> s l21 or l22
            28 L21
             7 L22
L23         34 L21 OR L22
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=> d his

     (FILE 'HOME' ENTERED AT 17:01:43 ON 09 SEP 2008)

     FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1          4064 S C11H13NO2/MF
L2             5 S L1 AND ACRYLAMIDE
L3             0 S HYDROXYBENZYLACRYLAMIDE
L4            26 S HYDROXYBENZYL AND ACRYLAMIDE
L5            24 S L4 NOT CHLORO
L6            15 S L5 NOT TERT
L7             0 S 13560-55-9/CRN

     FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8            13 S L6
L9             4 S L8 AND PHOTO?

     FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008
L10            1 S 13560-56-0
L11            1 S  23281-77-8
L12            1 S   849686-90-4
L13            1 S 104835-82-7
L14           16 S 104835-82-7/CRN
L15            0 S   849686-90-4/CRN
L16            2 S  23281-77-8/CRN

     FILE 'CAPLUS' ENTERED AT 17:09:35 ON 09 SEP 2008
L17           16 S L10 OR L11 OR L12 OR L13 OR L14 OR L16
L18           14 S L17 NOT L9

     FILE 'REGISTRY' ENTERED AT 17:11:07 ON 09 SEP 2008
L19         4952 S C12H15NO2/MF
L20            5 S L19 AND ACRYLAMIDE
L21            2 S  13579-23-2 OR 14800-18-1
L22           16 S  13579-23-2/CRN OR 14800-18-1/CRN

     FILE 'CAPLUS' ENTERED AT 17:13:10 ON 09 SEP 2008
L23           34 S L21 OR L22

=> s l23 not l9 not l22
              7 L22
L24          26 L23 NOT L9 NOT L22

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L26 NOT FOUND
The L-number entered could not be found.  To see the definition
of L-numbers, enter DISPLAY HISTORY at an arrow prompt (=>).

=> s l24 and photo?
      1604210 PHOTO?
L25           0 L24 AND PHOTO?

=> s l26 and negativ?
L26 NOT FOUND
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of L-numbers, enter DISPLAY HISTORY at an arrow prompt (=>).

=> s l24 and negativ?
        101462 NEGATIV?
L26           0 L24 AND NEGATIV?

=> s l24 and polymeriz?
        410008 POLYMERIZ?
L27           9 L24 AND POLYMERIZ?

=> d all 1-9

L27  ANSWER 1 OF 9  CAPLUS  COPYRIGHT 2008 ACS on STN
AN   1998:186505  CAPLUS
DN   128:205506
OREF 128:40649a,40652a
ED   Entered STN:  30 Mar 1998
TI   Polyvinyl graft polymers and manufacturing method thereof
IN   Tamai, Kazuhiko; Yonezawa, Kazuya
PA   Kanegafuchi Kagaku Kogyo K. K., Japan
SO   U.S., 4 pp., Cont.-in-part of U.S. Ser. No. 227,096, abandoned.
     CODEN: USXXAM
DT   Patent
LA   English
IC   ICM  C08F024-00
     ICS  C08F269-00; C08F020-18; C08F020-42; C08F012-08; C08F016-14
INCL 526273000
CC   37-6 (Plastics Manufacture and Processing)
     Section cross-reference(s): 35
FAN.CNT 2
     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
     ---------------     ----   --------    -------------------    --------
PI   US 5728791           A     19980317    US 1995-557329         19951114
     JP 04202513          A     19920723    JP 1990-339940         19901130
PRAI JP 1990-339940       A     19901130
     US 1992-915823       B1    19920728
     US 1994-227096       B2    19940413
CLASS
 PATENT NO.      CLASS  PATENT FAMILY CLASSIFICATION CODES
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 US 5728791      ICM    C08F024-00
                 ICS    C08F269-00; C08F020-18; C08F020-42; C08F012-08;
                        C08F016-14
                 INCL   526273000
                 IPCI   C08F0024-00 [ICM,6]; C08F0269-00 [ICS,6]; C08F0020-18
                        [ICS,6]; C08F0020-42 [ICS,6]; C08F0020-00 [ICS,6,C*];
                        C08F0012-08 [ICS,6]; C08F0012-00 [ICS,6,C*];
                        C08F0016-14 [ICS,6]; C08F0016-00 [ICS,6,C*]
                 IPCR   C08F0291-00 [I,C*]; C08F0291-00 [I,A]
                 NCL    526/273.000; 525/286.000; 526/320.000; 526/328.000;
                        526/332.000; 526/341.000; 526/346.000
                 ECLA   C08F291/00+220/58
 JP 04202513     IPCI   C08F0212-08 [ICM,5]; C08F0212-00 [ICM,5,C*];
                        C08F0220-12 [ICS,5]; C08F0220-58 [ICS,5]; C08F0220-00
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[ICS,5,C*]
IPCR C08F0212-08 [I,A]; C08F0020-00 [I,C*]; C08F0020-52 [I,A]; C08F0020-58 [I,A]; C08F0212-00 [I,C*]; C08F0212-00 [I,A]; C08F0220-00 [I,C*]; C08F0220-10 [I,A]; C08F0220-12 [I,A]; C08F0220-58 [I,A]

AB The graft polymer bearing the group of CH2CR(CONHCH2Z) (R = H, Me; Z = C6-23 aromatic hydrocarbyl containing ≥1 glycidyloxy group) is prepared The graft polymer is excellent not only in mech. properties and heat resistance, but also in adhesiveness, paintability, dyeability and antistatic property. Thus, extruding a mixture of polystyrene 100, N-[4-(2,3-epoxypropoxy)-3,5-dimethylphenyl]acrylamide 10, and α,α'-bis(tert-butylperoxy-m-isopropyl)benzene 0.1 part gave a graft polymer.

ST polystyrene glycidyloxyphenyl acrylamide graft polymer; epoxy contg polymethyl methacrylate graft polymer

IT Polymers, preparation
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); PREP (Preparation); USES (Uses)
(graft, epoxy group-containing; manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT Polymerization
(graft; manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT Polymer blend compatibilizers
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT Polyesters, properties
RL: POF (Polymer in formulation); PRP (Properties); USES (Uses)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT Polymer blends
RL: PRP (Properties)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT 203937-56-8P 203937-57-9P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); PREP (Preparation); USES (Uses)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT 105597-20-4P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT
(Reactant or reagent)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT 25038-59-9, PET polyester, properties
RL: POF (Polymer in formulation); PRP (Properties); USES (Uses)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

IT 106-89-8, Epichlorohydrin, reactions 13579-23-2, 4-Acrylamidomethyl-2,6-dimethyl phenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(manufacture of epoxy-containing polyvinyl graft polymers and blends)

RE.CNT 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Anon; JP 61-148215 1986 CAPLUS
(2) Anon; JP 61-227 1986 CAPLUS
(3) Anon; JP 63-037109 1988
(4) Anon; JP 63-37109 1988

(5) Deguchi; US 5294673 1994 CAPLUS
(6) Kobayashi; US 5166273 1992 CAPLUS
(7) Ueki; US 5349027 1994 CAPLUS

L27 ANSWER 2 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1997:618917 CAPLUS
DN 127:279066
OREF 127:54503a,54506a
ED Entered STN: 27 Sep 1997
TI Poly(ethylene terephthalate)-based polyester compositions with improved mechanical strength and moisture-heat resistance
IN Matsumoto, Kazuaki
PA Kanegafuchi Chemical Industry Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C08L067-02
ICS C08K003-00; C08K005-00; C08G063-85; C08L067-02; C08L051-06
CC 37-6 (Plastics Manufacture and Processing)
Section cross-reference(s): 35, 38
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09241490	A	19970916	JP 1996-85813	19960313
PRAI	JP 1996-85813		19960313		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 09241490	ICM	C08L067-02
	ICS	C08K003-00; C08K005-00; C08G063-85; C08L067-02; C08L051-06
	IPCI	C08L0067-02 [ICM,6]; C08K0003-00 [ICS,6]; C08K0005-00 [ICS,6]; C08G0063-85 [ICS,6]; C08L0067-02 [ICS,6]; C08L0051-06 [ICS,6]
	IPCR	C08K0003-00 [I,C*]; C08K0003-00 [I,A]; C08G0063-00 [I,C*]; C08G0063-82 [I,A]; C08G0063-85 [I,A]; C08K0005-00 [I,C*]; C08K0005-00 [I,A]; C08L0067-00 [I,C*]; C08L0067-00 [I,A]; C08L0067-02 [I,A]

AB Title compns. contain (A) 100 parts poly(ethylene terephthalate)-based polyesters prepared by polymerization using Ge compound catalysts, (B) 0.2-50 parts graft copolymers obtained by contacting (a) 100 parts polyolefins with aqueous suspensions containing (b) 0.1-500 parts vinyl monomers, (c) 0.1-30 parts CH2:CRC(:O)NHCH2Ar (Ar = ≥1 glycidyloxy-containing C6-23 aromatic hydrocarbyl; R = H, Me), and (d) 0.01-10 parts [for 100 parts of (a + b)] radically polymerization initiators, and (C) 5-200 parts reinforcement fillers. Thus, poly(ethylene terephthalate) prepared using GeO2 100, N-[(2,3-epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide-ethylene-propylene-styrene graft copolymer 10, T 195H/P (glass fiber) 50, ADK Stab AO 60 0.35, and ADK Stab AO 412S 0.15 part were dry blended, melt kneaded, pelletized, and injection molded to give a test piece showing tensile

strength 150 MPa and good moisture-heat resistance.
ST polyester grafted polyolefin blend mech strength; polyethylene terephthalate polyolefin blend mech strength; glycidyl polyolefin grafted blend polyester; moisture resistance polyester grafted polyolefin; heat resistance polyester grafted polyolefin; germanium polymn catalyst polyethylene terephthalate
IT Phenoxy resins
RL: MOA (Modifier or additive use); USES (Uses)
(brominated, fireproofing agents; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Mica-group minerals, uses
RL: MOA (Modifier or additive use); USES (Uses)
(crystal nucleating agents, A 21S; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Reinforced plastics
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(fiber-reinforced; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Polymerization catalysts
(germanium compds.; poly(ethylene terephthalate)-based polyester blends
with improved mech. strength and moisture-heat resistance)
IT Polyolefins
Polyolefins
RL: MOA (Modifier or additive use); USES (Uses)
(graft; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Heat-resistant materials
Water-resistant materials
(poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Polyesters, uses
Polyesters, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Polymer blends
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT Polyethers, uses
Polyethers, uses
RL: MOA (Modifier or additive use); USES (Uses)
(polyester-, block; poly(ethylene terephthalate)-based polyester blends
with improved mech. strength and moisture-heat resistance)
IT Polyesters, uses
Polyesters, uses
RL: MOA (Modifier or additive use); USES (Uses)
(polyether-, block; poly(ethylene terephthalate)-based polyester blends

with improved mech. strength and moisture-heat resistance)
IT Glass fibers, uses
RL: MOA (Modifier or additive use); USES (Uses)
(reinforcements, T 195H/P; poly(ethylene terephthalate)-based polyester
blends with improved mech. strength and moisture-heat resistance)
IT 14807-96-6, Micro Ace K 1, uses
RL: MOA (Modifier or additive use); USES (Uses)
(crystal nucleating agents; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT 9003-53-6D, Polystyrene, brominated 152787-57-0, YPB 43M
RL: MOA (Modifier or additive use); USES (Uses)
(fireproofing agents; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT 1309-64-4, Antimony trioxide, uses
RL: MOA (Modifier or additive use); USES (Uses)
(fireproofing aids; poly(ethylene terephthalate)-based polyester blends
with improved mech. strength and moisture-heat resistance)
IT 196618-62-9P
RL: PNU (Preparation, unclassified); PREP (Preparation)
(modifiers; poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT 108854-80-4P, Bisphenol A-ethylene oxide adduct-ethylene glycol-terephthalic acid block copolymer 166399-68-4P 168967-98-4P 180720-10-9P
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT 25038-59-9, Poly(ethylene terephthalate), uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(poly(ethylene terephthalate)-based polyester blends with improved mech. strength and moisture-heat resistance)
IT 1310-53-8, Germanium oxide, uses
RL: CAT (Catalyst use); USES (Uses)
(polymerization catalysts; poly(ethylene terephthalate)-based polyester blends
with improved mech. strength and moisture-heat resistance)
IT 106-89-8, Epichlorohydrin, reactions 13579-23-2, 4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of modifiers for grafted polyolefins)

L27 ANSWER 3 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:693575 CAPLUS
DN 123:288321
OREF 123:51641a,51644a
ED Entered STN: 22 Jul 1995
TI Polyolefin compositions and their manufacture
IN Tamai, Kazuhiko; Kurimoto, Kenji; Tomita, Haruo
PA Kanegafuchi Chemical Ind, Japan
SO Jpn. Kokai Tokkyo Koho, 8 pp.

CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C08F255-00
ICS C08F263-04; C08L023-26; C08L031-04
CC 37-6 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07109319	A	19950425	JP 1993-277544	19931008
PRAI JP 1993-277544		19931008		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07109319	ICM	C08F255-00
	ICS	C08F263-04; C08L023-26; C08L031-04
	IPCI	C08F0255-00 [ICM,6]; C08F0263-04 [ICS,6]; C08F0263-00 [ICS,6,C*]; C08L0023-26 [ICS,6]; C08L0023-00 [ICS,6,C*]; C08L0031-04 [ICS,6]; C08L0031-00 [ICS,6,C*]
	IPCR	C08L0023-00 [I,C*]; C08L0023-26 [I,A]; C08F0255-00 [I,C*]; C08F0255-00 [I,A]; C08F0263-00 [I,C*]; C08F0263-00 [I,A]; C08F0263-04 [I,A]; C08L0031-00 [I,C*]; C08L0031-04 [I,A]

OS MARPAT 123:288321
AB Title polymers with improved mech. and adhesive properties are manufactured by melt-kneading 100 parts mixture of 5-95% polyolefins selected from polypropylene, polyethylene, ethylene-propene rubbers, and diene copolymers, and 5-95% EVA, 0.1-30 parts H2C:CRCONHCH2Ar (Ar = C6-23 aromatic hydrocarbyl containing ≥1 glycidyloxy group; R = H, Me), [e.g., N-(3,5-dimethyl-4-glycidyloxyphenylmethyl)acrylamide (I)], and 0.01-5 parts radical initiators. Thus, a mixture of Noblen D 501 50, Evaflex 260 40, I 10, and α,α'-bis(tert-butylperoxy-m-isopropyl)benzene 0.05 part was extruded at 200° with graft efficiency 87%. A specimen injection-molded from the graft polymer showed elongation >200% and no breakage in the impact test (ASTM D 256) and two Al sheets bonded with the graft polymer showed T-peel strength 18 kg/25 mm.
ST polyolefin EVA grafting glycidyloxydimethylphenylmethylacrylamide; impact resistance modified polyolefin EVA; adhesiveness modified polyolefin EVA metal; radical initiator grafting polyolefin glycidyloxydimethylphenylmethylacrylamide
IT Adhesives
Impact-resistant materials
(polyolefin compns. and their manufacture)
IT Polymerization
(graft, polyolefin compns. and their manufacture)
IT Polymerization catalysts
(radical, polyolefin compns. and their manufacture)
IT 1068-27-5 2094-98-6, 1,1'-Azobis(cyclohexane-1-carbonitrile) 2212-81-9
RL: CAT (Catalyst use); USES (Uses)

(initiators; polyolefin compns. and their manufacture)
IT 99431-43-3, N-[4-(2,3-Epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide
166399-74-2 169549-21-7
RL: MOA (Modifier or additive use); USES (Uses)
(polyolefin compns. and their manufacture)
IT 106-89-8, Epichlorohydrin, reactions 13579-23-2,
4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(polyolefin compns. and their manufacture)
IT 7429-90-5, Aluminum, miscellaneous
RL: MSC (Miscellaneous)
(sheets; polyolefin compns. and their manufacture)

L27 ANSWER 4 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1995:613049 CAPLUS
DN 123:230192
OREF 123:41113a,41116a
ED Entered STN: 15 Jun 1995
TI Modified polyolefin-based polymer compositions with good discoloration prevention
IN Munakata, Yasumitsu; Kurimoto, Kenji; Tomita, Haruo
PA Kanegafuchi Chemical Ind, Japan
SO Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C08L023-02
ICS C08F255-00; C08K005-15
CC 37-6 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 07082425	A	19950328	JP 1993-255000	19930917
PRAI JP 1993-255000		19930917		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 07082425	ICM	C08L023-02
	ICS	C08F255-00; C08K005-15
	IPCI	C08L0023-02 [ICM,6]; C08L0023-00 [ICM,6,C*]; C08F0255-00 [ICS,6]; C08K0005-00 [ICS,6,C*]
	IPCR	C08F0255-00 [I,C*]; C08F0255-00 [I,A]; C08K0005-00 [I,C*]; C08K0005-15 [I,A]; C08K0005-1515 [I,A]; C08L0023-00 [I,C*]; C08L0023-02 [I,A]

AB Title compns. useful for fibers, films, and moldings, contain (A) 100 parts polyolefin-based polymers, (B) 0.01-30 parts glycidyl group-containing
modifying agents of RC(:CH2)C(O)NHCH2Ar (R = H, Me; Ar = ≥1 glycidyl group-containing C6-23 aromatic hydrocarbyl), (C) 0.01-2 parts radical
initiators, and (D) 0.1-10 parts ≥1 stabilizer chosen from antioxidants and light stabilizers. Thus, EP 02P (ethylene-propylene copolymer) 100, N-[(2,3-epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide 7, Perhexa V 40 0.23, and Irganox 1010 0.5 part were mixed, kneaded at

220°, and extruded to give pellets, which was dried, dissolved in xylene at 100°, and dropped into acetone to give a modified polyolefin having epoxy equiv 4220 g/equiv, graft efficiency 98%, and good discoloration resistance.

ST discoloration prevention modified polyolefin; modifying agent polyolefin blend; radical initiator polyolefin blend; stabilizer polyolefin blend

IT Rubber, ethylene-propene
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(EP 02P; modified polyolefin-based polymer blends with good discoloration prevention)

IT Antioxidants
Light stabilizers
(modified polyolefin-based polymer blends with good discoloration prevention)

IT Discoloration prevention
(agents, modified polyolefin-based polymer blends with good discoloration prevention)

IT Alkenes, properties
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(polymers, modified polyolefin-based polymer blends with good discoloration prevention)

IT Polymerization catalysts
(radical, modified polyolefin-based polymer blends with good discoloration prevention)

IT 138049-74-8P 138230-47-4P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(modified polyolefin-based polymer blends with good discoloration prevention)

IT 106565-43-9, Noblen AH 561
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(modified polyolefin-based polymer blends with good discoloration prevention)

IT 99431-43-3P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(modifying agent; modified polyolefin-based polymer blends with good discoloration prevention)

IT 995-33-5, Perhexa V 40 6731-36-8, Perhexa 3M
RL: CAT (Catalyst use); USES (Uses)
(radical polymerization initiator; modified polyolefin-based polymer blends with good discoloration prevention)

IT 106-89-8, Epichlorohydrin, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction with acrylamidomethydimethylphenol)

IT 13579-23-2, 4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction with epichlorohydrin)

IT 9010-79-1
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(rubber, EP 02P; modified polyolefin-based polymer blends with good discoloration prevention)
IT 6683-19-8, Irganox 1010 94765-76-1, Irganox B 900
RL: MOA (Modifier or additive use); USES (Uses)
(stabilizer; modified polyolefin-based polymer blends with good discoloration prevention)

L27 ANSWER 5 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1994:681864 CAPLUS
DN 121:281864
OREF 121:51461a,51464a
ED Entered STN: 10 Dec 1994
TI Modified polyolefins and manufacture thereof
IN Tamai, Kazuhiko; Matsumura, Takahisa; Tomita, Haruo
PA Kanegafuchi Chemical Ind, Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C08F255-00
CC 37-3 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 06116343	A	19940426	JP 1992-289436	19921002
PRAI JP 1992-289436		19921002		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 06116343	ICM	C08F255-00
	IPCI	C08F0255-00 [ICM,5]
	IPCR	C08F0255-00 [I,C*]; C08F0255-00 [I,A]

OS MARPAT 121:281864
AB The title polymers with improved mech. properties, heat resistance, dyeability, coatability, etc. are formed without significant viscosity change or odor by reacting polyolefins with glycidyl compds. CH2:CRCONHCH2Ar (Ar = C6-23 aromatic hydrocarbyl having ≥1 glycidoxy group; R = H, Me) in the presence of ≥1 of 1,1'-azobis(cyclohexane-1-carbonitrile) (I), 1-[(1-cyano-1-methylethyl)azo]formamide, 2-phenylazo-4-methoxy-2,4-dimethylvaleronitrile, 2,2'-azobis(2-methylbutyronitrile), 2,2'-azobis(2,4,4-trimethylpentane), 2,2'-azobis(2-acetoxypropane), and 2,2'-azobis(2-acetoxybutane). EP-02P was grafted with 7 phr N-(4-glycidoxy-3,5-dimethylbenzyl)acrylamide in the presence of 0.1 phr I by extruding at 180° at a rate of 10 kg/h.
ST epoxy modified polyolefin; ethylene propene rubber epoxy grafted
IT Azo compounds
RL: USES (Uses)
(graft polymerization catalysts, for ethylene-propene rubber with glycidoxy group-containing acrylamides)
IT Polymerization catalysts

(graft, azo compds., for ethylene-propene rubber with glycidoxy group-containing acrylamides)
IT 2094-98-6, 1,1'-Azobis(cyclohexane-1-carbonitrile) 10288-28-5 13472-08-7, 2,2'-Azobis(2-methylbutyronitrile) 35634-74-3 39198-34-0, 2,2'-Azobis(2,4,4-trimethylpentane) 40888-97-9, 2,2'-Azobis(2-acetoxypropane) 57908-48-2, 2,2'-Azobis(2-acetoxybutane)
RL: USES (Uses)
(graft polymerization catalysts, for ethylene-propene rubber with glycidoxy group-containing acrylamides)
IT 99431-43-3P
RL: PREP (Preparation)
(manufacture and grafting with ethylene-propene rubber)
IT 138049-71-5P 138230-47-4P
RL: PREP (Preparation)
(manufacture of, with good adhesive properties, catalysts for)
IT 106-89-8, Epichlorohydrin, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with acrylamidomethyldimethylphenol)
IT 13579-23-2, 4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with epichlorohydrin)

L27 ANSWER 6 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:651367 CAPLUS
DN 119:251367
OREF 119:44855a,44858a
ED Entered STN: 11 Dec 1993
TI Blended polyester molding compositions having good compatibility and high strength
IN Deguchi, Yoshikuni; Yonezawa, Kazuya; Hamaguchi, Shigeki; Tamai, Kazuhiko
PA Kanegafuchi Kagaku Kogyo K. K., Japan
SO PCT Int. Appl., 29 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
IC ICM C08L067-02
ICS C08L067-04
CC 37-6 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 9307215	A1	19930415	WO 1991-JP1320	19911001
W: CA, JP, US				
RW: BE, DE, FR, GB, IT				
EP 559890	A1	19930915	EP 1991-916746	19911001
R: BE, DE, FR, GB, IT				
PRAI WO 1991-JP1320	W	19911001		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 9307215	ICM	C08L067-02
	ICS	C08L067-04
	IPCI	C08L0067-02 [ICM,5]; C08L0067-04 [ICS,5]; C08L0067-00 [ICS,5,C*]

IPCR C08L0023-00 [I,C*]; C08L0023-26 [I,A]; C08L0067-00 [I,C*]; C08L0067-02 [I,A]; C08L0067-04 [I,A]
ECLA C08L023/26+B4K; C08L067/02+B2A1; C08L067/02+B2Z; C08L067/04+B2A1
EP 559890 IPCI C08L0067-02 [ICM,5]; C08L0067-04 [ICS,5]; C08L0067-00 [ICS,5,C*]
IPCR C08L0023-00 [I,C*]; C08L0023-26 [I,A]; C08L0067-00 [I,C*]; C08L0067-02 [I,A]; C08L0067-04 [I,A]

AB The title compns. comprise 100 parts polyesters, and 1-100 parts polyolefins which have been modified to bear glycidoxyarylmethylacrylamide groups. Mixing 4-acrylamidomethyl-2,6-dimethylphenol with epichlorohydrin in the presence of PhCH2Et3N+Cl- at 100° for 30 min, cooling to 50°, adding 5-N NaOH, and mixing at 45-50° prepared N-[4-(2,3-epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide the grafting by which of LDPE gave an modified polyolefin useful as compatible modifier for polyester.

ST glycidoxyphenylmethylacrylamide grafted polyethylene improver polyester blend; compatible improver glycidoxy acrylamide graft polyolefin; epoxy modified LDPE blend polyester

IT Polyesters, uses
RL: USES (Uses)
(blends with glycidoxybenzylacrylamide-olefin graft copolymers, compatible, for molding with good strength)

IT Plastics, molded
RL: USES (Uses)
(polyester blends with epoxy group-containing acrylamide copolyolefins, compatible, with good strength)

IT Polymerization
(graft, of polyolefins with glycidoxybenzylacrylamides, for use in polyamide blends)

IT Alkenes, polymers
RL: USES (Uses)
(α-, polymers, with ethylene, grafted, blends with polyesters, compatible, for molding with good strength)

IT 24968-12-5, PBT polymer 25038-59-9, Kurapet KL226R, uses
RL: USES (Uses)
(blends with glycidoxybenzylacrylamide-olefin graft copolymers, compatible, for molding with good strength)

IT 74-85-1D, Ethylene, polymers with α-olefin, grafted with epoxypropoxydimethylphenylmethylacrylamide 138049-71-5 138049-81-7 138230-47-4
RL: USES (Uses)
(blends with polyesters, compatible, for molding with good strength)

IT 3115-68-2, Tetrabutylphosphonium bromide
RL: CAT (Catalyst use); USES (Uses)
(catalyst, for polyester blends with epoxy group-containing acrylamide copolyolefins)

IT 99431-43-3P, N-[4-(2,3-Epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide
RL: PREP (Preparation)
(preparation and grafting polyolefin with)

IT 106-89-8, Epichlorohydrin, reactions

RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with acrylamidomethyldimethylphenol)
IT 13579-23-2, 4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with epichlorohydrin)

L27 ANSWER 7 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1993:627224 CAPLUS
DN 119:227224
OREF 119:40567a,40570a
ED Entered STN: 27 Nov 1993
TI Blended polyamide molding compositions having good compatibility and high strength
IN Deguchi, Yoshikuni; Yonezawa, Kazuya; Hamaguchi, Shigeki; Tamai, Kazuhiko
PA Kanegafuchi Kagaku Kogyo K. K., Japan
SO PCT Int. Appl., 22 pp.
CODEN: PIXXD2
DT Patent
LA Japanese
IC ICM C08L077-00
ICS C08L023-00; C08L037-00
CC 37-6 (Plastics Manufacture and Processing)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9307218	A1	19930415	WO 1991-JP1319	19911001
	W: CA, US				
	RW: BE, DE, FR, GB, IT				
	EP 559892	A1	19930915	EP 1991-917026	19911001
	R: BE, DE, FR, GB, IT				
PRAI	WO 1991-JP1319	W	19911001		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 9307218	ICM	C08L077-00
	ICS	C08L023-00; C08L037-00
	IPCI	C08L0077-00 [ICM,5]; C08L0023-00 [ICS,5]; C08L0037-00 [ICS,5]
	IPCR	C09K0003-00 [I,C*]; C09K0003-00 [I,A]; C08G0063-00 [I,C*]; C08G0063-685 [I,A]; C08G0063-91 [I,A]; C08G0065-00 [I,C*]; C08G0065-48 [I,A]; C08G0069-00 [I,C*]; C08G0069-48 [I,A]; C08G0075-00 [I,C*]; C08G0075-02 [I,A]; C08G0075-06 [I,A]; C08L0023-00 [I,C*]; C08L0023-00 [I,A]; C08L0051-00 [I,C*]; C08L0051-06 [I,A]; C08L0077-00 [I,C*]; C08L0077-00 [I,A]; C08L0077-02 [I,A]
	ECLA	C08L023/00+B4N4; C08L051/06+B4; C08L077/00+B2A1; C08L077/00+B5A; C08L077/02+B2A1; C08L077/02+B5A
EP 559892	IPCI	C08L0077-00 [ICM,5]; C08L0023-00 [ICS,5]; C08L0037-00 [ICS,5]
	IPCR	C09K0003-00 [I,C*]; C09K0003-00 [I,A]; C08G0063-00 [I,C*]; C08G0063-685 [I,A]; C08G0063-91 [I,A]; C08G0065-00 [I,C*]; C08G0065-48 [I,A]; C08G0069-00 [I,C*]; C08G0069-48 [I,A]; C08G0075-00 [I,C*]; C08G0075-02 [I,A]; C08G0075-06 [I,A]; C08L0023-00

[I,C*]; C08L0023-00 [I,A]; C08L0051-00 [I,C*];
C08L0051-06 [I,A]; C08L0077-00 [I,C*]; C08L0077-00
[I,A]; C08L0077-02 [I,A]
AB The title compns. comprise 100 parts polyamides, and 1-100 parts polyolefins which have been modified with glycidoxyarylmethylacrylamide groups. Mixing 4-acrylamidomethyl-2,6-dimethylphenol with epichlorohydrin in the presence of PhCH2Et3N+Cl- at 100° for 30 min, cooling to 50°, adding 5 N NaOH, and mixing at 45-50° prepared N-[4-(2,3-epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide the grafting by which of LDPE gave an modified polyolefin useful as compatible modifier for polyamide.
ST glycidoxyphenylmethylacrylamide grafted polyethylene improver polyamide blend; compatible improver glycidoxy acrylamide graft polyolefin; epoxy modified LDPE blend polyamide
IT Polyamides, uses
RL: USES (Uses)
(blends with epoxy group-containing acrylamide copolyolefins, compatible, for molding with good strength)
IT Plastics, molded
RL: USES (Uses)
(polyamide blends with epoxy group-containing acrylamide copolyolefins, compatible, with good strength)
IT Polymerization
(graft, of polyolefins with glycidoxybenzylacrylamides, for use in polyamide blends)
IT 25038-54-4, Amilan CM1026, uses
RL: USES (Uses)
(blends with epoxy group-containing acrylamide copolyolefins, compatible, for molding with good strength)
IT 138049-71-5 138049-81-7 138230-47-4
RL: USES (Uses)
(blends with polyamides, compatible, for molding with good strength)
IT 99431-43-3P, N-[4-(2,3-Epoxypropoxy)-3,5-dimethylphenylmethyl]acrylamide
RL: PREP (Preparation)
(preparation and grafting polyolefin with)
IT 106-89-8, Epichlorohydrin, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with acrylamidomethyldimethylphenol)
IT 13579-23-2, 4-Acrylamidomethyl-2,6-dimethylphenol
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with epichlorohydrin)

L27 ANSWER 8 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:195513 CAPLUS
DN 116:195513
OREF 116:33151a,33154a
ED Entered STN: 16 May 1992
TI Acrylamide group-containing cyclic ether copolymers
IN Deguchi, Yoshikuni; Yonezawa, Kazuya
PA Kanegafuchi Chemical Industry Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C08G065-22
ICS C08G065-22
CC 37-3 (Plastics Manufacture and Processing)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 03285914	A	19911217	JP 1990-87022	19900330
PRAI JP 1990-87022		19900330		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 03285914	ICM	C08G065-22
	ICS	C08G065-22
	IPCI	C08G0065-22 [ICM,5]; C08G0065-22 [ICS,5]; C08G0065-00 [ICS,5,C*]
	IPCR	C08G0065-00 [I,C*]; C08G0065-22 [I,A]; C08G0065-02 [I,A]

AB Three-eight-membered cyclic ethers and acrylamide group-containing cyclic ethers are copolymd. to prepared title copolymers. Thus, 4-acrylamidomethyl-2,6-dimethylphenol was reacted with epichlorohydrin to prepare N-[4-(2,3-epoxypropoxy)-2,5-dimethylphenylmethyl]acrylamide which (10 parts) was copolymd. with 100 parts propylene oxide.
ST propylene oxide epoxypropoxydimethylphenylmethylacrylamide copolymer; cyclic ether ring opening copolymer
IT Polymerization
(ring-opening, of [(epoxypropoxy)dimethylphenylmethyl]acrylamide and propylene oxide)
IT 99431-43-3P
RL: IMF (Industrial manufacture); PREP (Preparation)
(manufacture and polymerization of)
IT 140913-00-4P
RL: PREP (Preparation)
(preparation of)
IT 106-89-8, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with acrylamidomethyldimethylphenol)
IT 13579-23-2
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with epichlorohydrin)

L27 ANSWER 9 OF 9 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1992:195144 CAPLUS
DN 116:195144
OREF 116:33095a,33098a
ED Entered STN: 16 May 1992
TI Modified polyolefin polymer, production thereof, and resin composition containing the same
IN Deguchi, Yoshikuni; Yonezawa, Kazuya
PA Kanegafuchi Chemical Industry Co., Ltd., Japan
SO PCT Int. Appl., 19 pp.
CODEN: PIXXD2

DT Patent
LA Japanese
IC ICM C08F008-08
ICS C08F008-30; C08F255-00; C08F279-02; C08F220-58; C08L033-24; C08L051-00; C08F210-00; C08L023-00
CC 35-8 (Chemistry of Synthetic High Polymers)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9117192	A1	19911114	WO 1991-JP552	19910424
	W: CA, JP, US RW: BE, DE, FR, GB, IT				
	CA 2063265	A1	19911029	CA 1991-2063265	19910424
	EP 480069	A1	19920415	EP 1991-908651	19910424
	EP 480069	B1	19981223		
	R: BE, DE, FR, GB, IT				
	US 5294673	A	19940315	US 1991-778144	19911226
PRAI	JP 1990-114462	A	19900428		
	JP 1990-129473	A	19900518		
	WO 1991-JP552	W	19910424		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 9117192	ICM	C08F008-08
	ICS	C08F008-30; C08F255-00; C08F279-02; C08F220-58; C08L033-24; C08L051-00; C08F210-00; C08L023-00
	IPCI	C08F0008-08 [ICM,5]; C08F0008-30 [ICS,5]; C08F0008-00 [ICS,5,C*]; C08F0255-00 [ICS,5]; C08F0279-02 [ICS,5]; C08F0279-00 [ICS,5,C*]; C08F0220-58 [ICS,5]; C08F0220-00 [ICS,5,C*]; C08L0033-24 [ICS,5]; C08L0033-00 [ICS,5,C*]; C08L0051-00 [ICS,5]; C08F0210-00 [ICS,5]; C08L0023-00 [ICS,5]
	IPCR	C08F0008-00 [I,C*]; C08F0008-30 [I,A]; C08F0110-00 [N,C*]; C08F0110-06 [N,A]; C08F0210-00 [I,C*]; C08F0210-00 [I,A]; C08F0255-00 [I,C*]; C08F0255-00 [I,A]; C08F0277-00 [I,C*]; C08F0277-00 [I,A]; C08F0279-00 [I,C*]; C08F0279-02 [I,A]
	ECLA	C08F008/30+10/00; C08F210/00; C08F255/00+220/58; C08F277/00+220/58; C08F279/02+220/58; M08F
CA 2063265	IPCI	C08F0210-00 [ICM,5]; C08F0255-00 [ICS,5]; C08F0008-08 [ICS,5]; C08F0008-30 [ICS,5]; C08F0008-00 [ICS,5,C*]
	IPCR	C08F0008-00 [I,C*]; C08F0008-30 [I,A]; C08F0110-00 [N,C*]; C08F0110-06 [N,A]; C08F0210-00 [I,C*]; C08F0210-00 [I,A]; C08F0255-00 [I,C*]; C08F0255-00 [I,A]; C08F0277-00 [I,C*]; C08F0277-00 [I,A]; C08F0279-00 [I,C*]; C08F0279-02 [I,A]
EP 480069	IPCI	C08F0008-08 [ICM,5]; C08F0008-30 [ICS,5]; C08F0008-00 [ICS,5,C*]; C08F0255-00 [ICS,5]; C08F0279-02 [ICS,5]; C08F0279-00 [ICS,5,C*]; C08F0220-58 [ICS,5]; C08F0220-00 [ICS,5,C*]; C08L0033-24 [ICS,5]; C08L0033-00 [ICS,5,C*]; C08L0051-00 [ICS,5]; C08F0210-00 [ICS,5]; C08L0023-00 [ICS,5]
	IPCR	C08F0008-00 [I,C*]; C08F0008-30 [I,A]; C08F0110-00 [N,C*]; C08F0110-06 [N,A]; C08F0210-00 [I,C*]; C08F0210-00 [I,A]; C08F0255-00 [I,C*]; C08F0255-00

[I,A]; C08F0277-00 [I,C*]; C08F0277-00 [I,A];
C08F0279-00 [I,C*]; C08F0279-02 [I,A]
ECLA C08F008/30+10/00; C08F210/00; C08F255/00+220/58;
C08F277/00+220/58; C08F279/02+220/58
US 5294673 IPCI C08F0269-00 [ICM,5]
IPCR C08F0008-00 [I,C*]; C08F0008-30 [I,A]; C08F0110-00
[N,C*]; C08F0110-06 [N,A]; C08F0210-00 [I,C*];
C08F0210-00 [I,A]; C08F0255-00 [I,C*]; C08F0255-00
[I,A]; C08F0277-00 [I,C*]; C08F0277-00 [I,A];
C08F0279-00 [I,C*]; C08F0279-02 [I,A]
NCL 525/286.000
ECLA C08F008/30+10/00; C08F210/00; C08F255/00+220/58;
C08F277/00+220/58; C08F279/02+220/58; M08F

AB The title polymer having good mech. properties, heat resistance, dyeability, adhesive properties, coatability, etc. and good compatibility with other resins contain 1 -CH2C(R)(CONHCH2Ar)- (Ar = C6-23 aromatic hydrocarbon group containing ≥1 glycidyl group; R H, Me) unit/2-1000 olefin unit. Polypropylene 100, N-[4-(2,3-epoxypropoxy)-3,5-dimethylbenzyl]acrylamide 1, and benzoyl peroxide 0.1 part were kneaded at 200° for 5 min and washed with acetone to give modified polymer of degree of grafting 0.7%.

ST polyolefin modified heat resistance; adhesion modified polyolefin; polypropylene epoxyacrylamide modified

IT Heat-resistant materials
((glycidoxydimethylbenzyl)acrylamide-grafted polyolefins)

IT Adhesives
((glycidoxydimethylbenzyl)acrylamide-grafted polyolefins, for aluminum)

IT Rubber, butyl, preparation
RL: PREP (Preparation)
((glycidoxydimethylbenzyl)acrylamide-grafted, manufacture of, with good heat resistance and adhesive properties)

IT Rubber, synthetic
RL: PREP (Preparation)
(dicyclopentadiene-ethylene-propene, (glycidoxydimethylbenzyl)acrylamid e-grafted, manufacture of, with good heat resistance and adhesive properties)

IT Rubber, synthetic
RL: PREP (Preparation)
(ethylene-ethylidenenorbornene-propene, (glycidoxydimethylbenzyl)acryla mide-grafted, manufacture of, with good heat resistance and adhesive properties)

IT Polymerization
(graft, of polyolefins, with (glycidoxydimethylbenzyl)acrylamide)

IT Rubber, butadiene, preparation
RL: PREP (Preparation)
(of 1,2-configuration, (glycidoxydimethylbenzyl)acrylamide-grafted, manufacture of, with good heat resistance and adhesive properties)

IT 7429-90-5, Aluminum, miscellaneous
RL: MSC (Miscellaneous)
(adhesives for, (glycidoxydimethylbenzyl)acrylamide-grafted polyolefins

as)
IT 99431-43-3P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation);
RACT
(Reactant or reagent)
(manufacture and graft polymerization of)
IT 138049-71-5P 138049-81-7P 140681-96-5P 140681-97-6P 140681-98-7P
140701-92-4P
RL: IMF (Industrial manufacture); PREP (Preparation)
(manufacture of, with good heat resistance and adhesive properties)
IT 106-89-8, Epichlorohydrin, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with acrylamidomethyldimethylphenol)
IT 13579-23-2
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with epichlorohydrin)
IT 9010-85-9P
RL: PREP (Preparation)
(rubber, (glycidoxydimethylbenzyl)acrylamide-grafted, manufacture of,
with
good heat resistance and adhesive properties)
IT 9003-17-2P
RL: PREP (Preparation)
(rubber, of 1,2-configuration, (glycidoxydimethylbenzyl)acrylamide-
grafted, manufacture of, with good heat resistance and adhesive
properties)

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FULL ESTIMATED COST 37.23 219.61

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS) SINCE FILE ENTRY TOTAL SESSION
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DICTIONARY FILE UPDATES: 8 SEP 2008 HIGHEST RN 1047724-15-1

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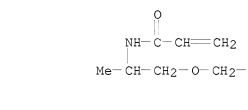
=> s c13h17no2/mf
L28 5280 C13H17NO2/MF

=> s l28 and acrylamide
18439 ACRYLAMIDE
L29 3 L28 AND ACRYLAMIDE

=> d 1-3

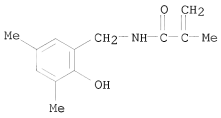
L29 ANSWER 1 OF 3 REGISTRY COPYRIGHT 2008 ACS on STN
RN 727654-92-4 REGISTRY
ED Entered STN: 17 Aug 2004
CN 2-Propenamide, N-[1-methyl-2-(phenylmethoxy)ethyl]- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-[2-(benzyloxy)-1-methylethyl]- (5CI)
MF C13 H17 N O2
SR CAS EARLY REGISTRATIONS
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

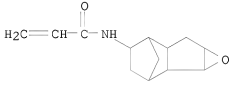
L29 ANSWER 2 OF 3 REGISTRY COPYRIGHT 2008 ACS on STN
RN 13579-40-3 REGISTRY
ED Entered STN: 16 Nov 1984
CN 2-Propenamide, N-[(2-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl- (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN Acrylamide, N-(3,5-dimethylsalicyl)-2-methyl- (8CI)
MF C13 H17 N O2
CI COM
LC STN Files: BEILSTEIN*, CA, CAPLUS, IFICDB, IFIPAT, IFIUDB, USPATFULL
(*File contains numerically searchable property data)



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

2 REFERENCES IN FILE CA (1907 TO DATE)
2 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L29 ANSWER 3 OF 3 REGISTRY COPYRIGHT 2008 ACS on STN
RN 7534-87-4 REGISTRY
ED Entered STN: 16 Nov 1984
CN Acrylamide, N-(1,2-epoxyhexahydro-4,7-methanoindan-5-yl)- (7CI, 8CI) (CA INDEX NAME)
MF C13 H17 N O2
LC STN Files: CA, CAOLD, CAPLUS, USPATOLD



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)
1 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> s 13579-40-3
L30 1 13579-40-3
(13579-40-3/RN)

=> s 13579-40-3/crn
L31 1 13579-40-3/CRN

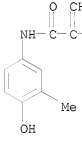
=> d

L31 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2008 ACS on STN
RN 149787-60-0 REGISTRY
ED Entered STN: 04 Sep 1993
CN Carbonic acid, 1,1-dimethylethyl 2-methyl-4-[[(2-methyl-1-oxo-2-

propenyl)amino]methyl]phenyl ester, polymer with 1,1-dimethylethyl 2-methyl-6-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate, N-[(2-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-2-propenamide and N-(4-hydroxy-3-methylphenyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 2-Propenamide, N-(4-hydroxy-3-methylphenyl)-2-methyl-, polymer with 1,1-dimethylethyl 2-methyl-4-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate, 1,1-dimethylethyl 2-methyl-6-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate and N-[(2-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-2-propenamide (9CI)
CN 2-Propenamide, N-[(2-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-, polymer with 1,1-dimethylethyl 2-methyl-4-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate, 1,1-dimethylethyl 2-methyl-6-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate and N-(4-hydroxy-3-methylphenyl)-2-methyl-2-propenamide (9CI)
CN Carbonic acid, 1,1-dimethylethyl 2-methyl-6-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl ester, polymer with 1,1-dimethylethyl 2-methyl-4-[[(2-methyl-1-oxo-2-propenyl)amino]methyl]phenyl carbonate, N-[(2-hydroxy-3,5-dimethylphenyl)methyl]-2-methyl-2-propenamide and N-(4-hydroxy-3-methylphenyl)-2-methyl-2-propenamide (9CI)
MF (C17 H23 N O4 . C17 H23 N O4 . C13 H17 N O2 . C11 H13 N O2)x
CI PMS
PCT Polyacrylic
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

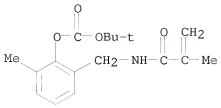
CM 1

CRN 149787-58-6
CMF C11 H13 N O2



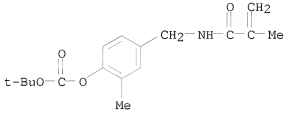
CM 2

CRN 149450-99-7
CMF C17 H23 N O4



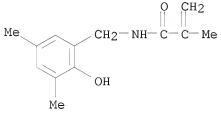
CM 3

CRN 149450-98-6
CMF C17 H23 N O4



CM 4

CRN 13579-40-3
CMF C13 H17 N O2



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> file caplus

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	19.22	238.83

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION

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FILE COVERS 1907 - 9 Sep 2008 VOL 149 ISS 11
FILE LAST UPDATED: 8 Sep 2008 (20080908/ED)

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http://www.cas.org/legal/infopolicy.html

=> d his

(FILE 'HOME' ENTERED AT 17:01:43 ON 09 SEP 2008)

FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1 4064 S C11H13NO2/MF
L2 5 S L1 AND ACRYLAMIDE
L3 0 S HYDROXYBENZYLACRYLAMIDE
L4 26 S HYDROXYBENZYL AND ACRYLAMIDE
L5 24 S L4 NOT CHLORO
L6 15 S L5 NOT TERT
L7 0 S 13560-55-9/CRN

FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8 13 S L6
L9 4 S L8 AND PHOTO?

FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008
L10 1 S 13560-56-0
L11 1 S 23281-77-8
L12 1 S 849686-90-4
L13 1 S 104835-82-7
L14 16 S 104835-82-7/CRN
L15 0 S 849686-90-4/CRN
L16 2 S 23281-77-8/CRN

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L17           16 S L10 OR L11 OR L12 OR L13 OR L14 OR L16
L18           14 S L17 NOT L9

     FILE 'REGISTRY' ENTERED AT 17:11:07 ON 09 SEP 2008
L19         4952 S C12H15NO2/MF
L20            5 S L19 AND ACRYLAMIDE
L21            2 S  13579-23-2 OR 14800-18-1
L22           16 S  13579-23-2/CRN OR 14800-18-1/CRN

     FILE 'CAPLUS' ENTERED AT 17:13:10 ON 09 SEP 2008
L23           34 S L21 OR L22
L24           26 S L23 NOT L9 NOT L22
L25            0 S L24 AND PHOTO?
L26            0 S L24 AND NEGATIV?
L27            9 S L24 AND POLYMERIZ?

     FILE 'REGISTRY' ENTERED AT 17:14:45 ON 09 SEP 2008
L28         5280 S C13H17NO2/MF
L29            3 S L28 AND ACRYLAMIDE
L30            1 S 13579-40-3
L31            1 S 13579-40-3/CRN

     FILE 'CAPLUS' ENTERED AT 17:15:54 ON 09 SEP 2008

=> s l30 or l31
               2 L30
               1 L31
L32            2 L30 OR L31

=> d all 1-2

L32  ANSWER 1 OF 2  CAPLUS  COPYRIGHT 2008 ACS on STN
AN   1993:549504  CAPLUS
DN   119:149504
OREF 119:26551a,26554a
ED   Entered STN:  02 Oct 1993
TI   Photosensitive composition with polymeric binder comprising alpha-beta
     unsaturated carboxylic acid residue
IN   Roeschert, Horst; Pawlowski, Georg; Przybilla, Klaus Juergen
PA   Hoechst A.-G., Germany
SO   Ger. Offen., 10 pp.
     CODEN: GWXXBX
DT   Patent
LA   German
IC   ICM  C07C233-20
     ICS  C08F020-58; C07F007-18; C07D307-20; C07D309-10; G03F007-004;
          H01L021-312
CC   74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
     Reprographic Processes)
     Section cross-reference(s): 35
FAN.CNT 1
     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
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PI   DE 4126409           A1    19930211    DE 1991-4126409        19910809
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EP 528203	A1	19930224	EP 1992-112588		19920723
EP 528203	B1	19951011			
R: BE, CH, DE, FR, GB, IT, LI					
US 5328973	A	19940712	US 1992-922507		19920731
JP 05255216	A	19931005	JP 1992-234193		19920810

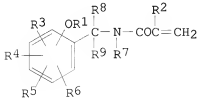
PRAI DE 1991-4126409 A 19910809

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
DE 4126409	ICM	C07C233-20
	ICS	C08F020-58; C07F007-18; C07D307-20; C07D309-10; G03F007-004; H01L021-312
	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]; C08F0020-58 [ICS,5]; C08F0020-00 [ICS,5,C*]; C07F0007-18 [ICS,5]; C07F0007-00 [ICS,5,C*]; C07D0307-20 [ICS,5]; C07D0307-00 [ICS,5,C*]; C07D0309-10 [ICS,5]; C07D0309-00 [ICS,5,C*]; G03F0007-004 [ICS,5]; H01L0021-312 [ICS,5]; H01L0021-02 [ICS,5,C*]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
EP 528203	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]; C08F0020-58 [ICS,5]; C08F0020-00 [ICS,5,C*]; G03F0007-039 [ICS,5]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]
	ECLA	C07C233/20; C08F020/58; G03F007/039
US 5328973	IPCI	C08F0020-60 [ICM,5]; C08F0020-00 [ICM,5,C*]; C08F0024-00 [ICS,5]; C08F0030-08 [ICS,5]; C08F0030-00 [ICS,5,C*]
	NCL	526/262.000; 430/270.100; 430/906.000; 430/910.000; 526/266.000; 526/270.000; 526/279.000; 526/292.500; 526/292.900; 526/298.000; 526/304.000
	ECLA	C07C233/20; C08F020/58; G03F007/039
JP 05255216	IPCI	C07C0233-20 [ICM,5]; C07C0233-00 [ICM,5,C*]
	IPCR	C07C0233-00 [I,C*]; C07C0233-20 [I,A]; C08F0020-00 [I,C*]; C08F0020-58 [I,A]; G03F0007-039 [I,C*]; G03F0007-039 [I,A]

OS MARPAT 119:149504

GI



I

AB The compds. I [R1 = acid-splittable group; R2 = alkyl, H, halogen, CN; R3-R6 = aliphatic, aromatic, araliph., halogen, OH, H; R7 = H, alkyl; R8, R9 = H, alkyl, aryl], the polymers containing ≥10 mol% of I, and photosensitive compns. containing the polymer are claimed. The composition is useful for resist material for deep-UV lithog.
ST acrylamide polymer photosensitive compn photoresist; lithog deep UV resist
acrylamide
IT Resists
(photo-, deep-UV, acrylamide polymers for)
IT Lithography
(photo-, UV, light-sensitive compns. containing acrylamide polymers for)
IT 13560-56-0P 13579-40-3P 104835-82-7P 149450-93-1P
149450-94-2P 149450-95-3P 149450-96-4P 149450-97-5P 149450-98-6P
149450-99-7P 149451-00-3P 149451-01-4P 149451-02-5P 149451-03-6P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation and reaction of, polymer binder for photosensitive composition from)
IT 149787-50-8P 149787-51-9P 149787-52-0P 149787-53-1P 149787-54-2P
149787-55-3P 149787-56-4P 149787-57-5P 149787-60-0P
149787-61-1P 149826-03-9P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, in photosensitive composition)

L32 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2008 ACS on STN
AN 1967:85610 CAPLUS
DN 66:85610
OREF 66:16015a
ED Entered STN: 12 May 1984
TI Benzylamides of unsaturated acids and polymers therefrom
PA CIBA Ltd.
SO Neth. Appl., 24 pp.
CODEN: NAXXAN
DT Patent
LA Dutch
IC C07C
CC 25 (Noncondensed Aromatic Compounds)
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	NL 6604304		19661003	NL 1966-4304	19660331
	CH 476689			CH	
	DE 1568261			DE	
	DE 1793113			DE	
	FR 1475097			FR	
	GB 1134341			GB	
	US 3627831		19711214	US	19690325
PRAI	CH		19650401		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
NL 6604304	IC	C07C
	IPCI	C07C
	IPCR	C08F0020-00 [I,C*]; C08F0020-54 [I,A]; C08F0028-00 [I,C*]; C08F0028-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-02 [I,A]
US 3627831	IPCR	C08F0020-00 [I,C*]; C08F0020-54 [I,A]; C08F0028-00 [I,C*]; C08F0028-00 [I,A]; C08L0007-00 [I,C*]; C08L0007-00 [I,A]; C08L0023-00 [I,C*]; C08L0023-02 [I,A]
	NCL	564/207.000; 524/217.000; 524/220.000; 524/222.000; 524/721.000; 524/723.000; 524/728.000; 525/119.000; 526/280.000; 526/304.000; 526/313.000; 544/216.000; 562/451.000; 564/153.000; 564/154.000; 564/158.000

GI For diagram(s), see printed CA Issue.

AB The title compds. are prepared by treating N-methylolamides of unsatd. carboxylic acids with phenols in an acidic medium. RCONHCH2X, where R is an alkenyl group and X is a phenolic hydroxyaryl group, are formed. If X has bacteriostatic or antioxidant properties, polymers or copolymers with corresponding properties can be obtained. For example, CH2:CHCONHCH2OH 10.1, 2-hydroxynaphthalene 14.3, and thiodiphenylamine 0.1 part were dissolved in 60 vols. absolute EtOH and 6 vols. 37% HCl were added. After 30 hrs., the reaction mixture was poured into 600 vols. H2O to give 86% N-(2-hydroxynaphthylmethyl)acrylamide (I), m. 148°. Also prepared were (compound, yield, and m.p. given): N-(2-hydroxy-3,5-dimethylbenzyl)acrylamide, 59, 155°; N-(4-hydroxy-3,5-dimethylbenzyl)acrylamide, 52, 142°; N-(2-hydroxy-3-methyl-5-tert-butylbenzyl)acrylamide, 19, 160°; N-(2-hydroxy-5-chlorobenzyl)acrylamide, 60, 126°; 2,4-bis(acrylamidomethyl)-6-chlorophenol, 158°; N-(2-hydroxy-4-methyl-5-chlorobenzyl)acrylamide and 2,6-bis(acrylamidomethyl)-3-methyl-4-chlorophenol, 183° and 190°; N-(2-hydroxy-5-nitrobenzylacrylamide, 61, 160°; N-(4-hydroxy-3,5-di-tert-butylbenzyl)acrylamide and N-(4-hydroxy-3,5-di-tert-butylbenzyl)methacrylamide, 94 and 88, 113° and 126°; N-(2-hydroxy-3-methyl-5-chlorobenzyl)acrylamide, 48, 139°; N-(2-hydroxy-3-isopropyl-5-chloro-6-methylbenzyl)acrylamide, 87, 150°; N-(2-hydroxy-3-nitro-5-chlorobenzyl)acrylamide, 73, 150°; N-(2-hydroxy-3-methylthio-5-methylbenzyl)acrylamide and 2-methylthio-3,6-bis(acrylamidomethyl)-4-methylphenol, 147° and 224°; N-[2-hydroxy-3-methyl-5-(methylthio)benzyl]acrylamide, 34, 146°; 5-(acrylamidomethyl)salicylic acid 10, 162°; N-(2,4-dihydroxy-5-chlorobenzyl)acrylamide, 10, 187°; N-(2-hydroxy-3,5-dimethylbenzylmethacrylamide 44, 110°; and N-(2-methoxy-5-nitrobenzyl)acrylamide 82, 183-4°. Copolymers of the above compds. with styrene, Me, Bu, lauryl, and stearyl methacrylates, acrylamide acrylonitrile, acrylic acid, and CH2:CCl2 were prepared by free radical polymerization

IT 13560-54-8P 13579-22-1P 13579-23-2P 13579-30-1P 13579-32-3P 13579-37-8P 13579-40-3P 14800-18-1P 15252-50-3P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT

(Reactant or reagent)
(preparation and polymerization of)
IT 13579-24-3P 13579-25-4P 13579-26-5P 13579-27-6P 13579-28-7P
13579-29-8P 13579-33-4P 13579-34-5P 13579-35-6P 13579-36-7P
13579-38-9P 13579-39-0P
RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation of)

=> d his

(FILE 'HOME' ENTERED AT 17:01:43 ON 09 SEP 2008)

FILE 'REGISTRY' ENTERED AT 17:01:55 ON 09 SEP 2008
L1 4064 S C11H13NO2/MF
L2 5 S L1 AND ACRYLAMIDE
L3 0 S HYDROXYBENZYLACRYLAMIDE
L4 26 S HYDROXYBENZYL AND ACRYLAMIDE
L5 24 S L4 NOT CHLORO
L6 15 S L5 NOT TERT
L7 0 S 13560-55-9/CRN

FILE 'CAPLUS' ENTERED AT 17:04:50 ON 09 SEP 2008
L8 13 S L6
L9 4 S L8 AND PHOTO?

FILE 'REGISTRY' ENTERED AT 17:05:50 ON 09 SEP 2008
L10 1 S 13560-56-0
L11 1 S 23281-77-8
L12 1 S 849686-90-4
L13 1 S 104835-82-7
L14 16 S 104835-82-7/CRN
L15 0 S 849686-90-4/CRN
L16 2 S 23281-77-8/CRN

FILE 'CAPLUS' ENTERED AT 17:09:35 ON 09 SEP 2008
L17 16 S L10 OR L11 OR L12 OR L13 OR L14 OR L16
L18 14 S L17 NOT L9

FILE 'REGISTRY' ENTERED AT 17:11:07 ON 09 SEP 2008
L19 4952 S C12H15NO2/MF
L20 5 S L19 AND ACRYLAMIDE
L21 2 S 13579-23-2 OR 14800-18-1
L22 16 S 13579-23-2/CRN OR 14800-18-1/CRN

FILE 'CAPLUS' ENTERED AT 17:13:10 ON 09 SEP 2008
L23 34 S L21 OR L22
L24 26 S L23 NOT L9 NOT L22
L25 0 S L24 AND PHOTO?
L26 0 S L24 AND NEGATIV?
L27 9 S L24 AND POLYMERIZ?

FILE 'REGISTRY' ENTERED AT 17:14:45 ON 09 SEP 2008
L28 5280 S C13H17NO2/MF
L29 3 S L28 AND ACRYLAMIDE

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L30             1 S 13579-40-3
L31             1 S 13579-40-3/CRN

     FILE 'CAPLUS' ENTERED AT 17:15:54 ON 09 SEP 2008
L32             2 S L30 OR L31

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FULL ESTIMATED COST                                 7.02     245.85

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)      SINCE FILE      TOTAL
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STRUCTURE FILE UPDATES:    8 SEP 2008  HIGHEST RN 1047724-15-1
DICTIONARY FILE UPDATES:   8 SEP 2008  HIGHEST RN 1047724-15-1

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on property searching in REGISTRY, refer to:

http://www.cas.org/support/stngen/stndoc/properties.html

=> log y
COST IN U.S. DOLLARS                            SINCE FILE      TOTAL
                                                   ENTRY    SESSION
FULL ESTIMATED COST                                 0.46     246.31

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)      SINCE FILE      TOTAL
                                                   ENTRY    SESSION
CA SUBSCRIBER PRICE                                 0.00     -23.20

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